

Strategies to Enhance the Charge Dynamics of Bismuth Vanadate

For Photocatalytic Water Oxidation

by

Umesh Prasad

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Graduate Supervisory Committee:

Arunachala Mada Kannan, Chair
Bruno Azeredo
Candace Chan
Sergio Garcia Segura

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ABSTRACT

Hydrogen is considered one of the most potential fuels due to its highest gravimetric energy density with no pollutant emission during the energy cycle. Among several techniques for hydrogen generation, the promising photoelectrochemical water oxidation is considered a long-term solar pathway by splitting water. The system contains a photoanode and a cathode immersed in an aqueous electrolyte where charge separation takes place in the bulk of the semiconducting material on light absorption, leading to water oxidation/reduction at the surface of the photoelectrodes/cathode.

It is imperative to develop materials that demonstrate high light absorption in the wide spectrum along with photoelectrochemical stability. N-type Monoclinic scheelite bismuth vanadate (BiVO_4) is selected due to its incredible light absorption capabilities, direct bandgap ($E_g \sim 2.4\text{-}2.5\text{ eV}$) and relatively better photoelectrochemical stability. However, BiVO_4 encounters huge electron-hole recombination due to smaller diffusion lengths and positive conduction bands that cause slow charge dynamics and sluggish water oxidation kinetics.

In order to improve the illustrated drawbacks, four strategies were discussed. Chapter 1 describe the fundamental understanding of photoelectrochemical cell and BiVO_4 . Chapter 2 illustrates details of the experimental procedure and state-of-the-art material characterization. Chapter 3 provide the impact of alkali metal placement in the crystal structure of BiVO_4 systematically that exhibited ~ 20 times more performance than intrinsic BiVO_4 , almost complete bulk charge separation and enhancement in the diffusion length. Detailed characterization determined that the alkali metal getting placed

in the interstitial void of BiVO₄ lattice and multiple interbands formation enhanced the charge dynamics.

Chapter 4 contains stoichiometric doping of Y³⁺ or Er³⁺ or Yb³⁺ at the Bi³⁺ site, leading to an extended absorption region, whereas non-stoichiometric W⁶⁺ doping at the V⁵⁺ site minimizes defects and increased charge carriers. To further enhance the performance, type-II heterojunction with WO₃ along *p-n* junction with Fe:NiO enhance light absorption and charge dynamics close to the theoretical performance.

Chapter 5 provides a comprehensive study of a uniquely developed sulfur modified Bi₂O₃ interface layer to facilitate charge dynamics and carrier lifetime improvement by effectively passivating the WO₃/BiVO₄ heterojunction interface. Finally, chapter 6 summarized the major findings, conclusion and outlook in developing BiVO₄ as an efficient photoanode material.

This dissertation is dedicated to my father, Shivpujan Seth, mother, Malti Devi, who always taught me to work hard and be honest towards my dream. In addition, my sister, Urmila Devi and brother, Ramesh Prasad, provided immense support, encouragement and always motivated me to pursue my dreams.

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CHAPTER 1 INTRODUCTION

1.1 Background

The rise in the economy and population led to a rapid increase in the total energy demand globally. In the current scenario, most of the energy supplies (>80%) come from non-renewable energy sources^{1,2}. However, the energy and environmental issues associated with non-renewable energy remain a significant challenge. Among the sustainable energy sources, solar energy is inexhaustible, with the highest potential and a ubiquitous energy resource^{3,4}. It can generate up to 30 TW of power only by using 0.8% of the land surface on earth with 10% efficient solar cell⁵. The drawback of this energy is intermittency due to the day/night cycle, presence of clouds, and change in weather^{1,5}. The proposed solution is to store solar energy for such intermittency, but it is exhaustible to store such vast energy. A possible system is grid-based energy storage in the form of a smart grid, however, at some point, the capacity of the grid system will be exceeded⁶, and alternative large-scale energy storage solutions need to be implemented.

There is no doubt that the sun is a major source of renewable energy, but a certain issue is an intermittency. The sun energy mostly depends on the day/night cycle, cloud and geographical location. Also, solar energy is relatively hard to extract in the form of fuel compared to fossil fuels, making it economically challenging to capture. In order to deal with such intermittency and complicity, electricity network operators might implement grid-based energy storage in the form of a smart grid. However, grid-based storage capacities may be exceeded, and more efficient large-scale energy storage solutions must be implemented. Another alternative possibility is to store solar energy in the form of chemical fuel. From Figure 1, many storage devices such as mechanical (compressed air,

pump water uphill), fuels (coal, wood, gasoline, diesel, methanol, natural gases and hydrogen), capacitors (supercapacitors and ultracapacitors) and batteries (Li-ion, Ni-Cd and Pd-acid) provide an effective way of energy storage⁷. However, among the suggested storage devices, battery, capacitors and fuel provide the most effective way of storing the energy with 2-3 orders of magnitude higher energy density because the energy is stored in the form of the smallest possible configuration: chemical bonds. This suggests that storing energy in the form of chemical fuels is one of the best possible ways. As depicted from the table, chemical fuels such as methanol, methane, diesel, and gasoline need a source of carbon in their synthesis, which is concerned with the environmental concern as discussed earlier.

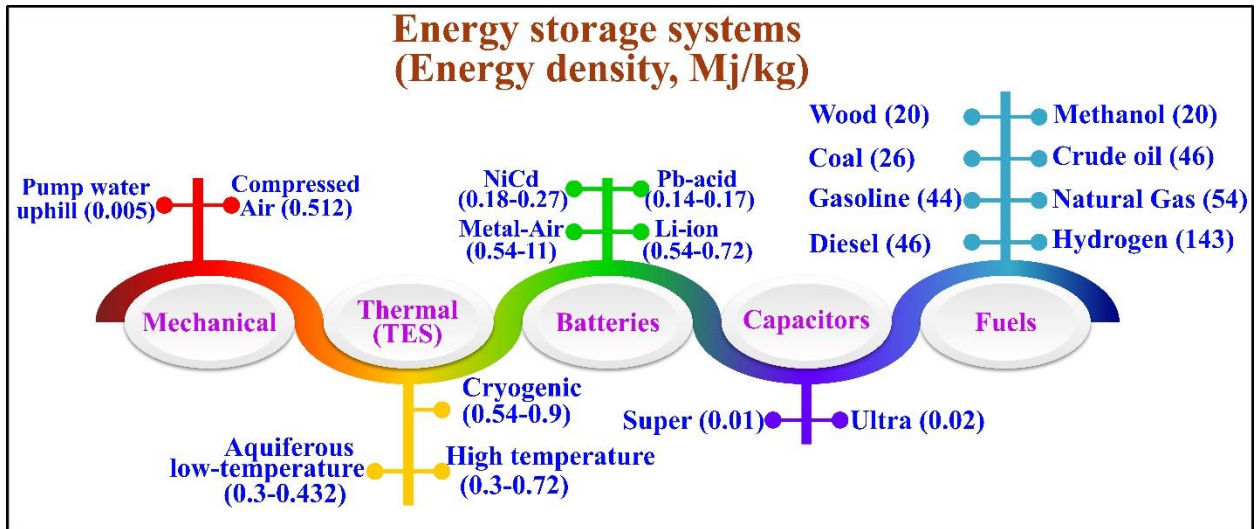


Figure 1 Various mechanical, thermal, batteries, capacitor and fuels energy storage systems.

A highly desirable approach is to store solar energy in the form of chemical fuels (hydrogen, methane, methanol, gasoline, and diesel), which has energy storage density (2-

3 order of magnitude) compared to mechanical systems and batteries⁸. Among the chemical fuels, hydrogen is without the source of carbon⁹. Converting solar energy into hydrogen is considered a highly desirable approach. Hydrogen production via water splitting is one of the most promising ways, and it is known as the "holy grail", convert solar energy directly into green storable chemical energy¹⁰. In contrast, there are many possible pathways for converting water and sunlight into hydrogen. Photoelectrochemical (PEC) water splitting is one of the most promising in complex routes because of the ease of collecting generated gasses at the convenient pressure-temperature operating window. The department of energy has projected PEC as a long-term goal for hydrogen generation through water splitting, as shown in Figure 2. The technology for indirect PEC water splitting using coupled photovoltaic (PV) and electrolyze systems is already commercially available, showing a solar-to-hydrogen (STH) efficiency of around 8%. However, direct PEC water splitting—this process will be discussed in the next section—offers three important advantages. First, a much lower overpotential is needed due to the 50-100 times lower operating current density of the direct PEC water splitting that relaxes the condition of the catalytic step in the process. Second, in order to achieve the potential needed for the electrolyzer (~1.9V), three (or more) PV cells are normally used in series. As a result, a larger area is needed to achieve the same current density, which is not the case for direct PEC water splitting. Finally, a direct PEC water splitting system requires fewer additional components (wires, frames, glass, etc.) than a combination of PV plus electrolysis since one can construct a monolithic device that may lead to a significantly lower balance-of-system cost for producing hydrogen. Coupled PV-electrolyzer is estimated to produce hydrogen at the cost exceeding US\$ 8/kg, while a reasonable estimate of the direct PEC

water splitting shows a cost in the range of US\$ 3-5/kg, compares very well with the US\$ 2-4/kg target that is set by the US Department of Energy (DOE), and the EU's 5 €/kg H₂ target for future hydrogen production pathways.

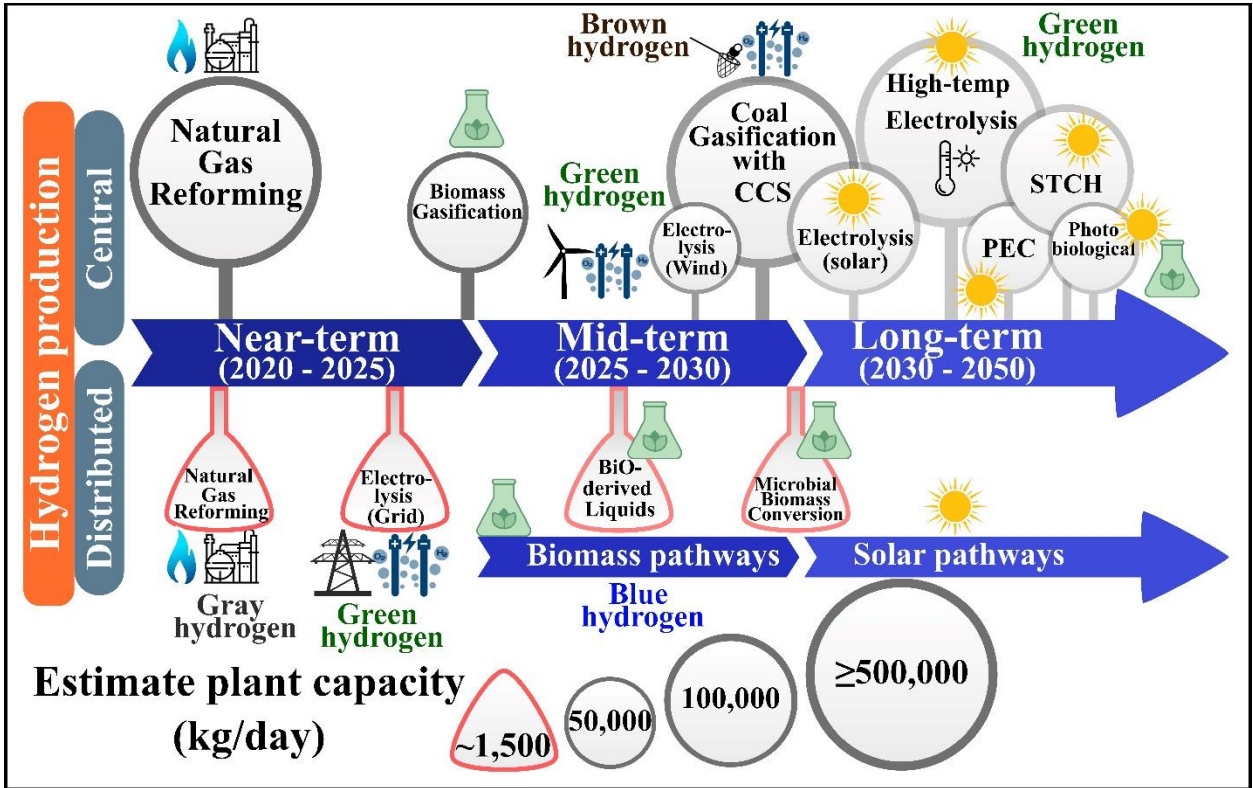


Figure 2 Time frame and production scale of hydrogen generation pathways with near, mid and long-term as per department of energy

1.2 The Photoelectrochemical Water Splitting

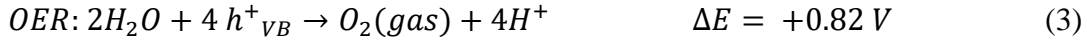
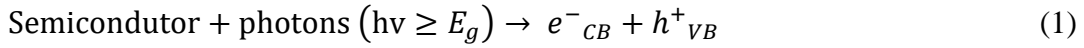
The photoelectrochemical (PEC) water splitting is the most promising long term approach for hydrogen generation, which involves capturing ambient sunlight and converting the electromagnetic energy directly into chemical energy in the form of chemical bonds^{11,12}.

PEC cell contains a semiconducting photoanode and photocathode immersed in an aqueous electrolyte, charge separation take place in the bulk of the semiconducting material on light absorption that leads to water oxidation/reduction at the surface of the photoelectrodes. The system is attractive and has multiple advantages as it can be carried out at room temperature, much lower overpotential required, no need for large-scale solar concentration, and the device can be constructed entirely by using inorganic materials. However, water oxidation is challenging despite being the most abundant electron donor because it involves four-electrons and four-protons processes that need significant overpotential due to high electrons and holes recombination and kinetic barriers^{13,14}.

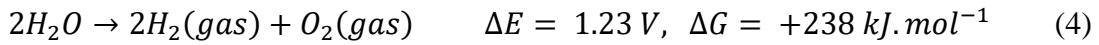
1.3 Fundamentals of Photoelectrochemical Solar Water Splitting

The simplified diagram for the PEC water splitting is given in Figure 3a. The prime components of the PEC cell are semiconductor, which works as a photoanode, aqueous electrolyte, membrane and metal as a counter electrode. When light photons, with higher energies than bandgap (E_g) of the semiconductor, incident on the surface of photoanode, electron and hole pairs generate in the bulk of the semiconducting material (eq 1) and get separated due to the presence of electric field inside the semiconductor after applying small external bias through the power supply unit (PSU)^{15,16}. The electrons excite from occupied VB to unoccupied CB band, are swept away towards the charge collector, and transported to the metal counter electrode for water reduction to form hydrogen gas (HER) (eq 2)⁴. On the other hand, photogenerated holes in the VB swept towards the photoanode surface/electrolyte interface for water oxidation to form oxygen gas (OER) (eq 3)¹¹. The OER reaction is essential for achieving high water splitting as it generates protons (H^+) and

electrons for the water-splitting process. The photoanode and counter electrode are separated by a thin membrane, which avoids mixing evolving hydrogen and oxygen gases at the respective electrodes.



Overall:



Thermodynamically, the eq 4 is an uphill reaction because of a higher positive change in Gibbs free energy ($\Delta G +238 \text{ kJ mol}^{-1}$). Furthermore, it can be observed from eqn 2 and 3 that the bottom of the CB edge must be located lower than the reduction potential (H^+/H_2) -0.41 eV and the top of the VB edge must be exceeded the oxidation potential ($\text{H}_2\text{O}/\text{O}_2$) 0.82 eV for efficient overall water splitting¹⁷. Therefore, the required bandgap energy (E_g) of a semiconducting material should be at least 1.23 eV to split water into H_2 and O_2 . Additionally, kinetic overpotentials are required to drive the HER and OER reactions due to the energy losses. Thus, the required E_g of semiconducting material should be from 1.5 to 2.5 eV per electron-hole pair generation to account for these losses¹⁴.

The CB edge of the semiconducting materials varies with pH in the linear relationship as per the Nernstian relation, as given in eq 5^{18,19}. At room temperature and atmospheric pressure, the change in CB edge is 59 mV per pH unit.

$$E_{CB} = E_{CB}^0(pH = 0) - 0.059 pH \quad (5)$$

The redox potential of water also changes as per the Nernstian equation with a change of 59 mV per pH, which makes no change in the overpotential of photogenerated electron-hole pairs for water redox potential at different pH^{20,21}.

The interface mechanism started on the relative positions of fermi levels when a semiconductor and redox electrolyte were brought into contact. Figure 3b shows a PEC cell before the equilibrium process where an n-type semiconductor is ohmically connected with the metal counter electrode and both electrodes are immersed in the electrolyte. After establishing contact between semiconductor and counter electrode, a net flow of charge starts flowing through the interfaces until the chemical potential of electrons reaches equilibrium with the semiconductor, redox electrolyte and metal counter electrode²². The chemical potential of electrons is determined by the fermi level of semiconductor (E_F), whereas the redox potential of electrolyte (E_{redox}) is determined by the redox couples present in the electrolyte²³. When the Fermi level of an n-type semiconductor lies higher, the redox potential of electrolyte, electrons start flowing from semiconductor to electrolyte via a counter electrode, as shown in Figure 3c. This flow of electrons leads to forming a depletion layer or space charge layer (W_{SC}) towards the semiconductor at the semiconductor surface/electrolyte interface²⁴ (shown in Figure 3c). Another layer generated in the electrolyte is similar to the space charge layer but opposite in the Helmholtz layer (HL) sign. This layer is composed of absorbed ions from electrolytes,

extend in the length of a few angstrom²², as indicated in Figure 3c. The positive ions (holes) build a positive space charge layer, and an internal electric field causes the bend in the CB and VB edges of the semiconductor.

Similarly, in the case of a p-type semiconductor, where the Fermi level lies below the redox potential of electrolyte, holes start flowing into electrolyte via the counter electrode and remaining electrons in the semiconductor build a negative space charge layer, and the internal electric field causes the bends down in the CB and VB edges of the semiconductor. The band bending, V_B , acts like a potential barrier against electrons flow (n-type semiconductor) or holes transfer (p-type semiconductor), known as Schottky-Barrier. As the majority of charge carriers depleted due to Schottky Barriers, the space charge layer grows to angstroms to microns range. Thus, total band bending is the difference between fermi levels of semiconductor and redox potential of electrolyte²⁵.

However, Schottky Barriers generated due to the band bending can be flattened after applying an external bias (E_{ext}), known as flat-band (U_{fb}) potential, which defines the thermodynamic ability of a semiconductor to oxidize/reduce water under illumination. Correspondingly, It determines the fermi levels position, charge carrier density, position of VB and CB edges of semiconductor with respect to reference electrode before equilibrium²³. On the other hand, the net flow of charge occurs at the metal electrode/electrolyte interface to equilibrate the fermi level of metal with electrolyte (E_{redox}) that led to minimizing W_{SC} due to the high concentration of free electrons in the metal⁵. Therefore, the barrier height determined by the energy difference between E_{redox} and the bottom of the CB edge at the equilibrium condition in the semiconductor defines the

maximum possible energy of the photogenerated electron-hole pairs in the semiconductor²⁵.

Under light illumination, photons with higher energy than the bandgap of a semiconductor get absorbed, generating electron-hole pairs as schematically represented in Figure 3d. The photogenerated electron-hole pairs get physically separated by internal electric field⁵, where electrons travel to the counter electrode via an external circuit to drive the reduction reaction and holes travel to the surface of the semiconductor and inject into the electrolyte to perform the oxidation reaction. As a result, a photovoltage (V_{ph}) generates between the semiconductor and metal counter electrode, equivalent to the difference between the semiconductor and the redox potential of electrolyte²³. The photovoltage raised the fermi level of semiconductor E_F by V_{ph} ²². The maximum possible Fermi level is equivalent to the U_{fb} , and split into two quasi-fermi levels, $E_{F,n}$ and $E_{F,p}$ on light illumination for electrons and holes respectively⁵ represented in Figure 3d.

As illustrated in Figure 3e, the oxidation and reduction process required an external bias potential ϕ_{ox} and ϕ_{Red} , respectively. Even though the illumination intensity is enough to flatten the bands, the hydrogen reduction reaction is not possible as the Fermi level is below the hydrogen reduction potential²⁵. The external bias (E_{ext}) raised the fermi level and provided overvoltage to the counter electrode¹⁶, as shown in Figure 3e. If the external bias is more negative for n-type semiconductors from equilibrium value, the band bending decreases and electrons start moving from CB to electrolyte via external contact²¹. In addition, the external bias raises the band bending for effective electron-hole pairs separation²⁵. However, with a more positive bias, the Schottky Barrier becomes bigger,

limiting the flow of electrons. Therefore the junction behaves similarly to Schottky Diode, blocking the flow of current in one direction^{18,23}.

The most critical parameters in the PEC cell are the light absorption, charge carriers transfer through the semiconductor (bulk) and across the semiconductor surface/electrolyte interface and the stability of the material²⁶. The photogeneration of electron-hole pairs and transport through the films are considered as a function of the bulk properties²⁷. On the other hand, phenomena such as charge transfer to reactant surface and material stability are surface properties²⁷. The oxidation and reduction reactions occur in the electrodes providing a net change in the electrolyte composition in such a manner that solar energy is directly stored in the form of chemical bonds²⁶

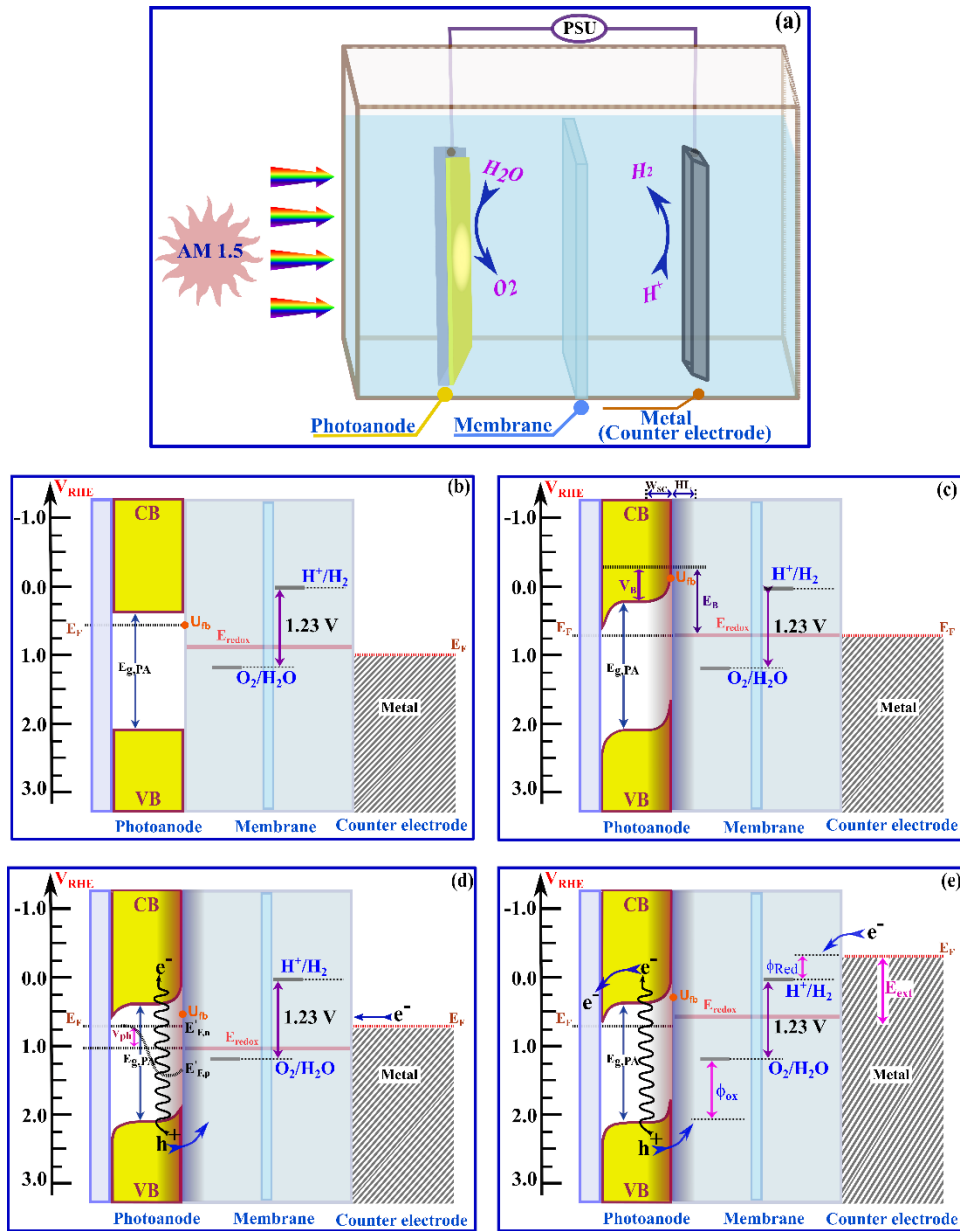


Figure 3 (a) Photoelectrochemical cell water splitting system containing photoanode, counter electrode and membrane as a separator. Energy level diagram at the solid and liquid interface when semiconductor and counter electrode placed in the electrolyte (b) no contact or before equilibrium, (c) in contact and after equilibrium, (d) after light illumination and (e) after applying external bias.

1.4 Materials for photoelectrochemical cell

It is imperative to develop materials that demonstrate high overall water splitting efficiencies. Semiconducting materials should meet requirements such as a sufficient photovoltage²⁸, an appropriate band alignment where the top of valence band (VB) edge must be positive enough to drive water oxidation²⁴, and the bottom of the conduction band (CB) must be more negative than the reduction potential of hydrogen for water reduction²⁴. In addition, the material should have better light-harvesting capabilities in the visible range²⁹, efficient charge separation and transport from the bulk of the thin film to the surface and from the surface to electrolyte solution³⁰. Additionally, the material should be thermodynamically favorable, have sufficient surface area to provide enough active sites, excellent corrosive resistance, and cost-effectiveness³¹.

Many recent efforts have been made to develop efficient photoelectrodes materials such as TiO₂³², WO₃³³, Fe₂O₃³⁴, ZnO³⁵, BiVO₄³⁶, Cu₂O³⁷, CuWO₄³⁸, CaFe₂O₄³⁹, ZnFe₂O₄⁴⁰, CuBi₂O₄⁴¹, CuNbO₄⁴², CuFeO₂⁴³, CuInS₂⁴⁴, TaON⁴⁵, Ta₃N₅⁴⁶, BaTaO₂N⁴⁷, BaNbO₂N⁴⁸, p-CdTe⁴⁹, n-CdTe⁴⁹, InP⁵⁰, GaAs⁵¹, InGaN⁵², p-GaP⁵³, n-GaP⁵³, SiC⁵⁴, p-Si⁵⁵, and n-Si⁵⁵. Some potential materials and theoretical photocurrent and solar to hydrogen efficiencies with bandgap and wavelength onset were shown in Figure 4. However, it is still a challenge to find material that can be utilized for practical application. Potential photoanode material such as TiO₂ was explored extensively. However, TiO₂ suffers from a wide bandgap, making it challenging to use for water splitting application³². Apart from TiO₂, materials such as Fe₂O₃³⁴, Cu₂O³⁷, WO₃³³, and TaON⁴⁵ were explored to harvest more sunlight. Even

after having an appropriate bandgap, achieving remarkable overall water splitting efficiency is still a challenge. Therefore, the work on finding efficient photoelectrode materials is in progress³¹.

Figure 4 further illustrates that material with a smaller bandgap can absorb the sunlight in the wider spectrum range to achieve high solar-to-hydrogen (STH) efficiency and photocurrent density (PCD). Theoretical STH and solar photocurrent of a photoelectrode under simulated AM 1.5G illumination ($100 \text{ mW}\cdot\text{cm}^{-2}$). It is based on an idealized case where 100% of the photons in the solar spectrum with energies exceeding the bandgap are absorbed and converted, shows the band gap of the semiconductor determines that It is still a challenge to achieve remarkable overall water splitting efficiency. Therefore, the work on finding efficient photoelectrode materials is in progress³¹.

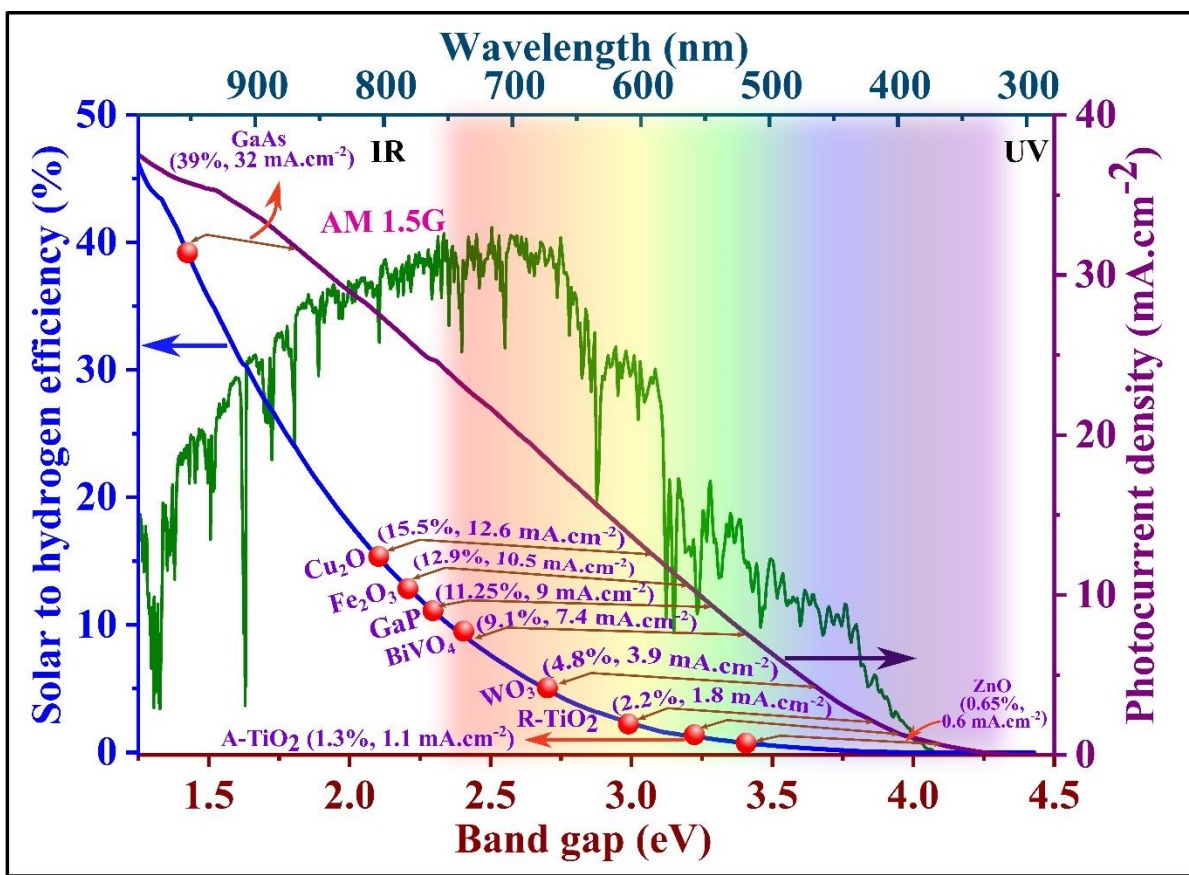


Figure 4 Solar energy-driven water splitting under simulated AM 1.5G illumination using a light absorber spectrum of AM 1.5G (i.e. 1 sun condition, power density of 100 mWcm⁻²).

1.5 BiVO₄: a potential material oxide semiconductor

Monoclinic scheelite n-type bismuth vanadate (BiVO₄) has garnered tremendous scientific interest as a potential photocatalyst since the study of its property by Kudo *et al.*⁵⁶ in 1998. BiVO₄ has incredible capabilities such as absorb light in the broad solar spectrum $\lambda \geq 520$ due to lower bandgap energy ($E_g \sim 2.4\text{-}2.5$ eV)⁵⁷, defect-tolerant nature⁵⁸, and appropriate VB alignment⁵⁹. Apart from that, BiVO₄ does not need a specific medium (acidic or basic) to obtain a high current⁶⁰. However, being a suitable photoanode material, BiVO₄ possesses

many drawbacks such as substantial electron-hole recombination due to self-trapping and small diffusion length⁶¹, poor charge transport properties, sluggish water oxidation kinetics and the position of CB edge is below water reduction potential, which provides an unfavorable condition for the water splitting⁶². Several strategies have been implemented to improve the water oxidation kinetics of BiVO₄. Such as doping^{61,63,64}, forming heterostructure system³³, nanostructuring⁶⁵, coupling with carbonaceous materials to increase the charge carrier separation and transport⁵⁷. Additionally, implementing an electron transfer layer and surface overlayer formation or hole transfer layer for effective charge transfer^{61,66}.

1.6 Crystal and electronic structure of BiVO₄

This section discusses various crystal structures and the electronic structure of BiVO₄ related to photoelectrochemical properties.

The natural structure of BiVO₄ as a mineral is pucherite with the orthorhombic crystal structure (space group: *Pnca* with $a = 5.332$, $b = 5.06$ and $c = 12.02$ Å)⁶⁷. However, BiVO₄ does not form a pucherite structure after synthesization in the laboratory⁶⁸. Instead, it forms a scheelite or a zircon-type structure⁶⁹. The scheelite structure have tetragonal crystal system (space group: *I4₁/a* with $a = b = 5.1470$, $c = 11.7216$ Å)⁷⁰ or a monoclinic crystal system (space group: *I2/b* with $a = 5.1935$, $b = 5.0898$, $c = 11.6972$ Å, and $\beta = 90.3871^\circ$)⁷⁰ whereas zircon-type structure consists tetragonal crystal system (space group: *I4₁/and* with $a = b = 7.303$ and $c = 6.584$ Å)¹.

In the BiVO₄ scheelite structure, each Bi atom is coordinated by eight oxygen atoms from different VO₄ tetrahedral units and each V atom is coordinated by four oxygen atoms at

the tetrahedral site⁷⁰, as shown in Figure 5a and b, where Bi and V centers are coordinated along the [001] direction. Each oxygen atom is coordinated by two Bi and one V centers, forming a three-dimensional structure by holding Bi and V centers together. However, monoclinic scheelite structure shows differences such as more distortion in the local environment of Bi and V ions, two different V–O bond lengths (1.69 and 1.76 Å) and four different Bi-O bond lengths (2.35, 2.37, 2.52 and 2.63 Å) that lead to loss of four-fold symmetry⁷⁰. Whereas for tetragonal scheelite structure, all four V-O bond lengths are equal to (1.73 Å) and two different bond lengths, Bi-O (2.4 and 2.47 Å), exist⁷⁰. The structure of scheelite tetragonal and monoclinic and tetragonal zircon-type are shown in Figures 5a and b. The observed significant distortion in the monoclinic scheelite structure enhances the local polarization that leads to better electrons and holes separation and superior photocatalytic activity compared to tetragonal scheelite structure⁷¹. The local environment of Bi and V centers for zircon type structure is shown in Figure 5c, where eight oxygen atoms coordinate Bi by six different VO₄ tetrahedral units because two VO₄ tetrahedral units provide two oxygen atoms to Bi atom. Each V atom is coordinated by four oxygen atoms^{1,72}.

The zircon type structure was synthesized at low temperature (precipitation at room temperature)¹. On the other hand, zircon type structure to monoclinic scheelite structure was obtained at a high-temperature 400-550°C¹. The tetragonal scheelite structure was obtained at an even higher temperature than monoclinic scheelite temperature. The transition between tetragonal and monoclinic scheelite happens reversibly at 255°C¹. The photocatalytic activity of BiVO₄ highly depends on the crystal structure. For example, the scheelite BiVO₄ shows better photocatalytic activity over zircon type BiVO₄⁷³ because

of higher photons absorption, with a lower bandgap for scheelite (2.4 eV) compared to that of the zircon-type (2.9 eV)⁷². Kudo *et al*⁷³ proposed the schematic band diagram for scheelite and zircon-type BiVO₄, as shown in Figures 5d and e. In the scheelite type BiVO₄, the charge transition occurs between Bi 6s or hybrid Bi 6s-O 2p orbitals to empty V 3d orbitals¹, but, in zircon type BiVO₄, charge transition occurs from O 2p and V 3d orbitals⁷². Thus, the reduction in the bandgap of scheelite type BiVO₄ is due to the appearance of Bi 6s above O 2p^{1,72}.

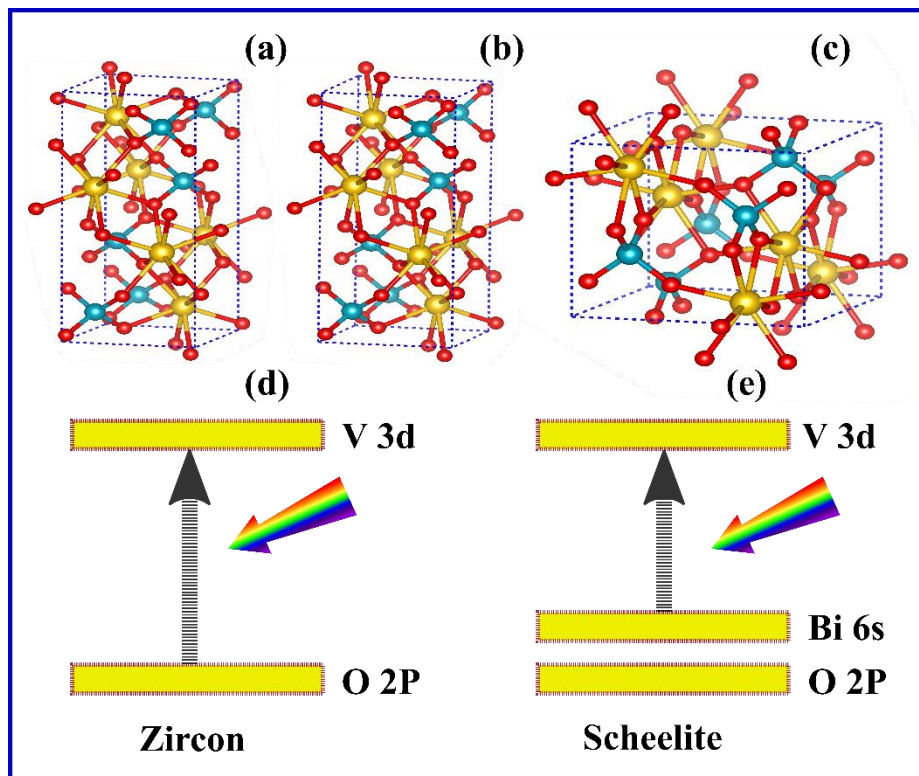


Figure 5 Crystal structure of scheelite, (a) tetragonal, and (b) monoclinic type BiVO₄. Crystal structure of (c)Tetragonal zircon type BiVO₄. (cyan: Bi, yellow: V and red: oxygen). (d) Band diagram of zircon, and (e)scheelite type BiVO₄.

1.7 Strategies to enhance the charge dynamics of BiVO₄

Monoclinic scheelite n-type bismuth vanadate (BiVO₄) has garnered tremendous scientific interest as a potential photocatalyst since the study of its property by Kudo *et al.*⁵⁶ in 1998. BiVO₄ has incredible capabilities such as absorb light in the broad solar spectrum $\lambda \geq 520$ due to lower bandgap energy ($E_g \sim 2.4\text{-}2.5$ eV)⁵⁷, defect-tolerant nature⁵⁸, and appropriate VB alignment⁵⁹. Apart from that, BiVO₄ does not need a specific medium (acidic or basic) to obtain high current⁶⁰. However, being a suitable photoanode material, BiVO₄ possesses many drawbacks such as substantial electron-hole recombination due to self-trapping and small diffusion length⁶¹, poor charge transport properties, sluggish water oxidation kinetics, and the position of CB edge is below water reduction potential, which provides an unfavorable condition for the water splitting⁶². Therefore, several strategies have been implemented to improve the water oxidation kinetics of BiVO₄. Such as doping^{61,63,64}, forming heterostructure system³³, nanostructuring⁶⁵, coupling with carbonaceous materials to increase the charge carrier separation and transport⁵⁷. Additionally, implementing an electron transfer layer and surface overlayer formation or hole transfer layer for effective charge transfer^{61,66}.

Chapter 2 discussed the detail of experimental procedures that include thin film deposition/fabrication process, details of photoelectrochemical analysis and various state-of-the-art characterization details. Chapter 3 discuss the role of alkali metal (Li or Na or K) doping in the BiVO₄ lattice structure to improve the light absorption, electron-hole pairs bulk diffusion length, and surface charge transfer for photoelectrochemical water splitting was systematically investigated. Chapter 4 discusses a systematic investigation of doping/co-doping of Y³⁺, Er³⁺, Yb³⁺ in BiVO₄ and W⁶⁺ at Bi³⁺ and V⁵⁺ sites, respectively

with respect to their light absorption, bulk and surface charge separation and transfer properties. The individual element doping with W was chosen in the current study because doping significantly enhances the charge transport property⁸¹. Individual elements Y, Er and Yb were chosen in the current study because of their extended light absorption, leading to high absorption efficiency^{82,83}. Furthermore, type II heterojunction was formed with WO₃ and *p-n* junction with Fe:NiO for efficient charge separation and transport. The combined effect of hetero and *p-n* junction facilitated an inner built electric field in enhancing the surface reaction kinetics (transportation of electron-hole pairs), lowering the band bending conditions, and increasing the bulk charge separation.

Chapter 5 implemented a multifaceted approach for addressing the interfacial charge recombination in WO₃/BiVO₄ heterojunction where (i) BiVO₄ was co-doped and (ii) an interfacial layer was implemented to improve the effective charge separation and transfer. Initially, BiVO₄ was co-doped with Ga³⁺ and W⁶⁺ at the Bi³⁺ and V⁵⁺ sites, respectively, to enhance light absorption, the concentration of photogenerated charge carriers, and improve bulk charge separation. A uniquely prepared sulfur (S) modified Bi₂O₃ (S:Bi₂O₃) layer was implemented so that S diffused to adjacent underlayer (WO₃) and overlayer ((Ga,W):BiVO₄), which helped in increasing additional reactive sites for charge transport. Finally, Chapter 6 summarizes all the research reported and recommends developing efficient BiVO₄ photoanodes for hydrogen generation water splitting.

CHAPTER 2 EXPERIMENTAL DETAIL AND CHARACTERIZATION PROCEDURES

2.1 Introduction

The design of experiments for all strategies was determined based on the conceptual modifications, required analysis and state-of-the-art characterizations to evaluate the compositional details, photoelectrochemical properties and charge dynamics behaviors. Figure 6 illustrates the various steps involved in completing a study. The initial stages contain the theoretical assessment to determine the appropriate modifications to enhance the charge dynamics of BiVO_4 . These steps include research layout, process development and designing experiments to execute the concepts from theoretical assessments to device fabrication. In the subsequent step, synthesis of novel nanostructured materials and thin-film fabrication. Materials were synthesized using solve thermal process and hydrothermal method. Then, thin films were prepared using various methods such as ultrasonic spray coating, chemical vapor deposition (CVD), spin coating, electrodeposition technique, dip and drop-casting.

Further, the prepared thin films were analyzed to determine the compositional details and quantitative analysis on the molecular level using various advanced analysis techniques. Subsequently, the charged dynamic was evaluated using advanced optical characterization and state-of-the-art characterizations. Photoelectrochemical analyses were conducted to study photoanode surface and electrolyte interface. The study contains linear sweep voltammetry, stability, impedance spectroscopy, Mott-Schottky and stability measurements. In order to analysis data, the various software package was employed such as Origin Lab and JMP. Various scripting was written using MATLAB and Python. The complete processes were repeated and revised based on the result concluded from the data

analysis. However, in most cases, various intermediate samples were fabricated to validate the concepts, including short annealing to evaluate the epitaxial crystal growth, composition evaluation, and charge dynamics properties evaluation. The process was repeated until reproducing the performance of samples. The troubleshooting and calibration of measurements are validated before every measurement. Also, multiple samples were prepared in order to determine the validity of the results.

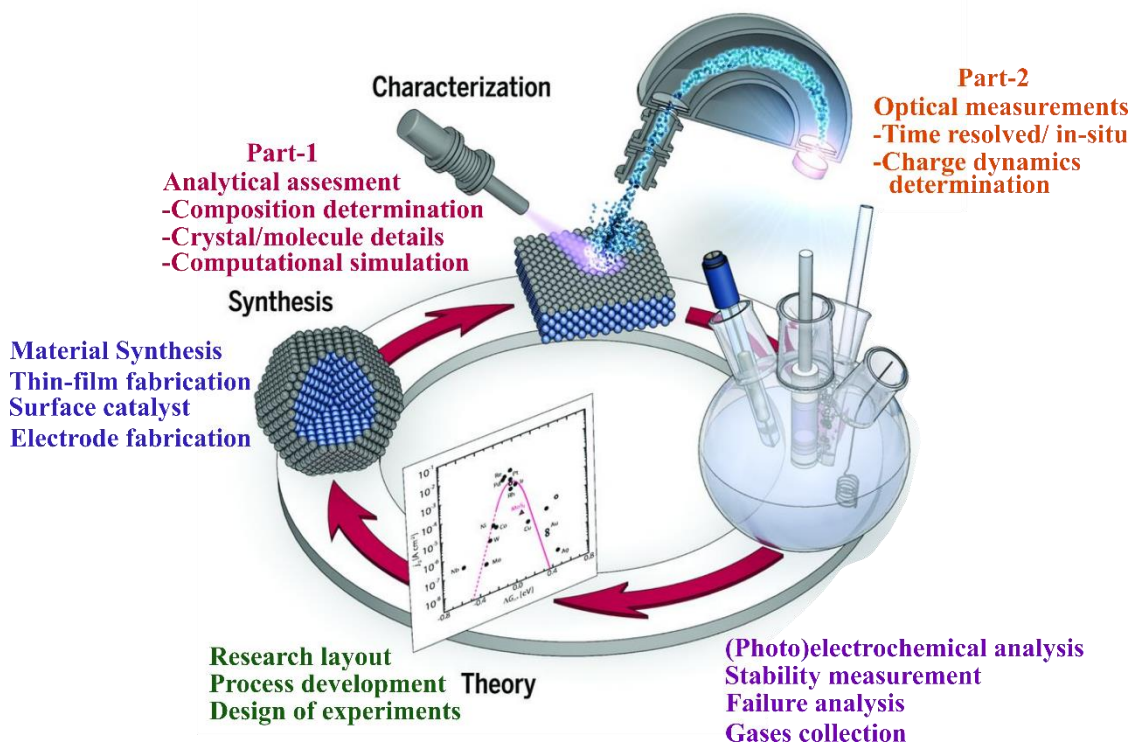


Figure 6 Experimental details and measurement procedure

2.2 Thin Film Fabrication

The precursor solution of BiVO_4 was prepared using 3mM $\text{Bi}(\text{NO}_3)_3 \cdot 5\text{H}_2\text{O}$ and 3 mM NH_4VO_3 in 2M HNO_3 . The thin film deposition was carried out using various techniques such as spin coating, chemical vapor deposition, dip and drop-casting. Ultrasonic spray

coating is one of the promising approaches for thin-film preparation, as shown in Figure 7. This system provides the flexibility of composition tuning, porosity control with an appropriate thermal cycle process, and an easy-to-build stack base structure. However, this system contains various complicated parts and is sensitive to the type and nature of the precursor. The pristine and alkali metal-doped BiVO_4 based thin film samples (Area: $1.0 \times 1.0 \text{ cm}^2$) were prepared on fluorine-doped tin oxide (FTO) glass substrate (Aldrich Chemistry: 2.3 mm thick, $\sim 7 \text{ } \Omega/\text{sq}$ surface resistivity). The liquid ink was sprayed with a 0.1 ml/min flowrate over FTO glass held at $70 \text{ } ^\circ\text{C}$. An optimum film thickness of $\sim 520 \text{ nm}$ was coated with two cycles of spraying followed by heat-treatment (Thermo Scientific Thermolyne: Model: F48028) at $500 \text{ } ^\circ\text{C}$ in the air for 2 h (Figure 8a).



Figure 7 Ultrasonic spray coating machine for thin-film fabrication

Atmospheric pressure chemical vapor deposition (APCVD) was used for the thin film deposition using a tubular furnace, as is shown in Figure 8b.

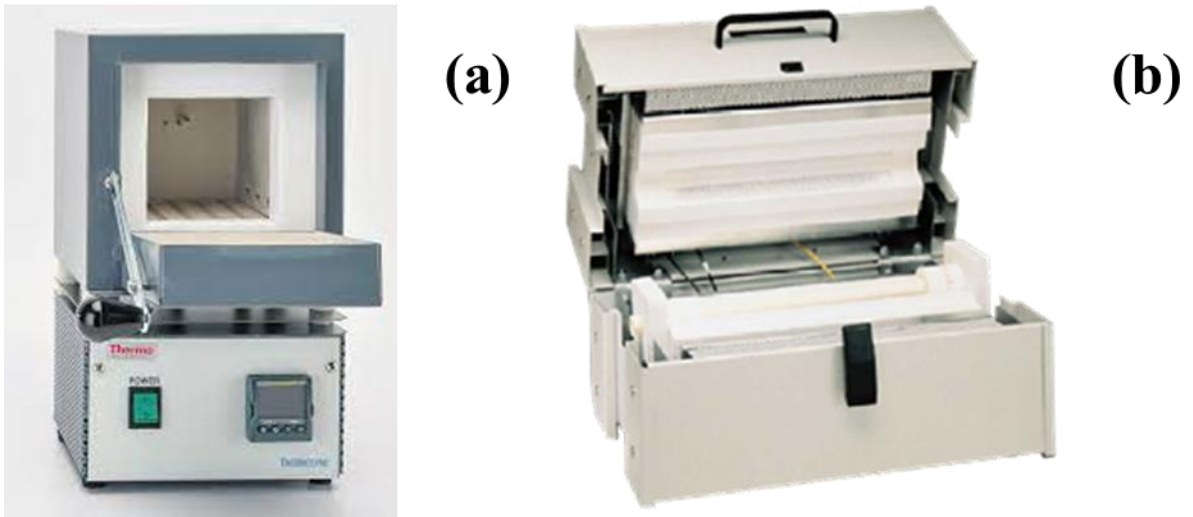


Figure 8 used (a) muffled furnace and (b) tubular furnace for the thin film fabrication.

The vapor was generated by heating an appropriate amount of powder/solid material in the tube furnace's upstream section at the specific temperature where it converted from solid to vapor. Argon was used as a carrier gas to carry the vapor downstream, where the substrate was placed in the hot zone of the tubular furnace. The prepared films are shown in Figure 9a. Figure 9b shows stack base structured films with all intermediate deposition steps.

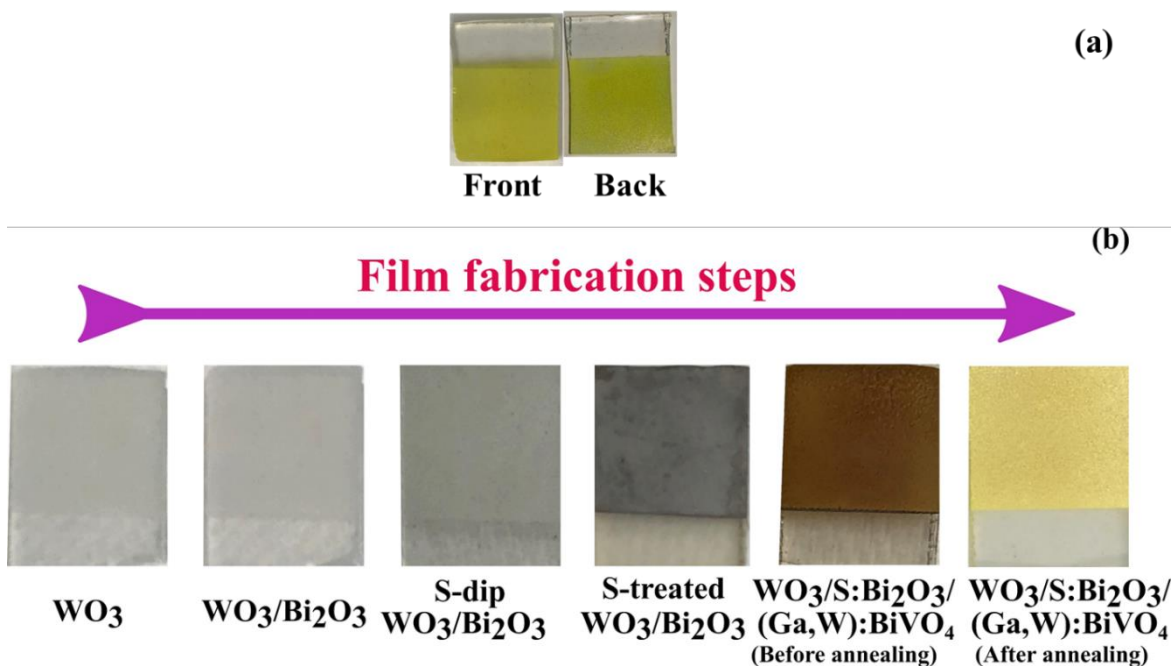


Figure 9 (a) prepared thin film front and back view, (b) various intermediate thin films of the stack-based film structure.

2.3 Electrode fabrication from thin films

Photoanodes were constructed from the prepared thin films by attaching a copper wire to the FTO, and silver paint was used to establish electrical contact. Epoxy (Loctite 9460) was applied to secure the connection and cover the copper wire, silver paint, and FTO edges. The active surface area was measured by scanning the electrode surface. An electrode fabrication from the thin film is shown in Figure 10.



Figure 10 Fabricated electrodes from the thin film

2.4 Photoelectrochemical measurement

The PEC performance of the photoanodes was evaluated in a standard three-electrode configuration using Pt wire (Premion 99.997%) and Ag/AgCl (3M NaCl filling solution) as a counter and reference electrodes, respectively. A solar simulator (Sun 3000, model#11000A, ABET Technologies, USA) was used as the light source. Simulated AM 1.5G illumination was established using a GaInP (bandgap: 1.8 eV) photovoltaic primary reference cell. Potentiostat/galvanostat (BioLogic SP-300) was used for photoelectrochemical (PEC) measurements in 0.1 M KPi solution in water (pH = 8.0). The setup for the photoelectrochemical measurement is shown in Figure 11.

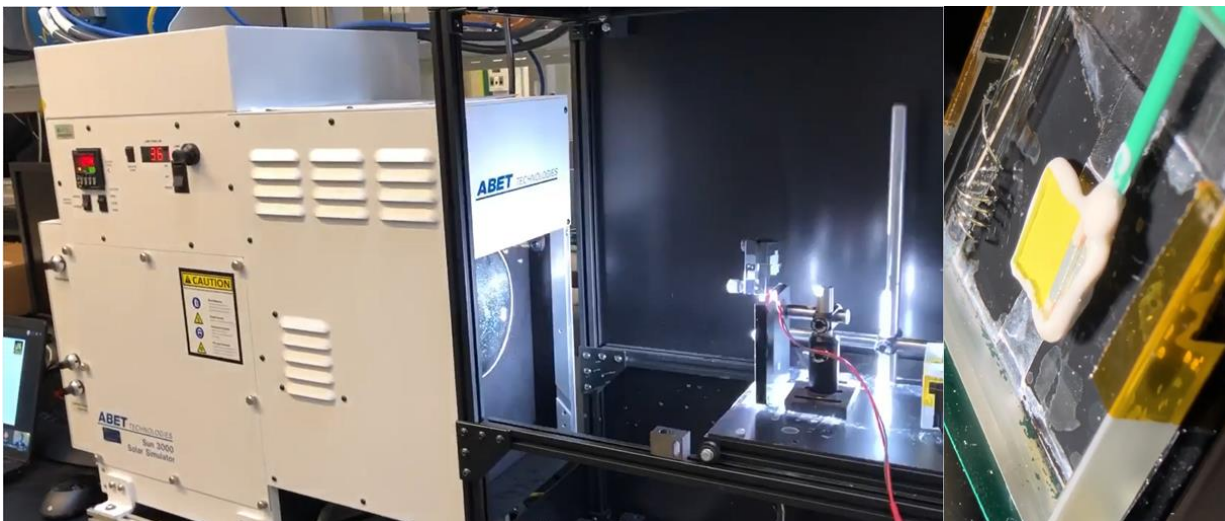


Figure 11 photoelectrochemical measurement station contains solar simulator, 3 electrode setup and potentiostat.

The electrolyte was degassed with N_2 gas for about 20 min before every measurement. Incident photon-to-current efficiency (IPCE) measurement was conducted using a 300 W Xe lamp (Newport, 66883), monochromator (Acton SpectraPro-150), mono-Si cell (Hamamatsu) and potentiostat (VersaSTAT 4 Ametek, Princeton Applied Research) with a lock-in amplifier (SR530 Stanford Research System). The setup is illustrated in Figure 12. A 495 nm long-pass filter (Newport) was added after the monochromator for wavelengths > 550 nm to filter second-order diffraction.

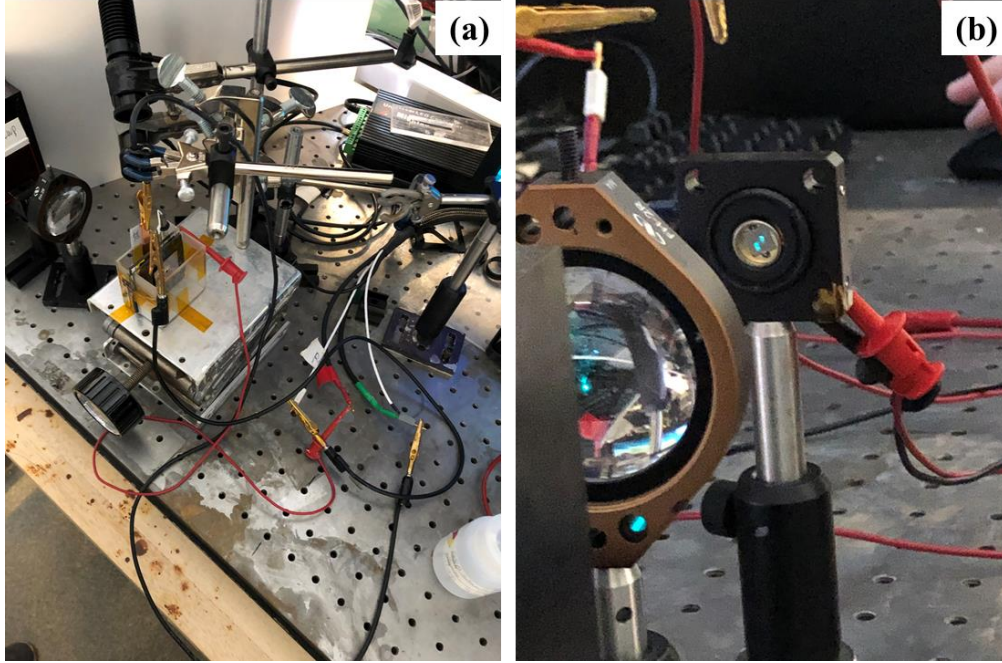


Figure 12 Incident photon-to-current conversion efficiency (IPCE) (a) complete setup and (b) beam size and focus.

The photocurrent was also measured with a hole scavenger (Na_2SO_3), where the electron-hole recombination is considered almost negligible.⁸⁴ Electrochemical impedance spectroscopy (EIS) measurements were performed at a frequency range of 100 kHz to 100 mHz under simulated AM 1.5G illumination. Mott-Schottky estimated flat band (onset) potential–Schottky at 1 kHz in the dark with AC amplitude of 20 mV at 1.23 V vs RHE in 0.1 M K_2HPO_4 electrolyte (pH 7.5) by the relationship given in equation (6).³³

$$\frac{1}{C^2} = \frac{2}{(\epsilon\epsilon_0 A^2 e N_D)} \left(V_{app} - V_{FB} - \frac{k_B T}{e} \right) \quad (6)$$

Where C is the capacitance in space charge region; ϵ is relative permeability which is taken as⁸⁵ for the calculation; ϵ_0 is vacuum permeability ($8.8 \times 10^{-12} \text{ F m}^{-1}$); A (cm^2) is the area of

the photoanode thin film; e is the charge of an electron (1.602×10^{-19} C); N_D is the number of charge carrier per cm^{-3} , estimated from Mott-Schottky measurement plot; V_{app} (in RHE) is the applied potential; V_{FB} is the flat band potential measured from Mott-Schottky plot; K_B is Boltzmann constant (1.38×10^{-23} J K^{-1}); T (K) is the temperature at which the measurement is performed (298 K).

The majority of the photoelectrochemical measurements were conducted by illuminating 1 sun from the back of the thin film (through the glass). Since BiVO_4 is mainly composed of electron-hole pairs that are generated within the film's thickness, they need to travel across the film's entire thickness to the BiVO_4/FTO interface. The rate-limiting step is a crucial step in the design of photoelectrodes. It can be used to evaluate the efficiency of the collector and the film thickness. Since electron-hole pairs in BiVO_4 are mostly generated within the penetration length of the light (~ 100 nm), the electrons need to travel across the entire thickness of the film to the BiVO_4/FTO interface for collection when illumination is from the front. The optimized thickness photoanode is considered to be approximately 500 nm for BiVO_4 and 200 - 250 nm for Bi_2O_3 and WO_3 . So back illumination will facilitate the electron to rapidly moved to the electron collector, as illustrated in Figure 13.

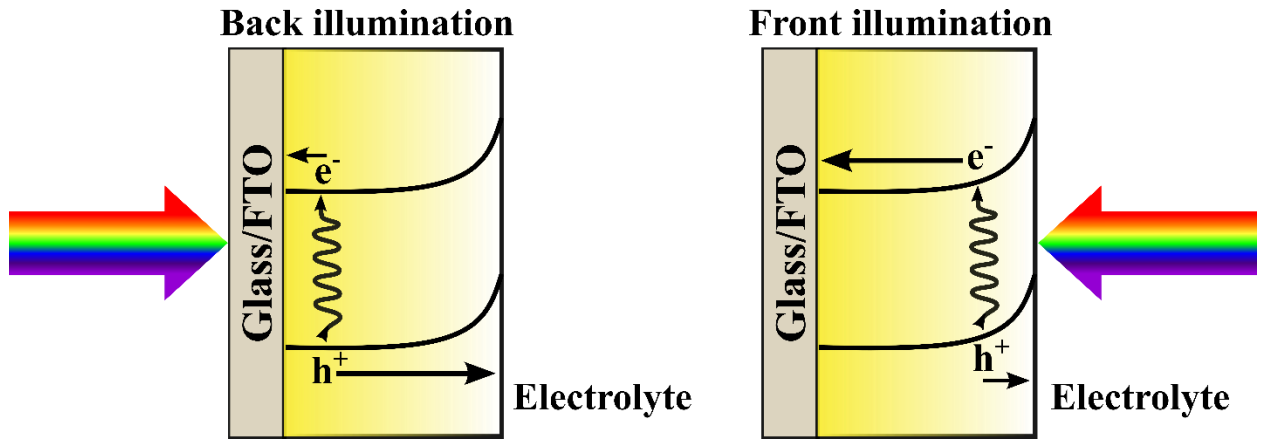


Figure 13 Significant of front and back light illumination on the electrode sample.

2.5 Process of hydrogen collection

The H_2 and O_2 gases generated in the PEC process were collected in a three-electrode setup by tracking the electrolyte volume from a filled tube.⁸⁶ The faradaic efficiency (η_{H_2}) was calculated using equation (7).

$$\eta_{H_2} = \frac{\frac{P_{H_2} V}{RT}}{(Coulombs\ passed) \times \left(\frac{mol\ e^-}{96485C}\right) \times \left(\frac{mol\ H_2}{2mol\ e^-}\right)} \quad (7)$$

Where P_{H_2} , V , R and T are pressure from H_2 evolution (hPa), volume (L), gas constant (0.08206 L atm $K^{-1}mol^{-1}$) and T temperature (K), respectively. P_{H_2} was calculated by subtracting the water vapor pressure ($P_{H_2O\ vapor}$) and pressure from the suspended solution ($P_{suspended}$) from atmospheric pressure (P_{atm}) measured using a barometer, by equation (8).

$$P_{H_2} = P_{atm} - P_{H_2O\ vapor} - P_{suspended} \quad (8)$$

Where, $P_{suspended}$ is calculated by measuring the height (h_1) of the suspended solution above the solution level in the setup. The equation (9) is used for the calculation.

$$P_{suspended} = h_1 \times \frac{Hg \text{ Density}}{Solution \text{ density}} \times \frac{1 \text{ atm}}{760 \text{ mm Hg}} = h_1 \times 0.0736 \text{ (torr}^{-1}\text{mm}^{-1}) \quad (9)$$

The faradic efficiency measurement was validated using Pt electrodes as an anode and cathode for the electrolysis and obtained η_{H_2} 0.98 ± 0.02 . The measurement was conducted at 1.23 V_{RHE} in KPi electrolyte under simulated AM 1.5G illumination. A typical setup is shown in Figure 14.



Figure 14 Hydrogen collection setup

2.6 Important equations and calculation processes

Photoelectrochemical measurements

The reference electrode potential was converted to reverse hydrogen electrode (RHE) by the relationship given in equation (10).

$$E_{RHE} = E_{Ag/AgCl}^0 + E_{Ag/AgClSCE} + 0.059 \text{ pH} \quad (10)$$

Where $E_{Ag/AgCl}^0 = 0.1976 \text{ V vs. RHE, at } 298 \text{ K}$

Process of theoretical photocurrent ($J_{\text{theoretical}}$ calculation)

The light-harvesting efficiency (LHE) or absorption efficiency (ϕ_{abs}) relationship is show in (equation (11))

$$LHE = 1 - 10^{-A(\lambda)} = \phi_{\text{abs}} \quad (11)$$

Where A is absorbance with wavelength (λ)

The absorption efficiency was calculated by integrating absorption spectra from wavelength 300 to 550 nm for all samples.

Further, photon energy and photon flux were calculated from AM1.5G solar irradiance with wavelength by following relation (equation (12-14)).

$$E(\lambda) = h \times C / \lambda \quad (12)$$

Where, $E(\lambda)$: photon energy h : Planck constant C : speed of the light

$$\text{Number of photons} = h \times C / \lambda \quad (13)$$

$$\text{Photons flux } (\phi(\lambda)) = P(\lambda) / E(\lambda) \quad (14)$$

The theoretical photocurrent was calculated using the above-calculated data assuming 100% incident to photon conversion efficiency (IPCE) and by the following relationship.^{33,61}

$$J_{theoretical} = \int_{\lambda_1}^{\lambda_2} e \times \phi(\lambda) \times LHE \times d\lambda \quad (15)$$

Charge transport calculation: bulk and surface

Major losses in theoretical photocurrent are electron-hole recombination in bulk and at the surface, which are known as charge separation (η_{sep}) and charge transfer or charge injection efficiency (η_{trans}), by relationship equation (16 and 17).

$$J_{H_2O} = J_{theoretical} \times \phi_{sep} \times \phi_{trans} \quad (16)$$

The transfer efficiency is almost 100% in the presence of hole scavengers, given by relationship equation (10).⁶¹

$$J_{Na_2SO_3} = J_{theoretical} \times \phi_{sep} \quad (17)$$

Using equations (16 and 17), the η_{sep} and η_{trans} can be calculated

IPCE calculation

The IPCE was measured by the relationship given in equation (18)

$$IPCE = \frac{\text{Number of electrons}}{\text{Number of photons}} = \frac{J_{monochromator} \times h \times C}{P_{monochromator} \times \lambda} \quad (18)$$

Integrated current calculation

Integrated current ($J_{integrated}$) was calculated using the relationship given in eq (19)

$$J_{Integrated} = \int_{\lambda_1}^{\lambda_2} e \times \phi(\lambda) \times IPCE \times LHE \times d\lambda \quad (19)$$

2.7 State-of-the-art material characterization

It is imperative to evaluate the photocatalytic behavior of BiVO₄ thin film to understand overall water oxidation kinetics. Various electrochemical studies, material characterization, theoretical studies were performed to understand the semiconductor surface, bulk and surface/electrolyte interface characteristics of semiconductor and photogenerated charge carrier properties. A list of evaluation techniques is given in Table 1.

The PEC performance of the prepared photoanode was evaluated in a standard three-electrode configuration using Pt mesh and saturated calomel electrode (SCE) as a reference and photoanode as a working electrode, respectively. A solar simulator, equipped with AM 1.5G filter (calibrated for 1 sun (100 mW.cm⁻²)) as a light source along with a potentiostat/galvanostatic used for photoelectrochemical measurements in the electrolyte. The light absorption behavior of the photoanode was examined by measuring incident photon-to-current efficiency (IPCE). It is the ratio of total photocurrent versus the rate of incident photons as a function of wavelength⁸⁷. IPCE considers major efficiencies such as photon absorption/charge excitation, charge transport in bulk ($\eta_{separation}$) within the solid and interfacial charge transfer across the solid-liquid interface ($\eta_{transfer}$)⁸⁷. Further, based on photon absorption, absorbed photon-to-current efficiency (APCE)⁸⁸ was measured to determine the absorbed photon to current conversion rate. The Mott-Schottky analysis

determines the U_{fb} , W_{sc} , VB and CB edges³³. Besides, the amount of band bending can be calculated as per the procedure explained³³.

The crystal structure, crystallinity, phase change and phase composition of the synthesized thin film were determined by X-ray diffraction (XRD) analysis. The main observed peaks in the scheelite monoclinic BiVO_4 at 18.6° , 18.9° , 28.58° , 28.82° , 28.94° and 30.5° correspond to (110), (011), (-130), (-121), (121) and (040) crystal planes³⁶. Detecting the doping oriented peaks in XRD depends on the doping level, small substitutional doping (2-5%) does not make any change in the crystal structure of BiVO_4 , but slight changes in the lattice parameters are possible^{36,61} such as a small shift in the peaks were observed along with a change in the overall volume on Li doping in BiVO_4 ⁸⁸. Raman analysis predicts the change in the atomic arrangement in the crystal lattice after modifying the pristine semiconductor, such as a shift in the peaks towards lower wavenumber predicts the increment in the overall crystal symmetry after doping and co-doping in the BiVO_4 ³³. Also, change in bond length confirm the effect from modification such as doping can increase bond length³³.

Scanning electron microscopy (SEM) determines the surface morphologies of nanostructure along with the grain size and porosity of the thin film⁶¹. Energy-dispersive X-ray spectral (EDX) mapping analysis estimate the composition of the prepared thin film⁵⁷. X-ray photoelectron spectroscopy (XPS) analysis examines elements' oxidation state and provides information if their surroundings are getting affected by doping⁸⁸. Atomic force microscopy (AFM) provides insight into structural and optoelectronic properties. It can even illustrate (photo)current mapping that reveals nanoscale, (opto)electronic heterogeneity across the film⁸⁹. Along with the conductivity measurement

of the thin film, AMF can provide the charge transport mechanism through single current-voltage curves⁸⁹. Transmission electron microscopy (TEM) provides details about microstructural characteristics, lattice fringe spacing and selected area electron diffraction (SAED)⁹⁰.

The electron probe microanalyzer (EPMA) was applied for composition analysis of the thin film when surface modified during post-synthesis, such as nitrogen treatment of BiVO₄ surface. In this case, the quantity of nitrogen incorporated in the lattice structure of BiVO₄ can be estimated through EPMA⁹¹. Inductively coupled plasma mass spectrometry (ICP-MS) also provides the composition of the thin film⁸⁸. Both ICP-MS and EPMA provide the composition of the thin film based on different principles^{88,91}. Photoluminescence (PL) emission spectra originate from the radiative recombination of electrons and holes that can help in understanding the recombination process and lifetime of photogenerated electrons and holes⁶¹. Ultraviolet-visible spectroscopy (UV-vis) and diffuse measurement provide information about the thin film behavior towards the light, such as absorbance, reflectance, transmittance. Other parameters, optical band gap, light-harvesting and absorbance efficiency (LHE)^{33,36,57}.

To estimate the diffusion length of electron-hole pairs and correlation with the defect density, the Depth dependent Doppler broadening spectroscopy measurements were conducted using a slow positron accelerator³⁶ with the Doppler broadening spectra at increasing positron implantation energies (E, keV) are recorded using a HPGe detector (energy resolution 2.0 keV at 1332 keV of ⁶⁰Co). The spectra have been analyzed through line shape, S (ratio of counts in the low momentum (central) region (511±0.760 keV) to

the total area of the annihilation peak) and W (ratio in the high momentum (wing) region ($3.23 \text{ keV} \leq |\gamma-511\text{keV}| \leq 6.65\text{keV}$) to the total area of the photopeak) parameters.

To investigate the role of Na or K doping on the defect types and density in the BiVO_4 films, the S - E profiles have been fitted using VEPFIT³⁷. According to VEPFIT, S -parameter at particular implantation energy (E , keV) in a sample having n number of layers is expressed as

$$S(E) = f_s S_s + f_1 S_1 + f_2 S_2 + \dots + f_n S_n$$

For the present study, two layers model has been considered for the pristine or doped films on the FTO substrate.

Time-resolved microwave conductivity (TRMC) provides the lifetime of photogenerated electrons and holes, which is a critical parameter to determine the photoactivity of semiconductor⁹². Free charge carriers generated by nanosecond laser pulses induce a change in the microwave power reflected from the sample. This change can be correlated to the photoinduced change in the conductivity of the sample, which provides the lifetime and diffusion length of photogenerated electrons and holes⁹². Transient diffuse reflectance spectroscopy (TDRS) analysis focuses on the effect of carrier dynamics during the photocatalytic reaction, especially the difference of the crystal phase⁹³. Transient absorption spectra (TAS) provide details about the photogenerated electrons and holes dynamics at an applied bias. The decay time constant of photogenerated electrons and holes can be estimated with applied bias⁹⁴ to predict the complete dynamic of photogenerated electrons and holes. Time-resolved Terahertz Spectroscopy (TRTS) determines the electrons and holes properties⁹⁵, where semiconductors illuminated with the femtosecond

laser pulse generate electrons and holes that absorb THz probe radiation and can be detected by a decrease in transmitted or reflected THz power. This decrease can provide details about photogenerated electrons and holes conductivity, which leads to finding out mobility and diffusion length.

Apart from photoelectrochemical and characterization, a theoretical study using the first-principles density functional theory (DFT) as implemented in the Vienna *ab initio* simulation package (VASP) provides a fundamental understanding of the electronic properties of BiVO₄⁹⁶. The DFT analysis bestows deep insight by estimating optimum structure, formation energy, electronic band structure, absorbance and the site-projected density of states (PDOS) on the doping in the BiVO₄ structure⁹⁷.

The DFT calculations, which include structural optimizations and electronic properties, were carried out using the Vienna *Ab initio* Simulation Package with generalized gradient approximation. In specific, the Perdew-Burke-Ernzerhof exchange-correlation functional and the projector-augmented wave potentials were employed. The Bi_d, V_pv, Os_pv, K_sv, and Na_sv were used as a potential for all the calculations. The Bi (5d, 6s, 6p), V(2p, 3d, 4s), O(2s, 2p) and alkali metals (1s, 2s, 2p) electrons were treated as valence electrons. Plane wave functions with a kinetic energy cutoff of 600 eV were used to describe the wavefunction of electrons. The reciprocal space is meshed as $5 \times 5 \times 7$ using the Monkhorst–Pack method for all unit cell structure relaxations. The electronic band structure is plotted along the high-symmetry lines along the directions L(-0.5, 0, 0.5)-M(-0.5, 0.5, 0.5) -A(-0.5, 0, 0)- Γ (0,0,0)-Z(0, -0.5, 0.5)-V(0, 0, 0.5). The energy convergence criterion for electronic iterations is set to be 10^{-5} eV. The DFT+U method was used to improve the description of the highly localized d-electron correlation in the transition metal

V with a Hubbard U value of 2.7 eV. The formation energies for Na placement into the BiVO₄ interstitial position was calculated using,

$$E_{F,interstitial} = E_{Na:BiVO_4} - E_{BiVO_4} - E_{Na}$$

$E_{Na:BiVO_4}$, E_{BiVO_4} , and E_{Na} are the free energies for the Na doped BiVO₄, pristine BiVO₄ and single Na atom.

Table 1 Thin-film fabrication methods, material characterizations, theoretical analysis and various calculated parameters applied to determine the photocatalytic performance of BiVO₄.

Fabrication technique	Photocatalytic evaluation	Characterization	Theoretical analysis	Parameters	
Metal-organic	Photocurrent density with	XRD, Raman spectroscopy	Structure optimization	Light-harvesting	Bulk/surface capacitance

decomposition	hole scavengers			efficiency	
Sol-gel method, precipitation method	Transient current	SEM, EDX, TEM,	Static calculation	Absorption efficiency	Bulk/surface resistance
Spray pyrolysis, ultrasonic spray coating	Electrochemical Stability	XPS, AMF, photoluminescence	Density of State (DOS)	Separation efficiency	Charge transfer rate constant in the bulk and surface state
Dip coating and Drop cast method	Cyclic voltammetry	ICP-MS, EPMA	Bandgap calculation	Injection efficiency	Number of charge carrier density bulk and surface
Spin coating	Mott-Schottky	UV-Visible and diffuse reflectance	Electronic band structure	Total efficiency of photoanode	Electrochemical surface area (ECSA)
Sputter coating	Impedance measurement (EIS)	Time-resolved microwave conductivity	Dielectric calculation for absorbance	Total charge retention	Charge transfer kinetics
Hydrothermal	IPCE/APCE	TAS (transient absorption spectra)	Projected density of states	Band gap calculation	Rietveld refinement
Electrode deposition	Open circuit potential (Δ OCP)	Transient diffuse reflectance spectroscopy	Formation energy	ABPE	Width of space charge region (WSCL)
Chemical vapor deposition	Amount of H ₂ and O ₂ gas evolution	Time-resolved Terahertz Spectroscopy	Polaron hopping analysis	Amount of band bending	Density of state and Fermi level determination
Vacuum deposition methods	Surface state determination	Doppler broadening spectroscopy measurements	Adsorption energy calculation	Valence and conduction band edges	Electro-hole pairs diffusion length

CHAPTER 3 ALKALI METAL PLACEMENT IN THE CRYSTAL STRUCTURE OF
BIVO₄

3.1 Introduction

Several attempts have been made to improve the performance of BiVO₄ through doping³⁶, junction formation⁹⁸ and nano-structuring⁹⁹ and adding electron transfer layer⁶⁶ and hole transfer layer¹⁰⁰. Among these strategies, employing p-n homojunction is a useful technique for promoting band alignment, charge separation and transfer due to the built-in internal electric field at p-n junction^{101,102,103}. Doping with transition metals (IIIA to VIIA group elements) has been proven to be one of the practical approaches for increasing OER reaction by enhancing diffusion length, charge carrier separation/transport, and light absorption by reducing band gap^{104,92,105}. According to Wang et al.¹⁰⁶, the HER and OER reactions can be promoted by doping for enhancing active sites, lowering overpotential, and improving durability. Ritcher et al.¹⁰⁷ has determined that Na and K doped TiO₂ nanotubes can reduce the external bias and induce charge transfer by forming a strong ionic bond and modifying the electronic band structure. Whereas Grewe et al.¹⁰⁸ illustrated that Na and K doping in mesoporous Ta₂O₅ without any structure change led to superior water splitting performance. The elements such as S, H and N are incorporated into the BiVO₄ lattice, and their effect on diffusion length, absorption and charge transport have been studied extensively^{109–111}. Marlene et al.¹⁰⁹ has studied sulfur incorporation in the oxygen site in BiVO₄ and evaluated the bandgap reduction and the increase in carriers mobility and diffusion length. Jang et al.¹¹⁰ subjected BiVO₄ surface to mild hydrogen treatment for improving carrier mobility and lifetime through hydrogen bonding with oxygen. Irani et al.¹¹¹ demonstrated significant enhancement in optical absorption and bandgap reduction by nitrogen doping at vanadium sites in BiVO₄. However, there has not been any systematic study on the alkali metal doping in the BiVO₄ structure.

In the present study, the role of alkali metal (Li or Na or K) doping in the BiVO₄ lattice structure improves light absorption, electron-hole pairs bulk diffusion length, and surface charge transfer for photoelectrochemical water splitting was systematically investigated. The doped BiVO₄ thin films prepared using ultrasonic spray coater exhibited planner surface morphology with interconnected nano porous grains. Depth-dependent Doppler broadening spectroscopy measurements were employed for analyzing the bulk diffusion length of charge pair and correlated with the defect density. The placement of alkali metal in the interstitial position of BiVO₄ crystal structure resulted in the reduction of the Bi and V voids due to shared interaction of doped alkali metal, Bi and V, with lattice oxygen atoms. The effect was highly significant in the Li and Na doped BiVO₄ film compared to that with K. The density functional theory confirmed the formation of multiple interbands with optical band gap reduction with Li and Na doping, resulting in the extended light absorption, enhanced charge separation in the bulk and surface transfer during PEC process. The Li:BiVO₄ and Na:BiVO₄ photoanode showed the highest photocurrent density of 2.35±0.15 and 1.82 ±0.1 mA.cm⁻² in 0.1 M K₂HPO₄ electrolyte under 1 sun illumination at 1.23 V_{RHE}.

3.2 Preparation of alkali metals doped BiVO₄ thin film

The pristine and alkali metal doped BiVO₄ based thin film samples (Area: 1.0 × 1.0 cm²) were prepared on fluorine-doped tin oxide (FTO) glass substrate (Aldrich Chemistry: 2.3 mm thick, ~7 Ω/sq surface resistivity) using ultrasonic spray coating technique (Sono-Tek Corporation, USA)³³. Precursor solution of BiVO₄ in 3mM Bi(NO₃)₃·5H₂O (Alfa-Aesar, CAS#10035060) and 3 mM NH₄VO₃ (Sigma-Aldrich, CA

S#7803556) in 2M HNO₃ (Sigma-Aldrich, CAS#7803556) was sprayed at a 0.1 ml/min flow rate over FTO glass at 70 °C. An optimum film thickness of ~ 520 nm was coated with two cycles of spraying followed by heat-treatment (Thermo Scientific Thermolyne: Model: F48028) at 500 °C in the air for 2 h (see Figure 15). Alkali metal (Li or Na or K) doping in the BiVO₄ (2 to 6 wt. %) was carried out by adding sodium hydroxide (Sigma-Aldrich, CAS#1310732) or potassium hydroxide (Sigma-Aldrich, CAS# 1310-58-3) in the BiVO₄ precursor solution.

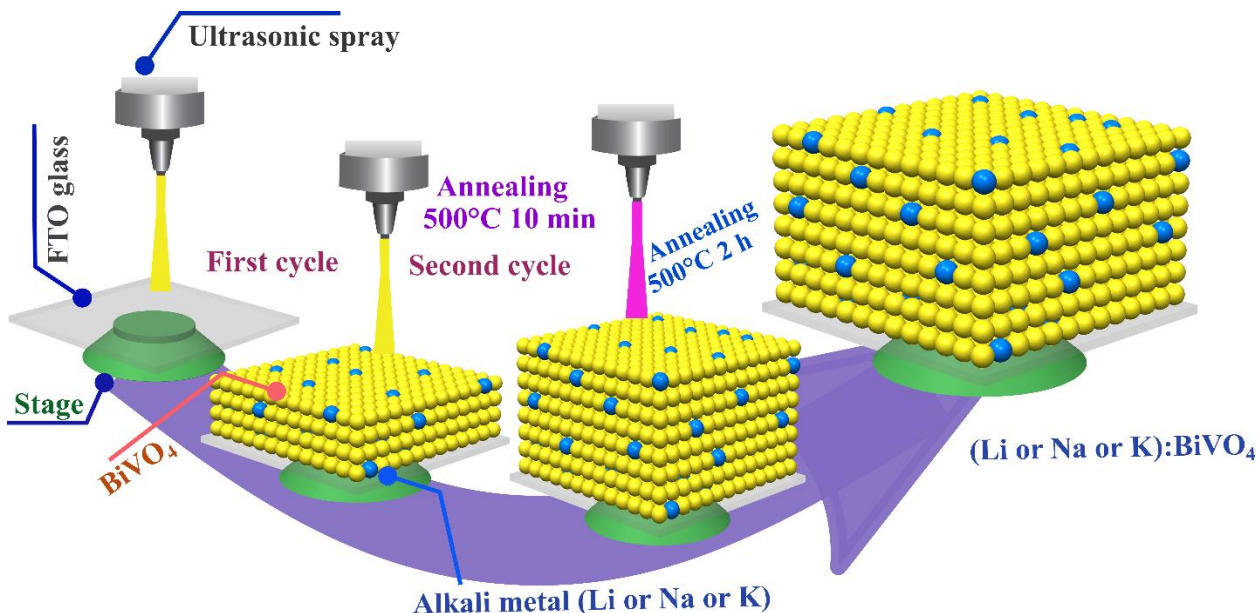


Figure 15 Schematic illustration of alkali metal-doped BiVO₄ film fabrication process.

3.3 Photoelectrochemical measurements

The enhanced water oxidation performance of alkali metals (Li, Na, K) doping in the BiVO₄ system is evaluated by measuring PEC performance. It was observed from Figure 16a that with individual Li, Na and K doping in BiVO₄, the photoanode Li:BiVO₄ showed

PCD (2.35 ± 0.15 and 6.2 ± 0.30 mA.cm⁻² at 1.23 and 2.0 V vs RHE, respectively), which is 24 times pristine BiVO₄, Na:BiVO₄ shown PCD of 1.82 ± 0.1 mA.cm⁻² which is 17 times corresponding to the pristine BiVO₄ (0.11 ± 0.01 mA.cm⁻²) measured at 1.23 V vs RHE in 0.1 M K₂HPO₄ (pH: 8.0) under 1 sun illumination. Furthermore, K doped BiVO₄ demonstrated improved performance (0.85 ± 0.04 mA.cm⁻²) up to 8 times than pristine BiVO₄. Further, the nature of alkali metal-doped BiVO₄ photoanodes PEC performance was measured in hole scavengers (Na₂SO₃) for the sulfite oxidation, which makes the electrons and holes recombination almost negligible.

The investigation of obtained PCD was further elaborated by transient current measurement under chopped light for 5 sec up to 120 sec at 1.23 V vs RHE for the water and sulfite oxidation. It can be observed that the photocurrent is highest at the beginning of the first light illumination and then decreases gradually to some degree. However, this behavior decreased mostly after few cycles. This is because the charge accumulation is maximum at the first illumination of light then electron-holes recombination takes place. These recombinations are most evident in BiVO₄ and least for Na:BiVO₄ & Li:BiVO₄.

To understand the enhanced overall water splitting performance of alkali metals doped BiVO₄ photoanode, light absorption behavior on the surface of the photoanode was studied. As given in Figure 16b, the onset of the light absorption for pristine BiVO₄ starts from ~510 nm. However, on alkali metals doping, the light absorption onset improved towards a higher wavelength ~520 nm, 530 and 535 nm for K:BiVO₄, Na:BiVO₄, Li:BiVO₄, respectively. Apart from the improved absorption edge due to alkali metal doping, total absorption improved significantly due to a good amount of absorption even

before the absorption onset, speculating the formation of interbands¹¹². From Figure 16b inset, among all photoanode, the Li:BiVO₄ photoanode has the highest absorption (~75%) followed by Na:BiVO₄ (73%), K:BiVO₄ (69%) and pristine BiVO₄ (64%) due to placement of Li, Na and K in the interstitial position of BiVO₄ structure that generate sufficient disorder in the atomic arrangement due to electrostatic interaction and oxygen deficiency. As a result, there will be many active sites forming interband states in the bandgap region. The Li doped samples show the lowest band gap (~2.34 eV) compared to pristine BiVO₄ samples (~2.44 eV). This reduction in band gap corresponds to higher light absorption than other prepared samples. This validates more active sites generation on the Li doping compared to Na and K doping with the formation of the inter-band state. The improved absorption property of Li, Na and K doping samples was confirmed by diffuse reflectance and transmittance measurement that shows that the diffuse reflectance is minimum for Li doped samples compare to Na and K doped BiVO₄¹¹³. The Li:BiVO₄ showed improved overall light-harvesting capabilities compared to other prepared photoanodes with the film thickness (~520nm) more than hole diffusion length (~100 nm). The ultimate improvement is to enhance charge separation in the bulk of film more than the hole diffusion length.

In order to illustrate charge separation in the bulk and transport to the reactive surface due to alkali metal doping, the bulk charge separation efficiency (Φ_{sep}), charge transfer efficiency (Φ_{trans}) and total efficiency ($\Phi_{\text{abs}} \times \Phi_{\text{sep}} \times \Phi_{\text{trans}}$) of photoanodes were calculated. From Figure 16c, the Li doping has increased Φ_{sep} up to ~100 % from $27 \pm 1.4\%$ of pristine BiVO₄, whereas Na doping has increased the Φ_{sep} up to 91 ± 3.8 . This shows that Li doping played a significant role in charge separation in bulk. Respective, the overall efficiency Φ_{abs}

$\times \phi_{\text{sep}} \times \phi_{\text{trans}}$ for overall water oxidation kinetics is shown in Figure 16d for all photoanodes.

The total efficiency is maximum ($40 \pm 2\%$) for Li:BiVO₄ photoanode.

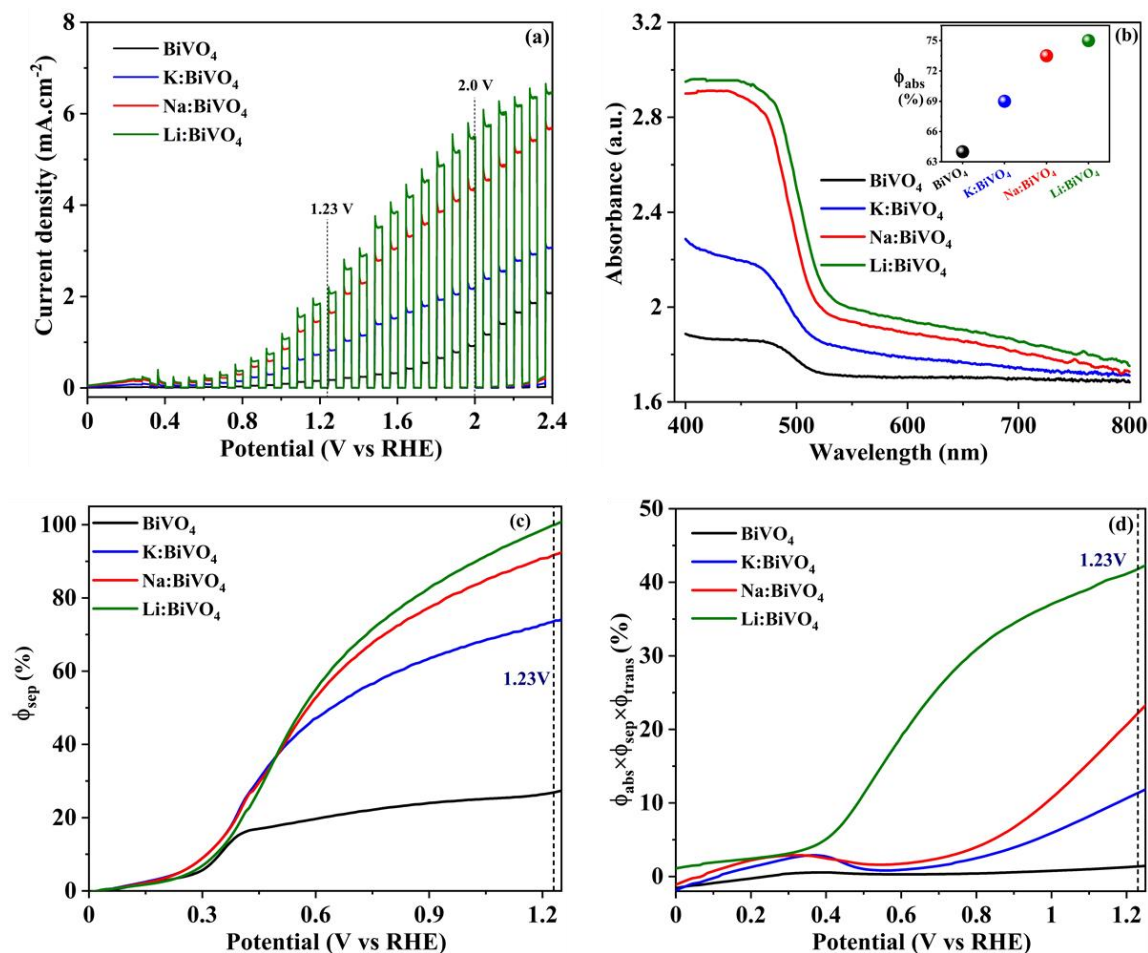


Figure 16 (a) J-V plot for (a) pristine BiVO₄, K:BiVO₄, Na:BiVO₄ and Li:BiVO₄ photoanodes. (b) Absorption spectra (inset: absorption efficiency), (c) separation efficiency and (d) total efficiency at 1.23V vs RHE in 0.1 M K₂HPO₄ (pH: 8.0) for pristine BiVO₄, K:BiVO₄, Na:BiVO₄ and Li:BiVO₄ photoanodes.

3.4 The incident photon-to-current conversion efficiencies (IPCE)

The incident photon-to-current conversion efficiencies (IPCE) of the photoelectrode are measured at 1.23 V vs RHE (Figure 17). Pristine BiVO_4 photoanode demonstrated IPCE from $\lambda \leq 510$ nm. However, on doping with Na and K, the IPCE onset extended up to $\lambda \leq 530$ nm and $\lambda \leq 520$ nm. The Li:BiVO_4 photoanodes showed the highest IPCE value 45 ± 3.5 % followed by Na:BiVO_4 ($38 \pm 2\%$), K:BiVO_4 ($18 \pm 1\%$) and BiVO_4 ($4.5 \pm 0.2\%$), respectively at 420 nm. Along with IPCE, Integrated photocurrents were calculated (Figure 17: secondary Y-axis) to obtain current integrated close to experimentally obtained PCD (Figure 16a) at 1.23 V vs RHE for all photoanodes. The integrated current density ¹¹³ (shown on the secondary Y-axis) corresponding to the IPCE matches well with the experimental PCD value of $2.2 \text{ mA}\cdot\text{cm}^{-2}$ at 1.23 V vs RHE for Li:BiVO_4 . The absorbance (Figure 16b) and the IPCE (Figure 17) values demonstrate the extended wavelength range (400 to 550 nm) by the Li:BiVO_4 photoanode towards PEC activity.

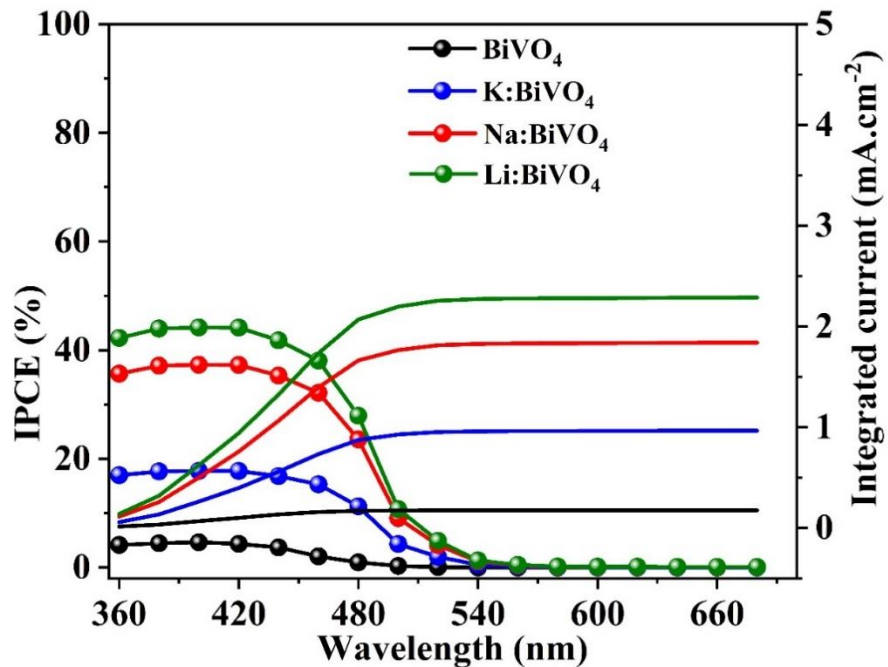


Figure 17 Incident photon-to-current efficiency (IPCE) for BiVO₄, K:BiVO₄, Na:BiVO₄ and Li:BiVO₄ photoanodes measured at 1.23 V vs RHE in 0.1 M K₂HPO₄ (pH: 8.0) electrolyte under 1 sun illumination. Figure 17: Y-axis demonstrated calculated integrated current.

3.5 XRD and Raman spectroscopy

From the XRD patterns shown in Figure 18, all the peaks were matched with the standard JCPDS #014-0688 and confirmed the clinobisvanite (monoclinic scheelite) structure of BiVO₄. Evidently, there were no other impurity phases in the doped samples, validating that 4 wt % doping of alkali metal did not change the crystal structure/space group of the BiVO₄ system. However, there were small shift (0.01 – 0.06 °) in the peaks (-121)/ (121) and (040) towards lower 2θ values for the shift relatively higher for the Li and Na doped compared to that with the K:BiVO₄ and BiVO₄ sample. The shift in the peaks (130), (-121) and (121) was given in Figure 18 to quantify the shift. The lattice parameters a, b and c increased slightly, leading to the unit cell volume expansion (~0.09 or 0.13%) for Li, Na or K doping compared to pristine BiVO₄, indicating that the doped atoms occupied in the interstitial position of BiVO₄ crystal lattice.

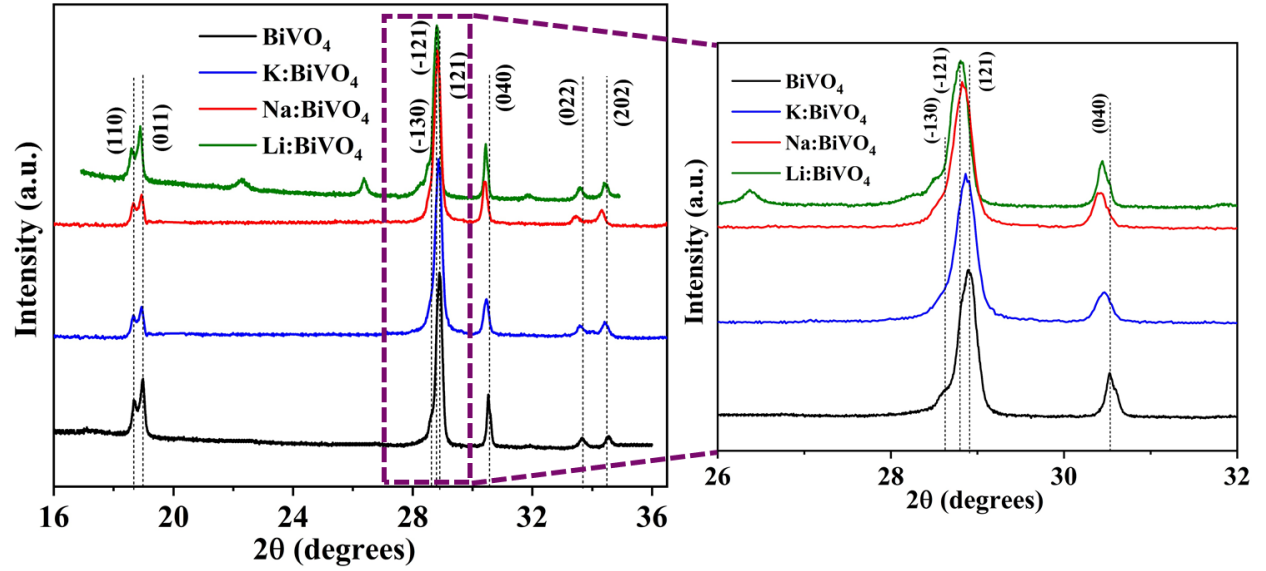


Figure 18 XRD spectrum of pristine BiVO₄, K:BiVO₄, Na:BiVO₄ and Li:BiVO₄ films.

Raman analysis (Figure 19) showed a shift in the peak positions of BiVO₄ due to the incorporation of alkali metal. The major peaks for pristine BiVO₄ sample were observed at 826.46, 365.68 and 332.7 cm⁻¹, corresponding to the δ_s (V-O), δ_s (VO₄³⁻) and δ_{as} (VO₄³⁻) stretching mode vibrations, respectively. It was observed that the most intense δ_s (V-O) peak shifted towards higher wavenumber, and it was maximum for the Li:BiVO₄ and Na:BiVO₄ sample, which confirmed the alkali metal placement in the BiVO₄ lattice that distorts the vibrational modes of V-O bond and VO₄³⁻ deformation modes.

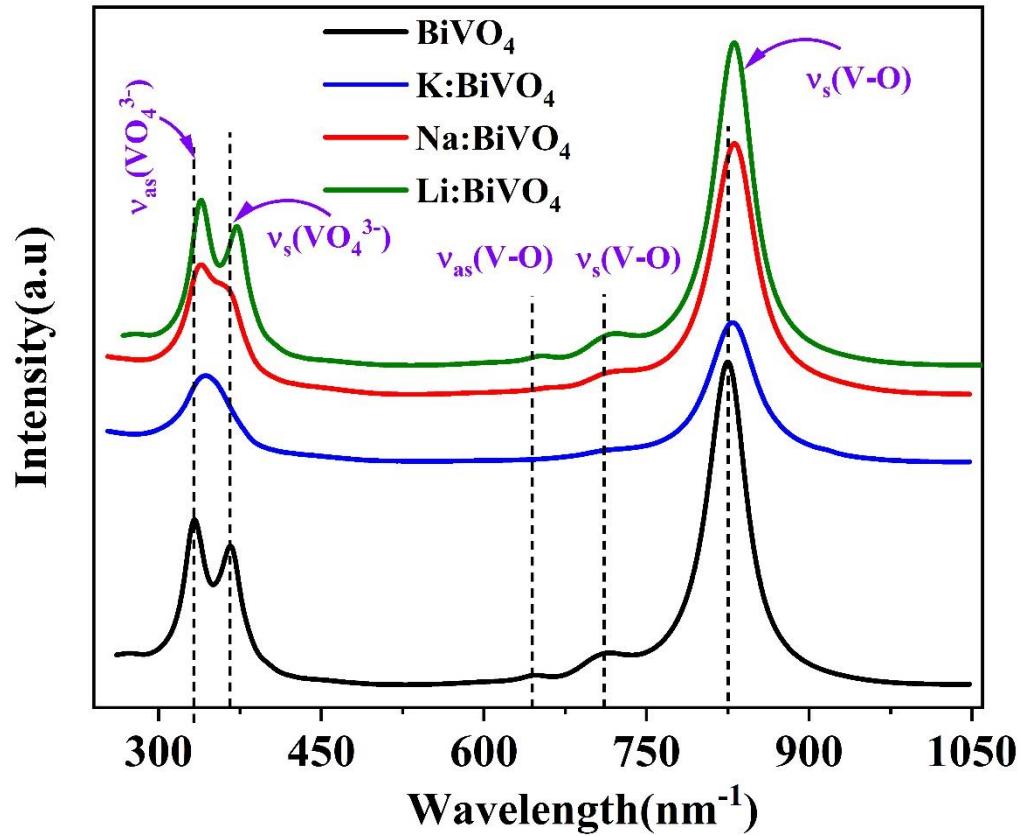


Figure 19 Raman spectrum of pristine BiVO₄, K:BiVO₄, Na:BiVO₄ and Li:BiVO₄ films.

3.6 DFT calculations

The first principles of DFT calculations were carried out for the Li and Na doped BiVO₄ to validate the experimental results. Figure 20 (i-v) showed the initial placement of one sodium atom in the different interstitial positions in the BiVO₄ unit cell, Figure 20 (vi-x) showed the relaxed Na doped BiVO₄ structure through the DFT calculations.

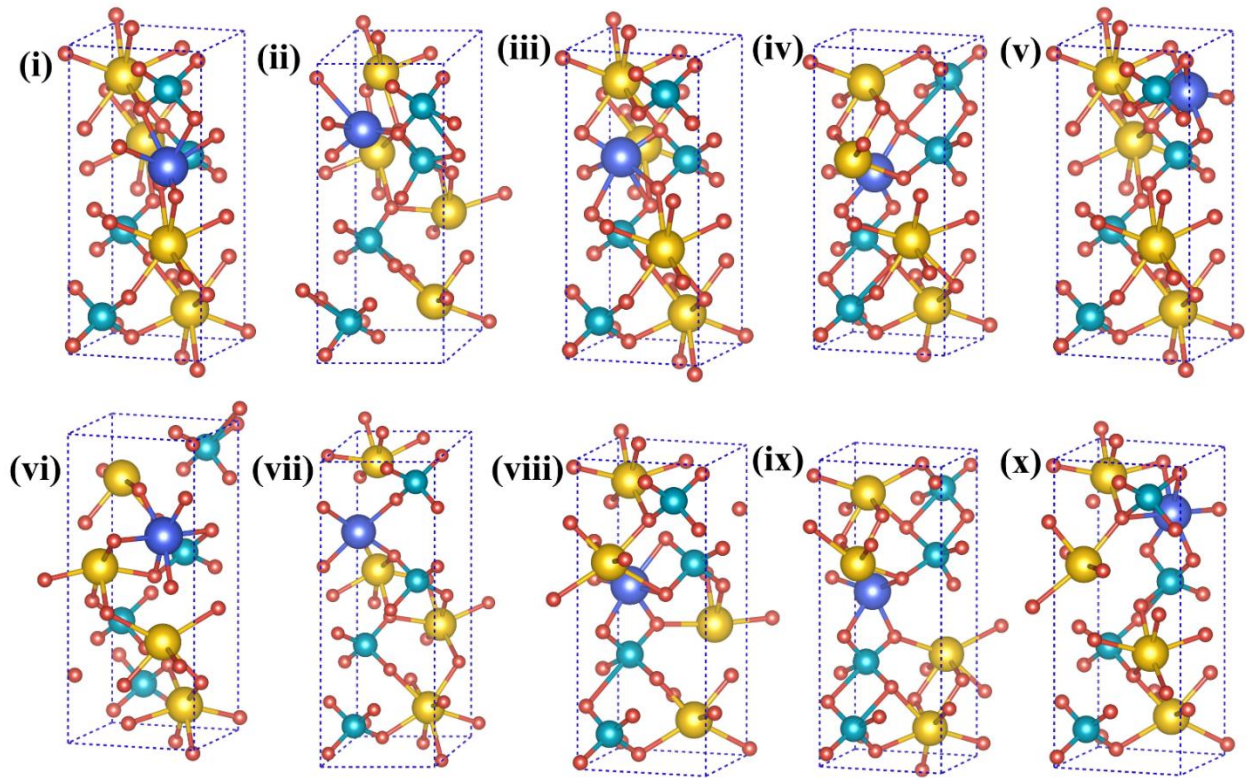


Figure 20 (i-v) various initial placements of sodium atom in BiVO_4 lattice, (vi-x) DFT relaxed final structures.

The most energetically favorable configuration for Li and Na placed BiVO_4 are shown in Figure 21. It was noticed that 4% Li and Na doping did not affect the space group of the BiVO_4 crystal structure.

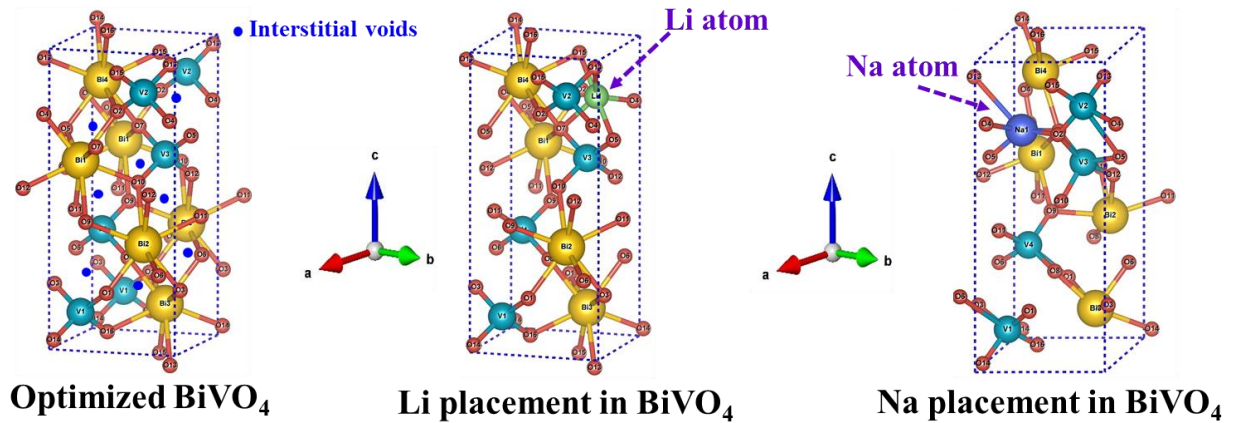


Figure 21 Optimized crystal structure of BiVO_4 and various interstitial void is also denoted. Optimized crystal structure of Li and Na placed crystal structure.

The simulated band structures in Figure 22a shows the presence of one interband for $\text{Li}:\text{BiVO}_4$ with reduction of bandgap (2.14 to 2.06 eV)^{114,115} for the Li doped compared to the pristine BiVO_4 . With the Li doping at the interstitial position in BiVO_4 , both the conduction and valence bands move downward, leading to a reduction in the bandgap by 0.08 eV due to a larger downward shift of the conduction band. Three interbands were observed for $\text{Na}:\text{BiVO}_4$ in Figure 22b, identified as bands #104 and 105 with the energies at ~ 0.25 eV and band #106 with the energy at ~ 1.8 eV between the valence and conduction bands. These interbands appeared mainly due to atomic distortion generated by Li and Na doping in the interstitial position in the BiVO_4 system. It was observed that the electron-occupied interband 104 is dominated by 62.8% p_z orbital mainly located at four oxygen atoms (O5, O7, O10, O12) which are nearby Na to form a Na-O bond (for O5, O7) and V-O and Bi-O bonds (for O10, O12). The electron-occupied interband #105 is mainly contributed by $\sim 95\%$ d_{z^2} orbital locating at the V3 atom forming Na-V bond. Finally, the unoccupied interband #106 is dominated by mostly 97% d_{z^2} orbitals at V1 and V2 atoms,

forming V-O bonds near the doping Na element. The presence of these interbands results in a slight reduction of band gap by 0.04 eV for Na:BiVO₄ (2.19 eV) compared to pristine BiVO₄ (2.23 eV) ^{116,117}.

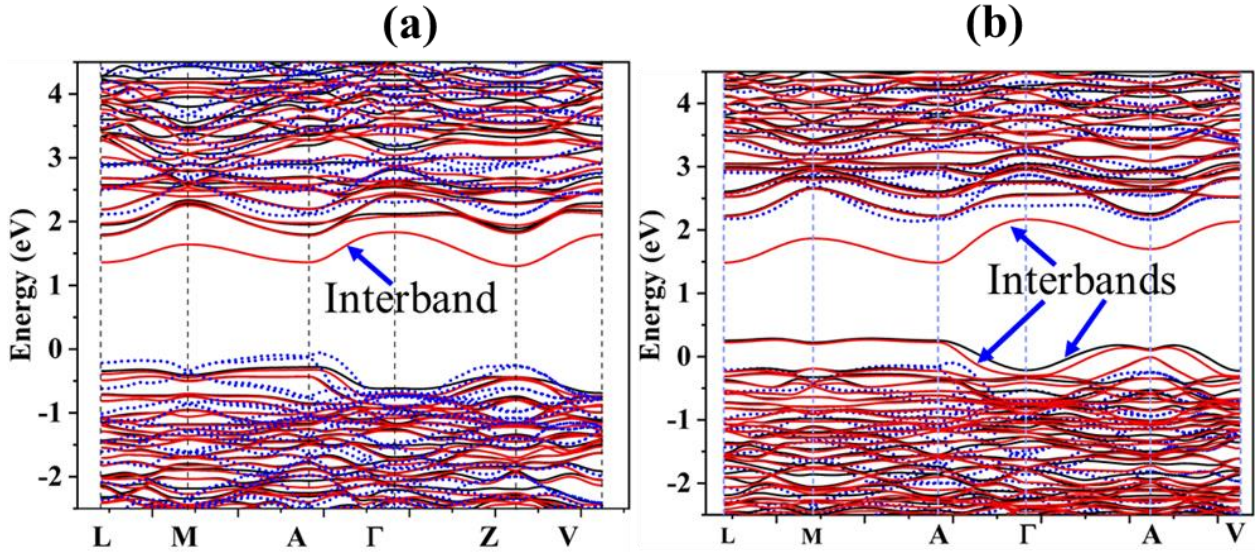


Figure 22 The spin-polarized electronic band structures of the pristine BiVO₄ (dots) (a) Li and (b) Na doped BiVO₄ with the spin up and down showing in red and black lines, respectively.

In addition, the absorption spectrum (imaginary part of dielectric function) was calculated from DFT. Figure 23a shows the simulated absorption spectrum (imaginary part of dielectric function) for the pristine and Li doped BiVO₄. As seen, both the pristine and Li doped BiVO₄ exhibited higher absorption > 2 eV. However, the Li:BiVO₄ showed an additional absorption peak ~ 1.2 eV, possibly due to a reduction in the band gap. This supports the experimental observation of increased absorption at extended lower energy regions due to Li doping (Figure 16b).

The simulated absorption spectrum for the pristine BiVO_4 and Na:BiVO_4 demonstrated an absorption onset ~ 2 eV, as shown in Figure 23b. Additional absorption was found for the Na:BiVO_4 in the form of the absorption peak at ~ 1 eV, which might be due to the multiple interbands formation and a small reduction in the bandgap. Similar enhanced absorption behavior was found through UV-vis measurements, as shown in Figure 16b. The site-projected density of states was evaluated for the pristine BiVO_4 , Na:BiVO_4 and Li:BiVO_4 . It was observed that oxygen atoms mostly contributed valence bands, and conduction bands were vastly by Bi and V atoms. The results obtained from the theoretical, experimental analysis and various characterizations confirmed that Li or Na doped BiVO_4 photoanode showed improved PEC performance due to the presence of multiple interbands, a slight reduction in the bandgap, increase in the electron-hole diffusion length and high charge transfer rate.

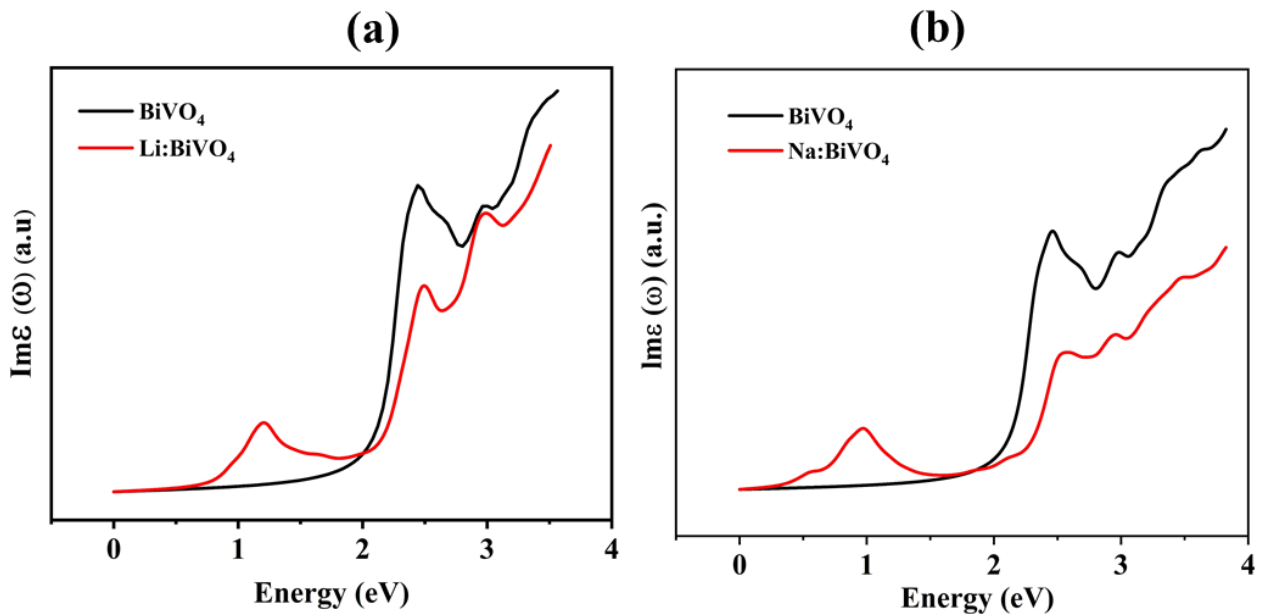


Figure 23 The DFT calculated absorption spectra for the pristine BiVO₄ along with (a) Li:BiVO₄ and (b) Na:BiVO₄.

3.7 XPS analysis

XPS analysis was carried out to determine the oxidation state of individual elements (Bi, V, K, Na and Li) in the pristine and doped BiVO₄ samples. The major peaks for Bi 4d_{5/2} (443.2 eV), Bi 4d_{3/2} (466.9 eV), V 2p_{3/2} (517.78 eV) and V 2p_{1/2} (525.28 eV) observed confirmed the oxidation state of Bi and V as +3 and +5, respectively in the pristine BiVO₄. Doped samples showed a slight decrease in the binding energies of Bi 4d and V 2p due to change in the local coordination environment of Bi³⁺ and V⁵⁺ ions¹¹⁸. It is also possible that the electron sphere around alkali metal in the interstitial void can exert electrostatic repulsive forces, reducing the Bi-O and V-O bond energy and increasing the unit cell volume, which also supported the observation in the XRD analysis (Figure 18). The binding energy corresponding to the individual doped alkali metal (K 2p_{3/2}: 294.08, K 2p_{1/2}: 296.77, Na 1s: 1071.8 eV and Li 1s: 55.6 eV) confirmed the oxidation state +1. Figure 24 a-d showed the high-resolution XPS spectra in the O 1s region for all doped and pristine samples. As shown, the surface lattice oxygen (V-O), surface adsorbed oxygen (-OH) and alkali metal to oxygen interaction bond (M-O) was located at ~ 530.3, ~532 and ~529 eV, respectively. The area ratios of peaks V-O: -OH:M-O in pristine BiVO₄ and alkali metal-doped BiVO₄ were given in Figure 24 a-d. It was observed that the interaction due to the insertion of Li and Na in the interstitial position of BiVO₄ lattice was ~ 3 to 2 times compared to that with K due to the size difference. Further, the alkali metal doping

concentration was validated from the peak fitting of each component (Bi, V, O, K, Na and Li).

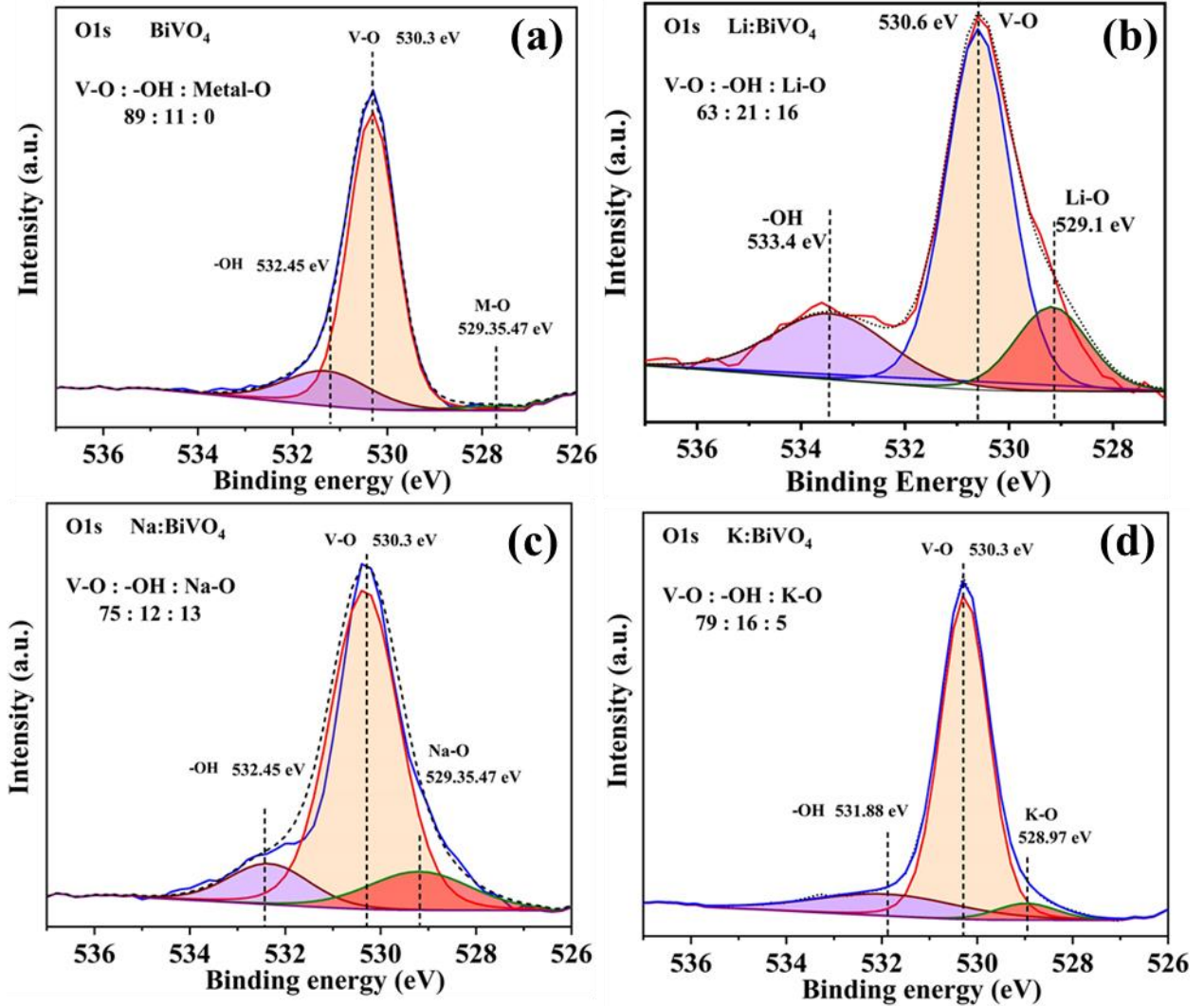


Figure 24 XPS spectra of fitted O1s peaks using Shirley background for (a) pristine BiVO₄, (b) Li:BiVO₄, (c) Na:BiVO₄ and (e) K:BiVO₄ films.

3.8 Doppler broadening spectroscopy

Figure 25 shows the *S-E* profile of FTO substrate, pristine and alkali metal-doped BiVO₄ samples. The solid lines through the data points explained the fitting of experimental *S-E*

profiles using VEPFIT (details are provided in supplementary information). In the case of FTO substrate, S -parameter first decreased from surface to positron implantation energy ~ 7.5 keV, attributed to the back diffusion of implanted positrons because the back diffused positron annihilated through a state similar to positronium with a higher S -parameter. However, the fraction of back diffused electrons was reduced, leading to a decrease in S -parameter with the increase in implantation energy¹¹⁹. Beyond ~ 7.5 keV implantation energy, S -parameter continuously increased, attributed to the positron implantation to the glass portion of FTO. On the other hand, the S - E profiles for pristine and alkali metal-doped BiVO₄ films were different from the FTO and unique to each other. The observed decreasing trend of S - E profiles (Figure 28a) in all the films indicates no positronium formation occurred within the bulk of the films, which validated the crystallinity as confirmed by XRD (Figure 18). The changes observed in S - E profiles on Li, Na and K doping were due to modifications in the open volume defects such as vacancy or vacancy clusters. Interestingly, the S -parameter continuously increased when positrons were implanted at higher energies (> 15 keV). The diffusion length of the implanted positrons was given in Figure 28a (inset). For the pristine BiVO₄, the positron diffusion length was 9.65 ± 0.92 nm, which was shorter than the bulk diffusion length in crystalline oxides¹²⁰. The shorter diffusion length in BiVO₄ films confirmed the presence of negatively charged (cation vacancy) or neutral vacancy defects or vacancy clusters (Bi or V vacancy defects), which act as a potential trap for positrons. On the other hand, K doping demonstrated a decrease in characteristic S -parameter and a slight increase in the diffusion length (13.49 ± 1.78 nm), indicating a small reduction in the defects density compared to pristine BiVO₄ films. On Na and Li doping, a significant increase (~ 4 times) in diffusion length

(54.19 ± 5.6 and 63.51 ± 6.4 nm) was observed along with a decrease in characteristic S -parameter value. It was dictated that Li and Na doping reduced Bi or V based vacancy defects in the film. In order to investigate the type of defects in these films, S - W correlation plots (Figure 25b) showed that the data points of all the three films follow a single trend indicating that the type of defects was similar in all three samples. However, their number density and chemical surrounding were modified due to the presence of alkali metal. The Bi and V based defects density in the bulk of the film was minimum in the Na:BiVO₄ and Li:BiVO₄ sample.

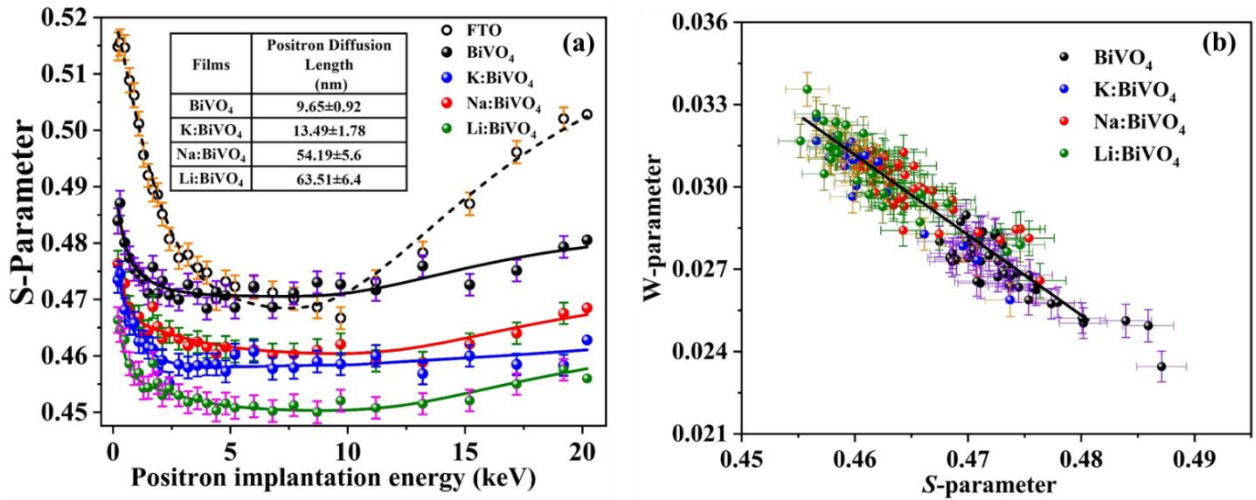


Figure 25 Doppler broadening spectroscopy measurements (a) S - E profiles; and (b) S - W correlation plots for substrate, pristine BiVO₄, K:BiVO₄, Na:BiVO₄ and Li:BiVO₄ films.

3.9 Conclusion

The alkali metal-doped BiVO₄ thin-film based photoanodes were prepared by ultrasonic spray coating technique and the planner structure with porous grains was confirmed by SEM analysis. The IPCE measurements confirmed the extended light absorption by

Li:BiVO₄ and Na:BiVO₄ compared to K:BiVO₄ and pristine BiVO₄. The XRD and Raman results indicated that alkali metal occupied the interstitial position of the BiVO₄ lattice structure. The diffusion length of charge particles was measured by implementing a positron at the surface of the thin films and found that the diffusion length of the positron increased by ~ 4 times in Na:BiVO₄ and Li:BiVO₄ compared to that of the pristine. It was also observed that the Bi and V based defect density was minimum on alkali metal doping in BiVO₄. The *ab initio* DFT calculations confirmed that the Li and Na doping in the BiVO₄ interstitial site was energetically the most favorable position. It was evident that oxygen atoms formed weak bonds with Li and Na atoms, and an interband and multiple internbands formed between conduction and valence band, leading to a small reduction in the bandgap for Na:BiVO₄ and Li:BiVO₄.

4. CHAPTER 4 SITE DOPING/CO-DOPING IN BiVO₄ WITH JUNCTIONS FORMATION

4.1 Introduction

Doping with metals is one of the promising approaches for improving the intrinsic properties of BiVO₄⁷⁴. There are several studies on systematic doping of Tungsten (W) (approximately 0-4 wt. %) in the BiVO₄ system and correlating its PEC performance with respect to defect generation⁷⁵⁻⁷⁹. Pattengale *et al.*¹²¹ has reported doping of 1.8 % W in BiVO₄ for improving PEC performance by 8-10 times compared to its undoped counterpart due to the formation of less distorted local structure at Bi's center, which favorably extends the electron lifetime by dramatically altering the nature of the recombination sites. Cho *et al.*¹²² reported that incorporating W in BiVO₄ induced crystal deformation of its lattice, which leads to a 10 times improvement in water oxidation compared to its undoped counterpart. Shi *et al.*⁷⁷ have investigated the role of surface states (SS) in W-doped BiVO₄ photoanodes for PEC water splitting and found the optimum W-doping level of 2 % to suppress SS, which act as electron-hole pair recombination sites, leading to a significant 10-12 times photocurrent increase with respect to the pristine BiVO₄ at 1.23 V vs RHE.

4.2 Stoichiometric and non-stoichiometric doping of W in BiVO₄

Thus far, in the reported literature, W-doping was gradually increasing out to obtain $\text{BiV}_{1-x}\text{W}_x\text{O}_4$ which increases the number of charge carriers (N) by substituting W at V sites^{77,123,124} and, thus, promoting bulk and interfacial charge separation, improving surface morphology, minimizing charge-trapping sites, increasing charge diffusion length, decreasing space charge region width, and suitably modifying Fermi level^{78,79,122,124,125}. However, It is necessary to optimize the doping level as well as the composition of BiVO_4 to avoid the generation of defect sites such as Bi and O vacancies which can act as recombination sites^{126,127}. Krol¹²⁸ has shown some issues with substituting W^{6+} for V^{5+} atoms in doped $\text{BiV}_{1-x}\text{W}_x\text{O}_4$ composition. In one scenario, Bi vacancies are formed to compensate extra charge from W^{6+} and preserve lattice site stoichiometry. This can lead to a decrease in the conductivity of W-doped n-type BiVO_4 . In another scenario, the lattice site stoichiometry is preserved by the segregation of vanadium out of the BiVO_4 in the form of V_2O_5 . This avoids the need for highly charged cation vacancies, and the W-dopant is now indeed charge-compensated by the desired free electrons. It should be realized that both these scenarios are unfavorable from an energetic point of view. A highly charged defect must be formed in one case, while in the other case, a second phase must segregate out. This leads to an important general observation for ternary – and more complex – metal oxides; doping these materials by simply dissolving a binary oxide is difficult to achieve in practice. An elegant solution for this can be to co-dope the BiVO_4 with excess amounts of W and Bi, so that Bi and W together can balance V charge deficiency. This is a well-known procedure to increase the solubility of binary oxides in ternary oxides in order to incorporate donor- or acceptor-type dopants⁸⁰.

To explore the optimum performance of BiVO₄, it is essential to perform a systematic study of the influence of stoichiometric and nonstoichiometric doping on the electronic structure and carrier dynamics of BiVO₄. The objective of present study was to synthesize stoichiometric and nonstoichiometric composition of W-doped BiVO₄ (i.e. Bi_{1-(x+δ)}V_{1-x}W_{x+δ}O₄; BiV_{1-x}W_{x+δ}O₄ and BiV_{1-y}W_yO₄; x = 0.008; y = 0.03 and δ = 0.005) using facile dip-coating technique and to understand its effect on PEC water oxidation behavior.

The PEC performances of the pristine and W-doped BiVO₄ photoanodes evaluated using linear sweep voltammetry under chopped light illumination on the front side of the electrodes without and with hole scavenger in 0.1M K₂HPO₄ electrolyte are given in Figure 26. It is evident from the plot that PEC performance for the stoichiometric composition of Bi, V and W (sample 2; Bi_{1-(x+δ)}V_{1-x}W_{x+δ}O₄; charge balance: 0) and non-stoichiometric compositions (sample 3; BiV_{1-y}W_yO₄; charge balance: 0.03; Bi atom in excess and sample 4; BiV_{1-x}W_{x+δ}O₄; charge balance: 0.038; Bi and W atom in excess) electrodes are better than pristine BiVO₄ (sample 1). The PEC performance in increasing order were as follows: samples 1 < 2 < 3 < 4. Further, the non-stoichiometrically doped W in BiVO₄ for the co-doping.

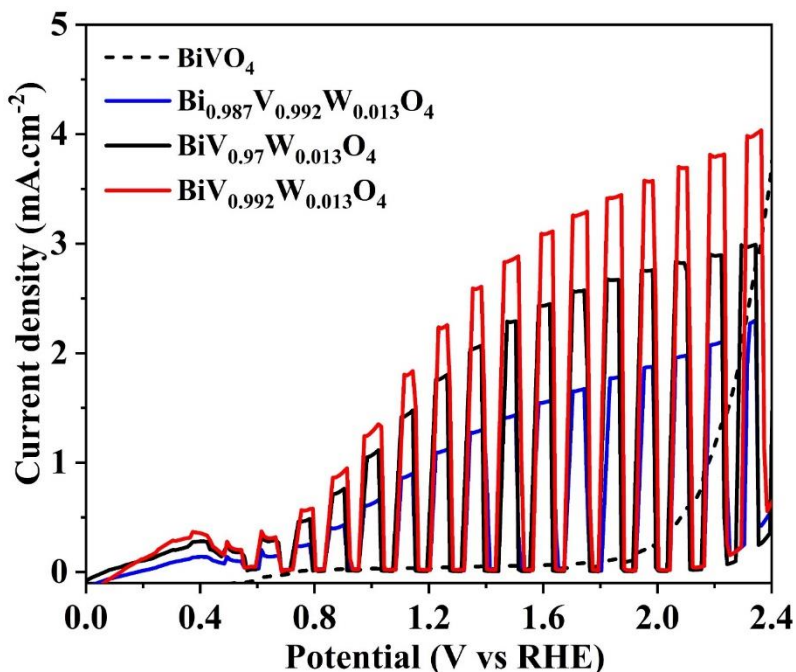


Figure 26 Linear sweep voltammetry for all samples under 1 sun illuminations in K_2HPO_4 electrolyte.

4.3 Rare earth metal doping at Bi site and coding with W in $BiVO_4$

There are several successful cases of doping at the V^{5+} site in $BiVO_4$ ^{129,130}. However, few attempts were made to simultaneously doping at the vanadium and bismuth sites (Bi^{3+}). In an attempt, Jo *et al.*¹³¹ enhanced water splitting performance through dual doping of In^{3+} and Mo^{6+} in $BiVO_4$. The mixed-phase (monoclinic and tetragonal) $BiVO_4$ showed a negative conduction band shift and led to PEC improvement compared to pristine $BiVO_4$, but no significant improvement in light absorption was observed. Xin *et al.*¹³² attempted to co-doped W, Ti in $BiVO_4$ and achieved nominal PCD $\sim 1.6 \text{ mA.cm}^{-2}$ with hole scavengers due to limited enhancement in hole mobility and charge separation. In another

attempt, Zhengbo et al.¹³³ co-doped Fe, W in BiVO₄ and additionally loaded metal-organic framework (MOF) to gain better charge carrier separation and stability of photoanode. The individual Fe and W doping in BiVO₄ showed poor PCD, and even dual doping of Fe, W in BiVO₄, and MOF loading could not significantly improve the PEC performance (1.6 mA.cm⁻² at 1.23 V vs RHE). There are not many reports which show the systematic study of co-doping in BiVO₄ for PEC application. However, most of them used co-doping, specifically using rare earth metals for photo-catalytically degradation of organic waste by utilizing its only extended light absorption property^{134,135}. The rare earth metal co-doping enhances light absorption, but it may lead to decreased charge transport property due to the possibility of charge recombination defect center formation in film and severely affecting PEC performance¹⁰⁴.

In the present study, we have systematically investigated the role of doping/co-doping of W and rare earth metals Er, Yb and Y in BiVO₄ with respect to their light absorption, bulk and surface charge separation and transfer properties. The individual element doping with W was chosen in the current study because it is doping significantly enhances the charge transport property⁸¹. Whereas individual elements Er, Yb and Y were chosen in the current study because of their extended light absorption, leading to high absorption efficiency^{82,83}. The charge separation/transfer and light absorption efficiency estimation revealed that W:BiVO₄ photoanode showed the best PEC performance due to its higher charge separation/transfer efficiencies. Whereas (Y,W):BiVO₄ and (Yb,W):BiVO₄ photoanodes showed improved PEC performance than pristine BiVO₄ due to extended light absorption characteristics ($\lambda \leq 550$) and overall bandgap reduction on Er³⁺, Yb³⁺ or Y³⁺ doping.

4.4 Light absorbance and photoelectrochemical measurements

In order to understand such water splitting performance, the light absorption behavior of photoanodes was evaluated. From Figure 27, it was observed that the light absorption onset extended from ~510 to ~550 nm with Yb³⁺ Er³⁺ and Y³⁺ doping in BiVO₄ in comparison to pristine BiVO₄. This phenomenon was observed even in the case of co-doped (Yb,W):BiVO₄, (Li,W):BiVO₄ and (Y,W):BiVO₄ photoanodes. The observed redshift in the absorption region with Yb³⁺, Er³⁺ and Y³⁺ doping have been well reported in the literature, and it may occur due to intrinsic electron transition between O and Yb or Y orbitals^{83,82}. It was observed that with Er doping in BiVO₄, the absorbance range widened from visible to NIR region i.e. wavelength region from 400-614 nm (Figure 27). Absorption for BiVO₄ is started from a lower wavelength ~535 nm, even after W doping the absorption didn't improve significantly. However, on the addition of Er, absorption enhanced significantly for Er:BiVO₄ and (Er,W):BiVO₄ electrode due to additional absorption in ~535 to ~680 nm light spectrum region. In absorption spectra at ~554 and ~675 nm, two minor bands were identified in Er³⁺ doped electrodes. This could be assigned to the transitions from the ground state ⁴I_{15/2} to excited states ⁴H_{11/2} (~554 nm) and ⁴F_{9/2} (~675 nm) of Er³⁺, respectively^{136,137}. At the same time, no substantial change in absorption onset was observed with W⁶⁺ doping in BiVO₄¹⁰⁴. The estimated absorption efficiency (η_{abs} : Figure 27: inset) from light-harvesting efficiency (LHE) showed that (Y,W):BiVO₄, (Er,W):BiVO₄ photoanode attained absorption efficiency 77 ± 4 and $74 \pm 3\%$ in comparison to 63 ± 3 and $62 \pm 3\%$ (Figure 27 inset) of W doped and pristine BiVO₄, respectively. The pristine and W doped BiVO₄ samples have shown a similar optical band ~2.52 eV. Yb and Y doped/co-doped BiVO₄ samples have shown decreased optical band,

i.e. 2.37 and 2.29 eV, respectively, due to redshift in the absorption^{83,82}. Corresponding band gap calculation for Er-doped shows that Er:BiVO₄ electrode has minimum ~2.37eV bandgap. The absorbance measurement confirmed that Er, Y, Yb doping enhances light absorption efficiency, whereas W doping does not significantly affect the absorption efficiency of BiVO₄ photoanode.

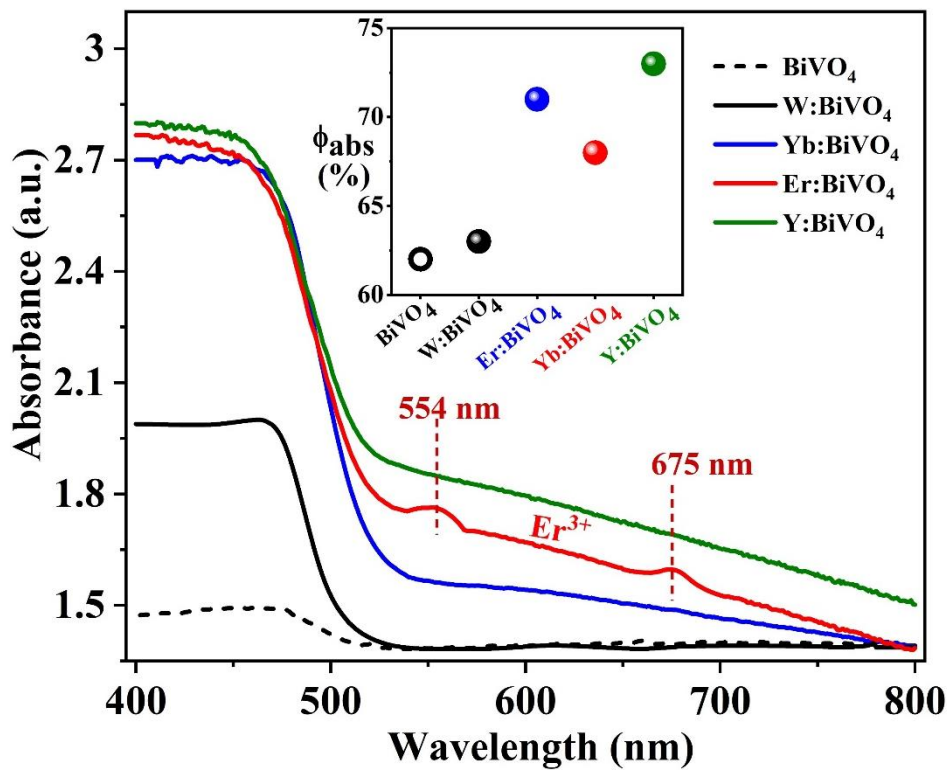


Figure 27 UV-vis absorption spectra for site doping samples

The water-splitting property of Er, Y, Yb, W individual and co-doped BiVO₄ photoanodes was evaluated for PEC performance (Figure 28). It was observed from Figure 28 that with individual Er, Yb, Y and W doping in BiVO₄, the PCD improved 2, 3, 4 and 23 times corresponding to the pristine BiVO₄. The significant increase in PCD of W:BiVO₄

compared to Er:BiVO₄, Yb:BiVO₄ or Y:BiVO₄ photoanodes are attributed to better bulk charge pair separation and transfer¹³⁸. Considering better PEC performance of the W:BiVO₄ photoanode, BiVO₄ was co-doped as (Er,W), (Yb,W) and (Y,W) to enhance the performance of individual Er, Yb and Y doped BiVO₄ photoanodes. The (Er,W):BiVO₄, (Yb,W):BiVO₄ and (Y,W):BiVO₄ photoanodes demonstrate obvious increment over Er:BiVO₄, Yb:BiVO₄ or Y:BiVO₄ photoanodes by achieving PCD 1.58 ± 0.08 , 1.29 ± 0.06 and 1.94 ± 0.1 mA.cm⁻² (Figure 28) respectively, but it could not perform better than W:BiVO₄ photoanode (2.2 ± 0.13 mA.cm⁻²). One possible reason for the lower PEC performance could be because even though there is high charge separation in bulk on W doping, the defect is generated in bulk and at the surface with substitutional doping of Er³⁺, Yb³⁺, Y³⁺ at Bi³⁺ sites could act as a recombination center.

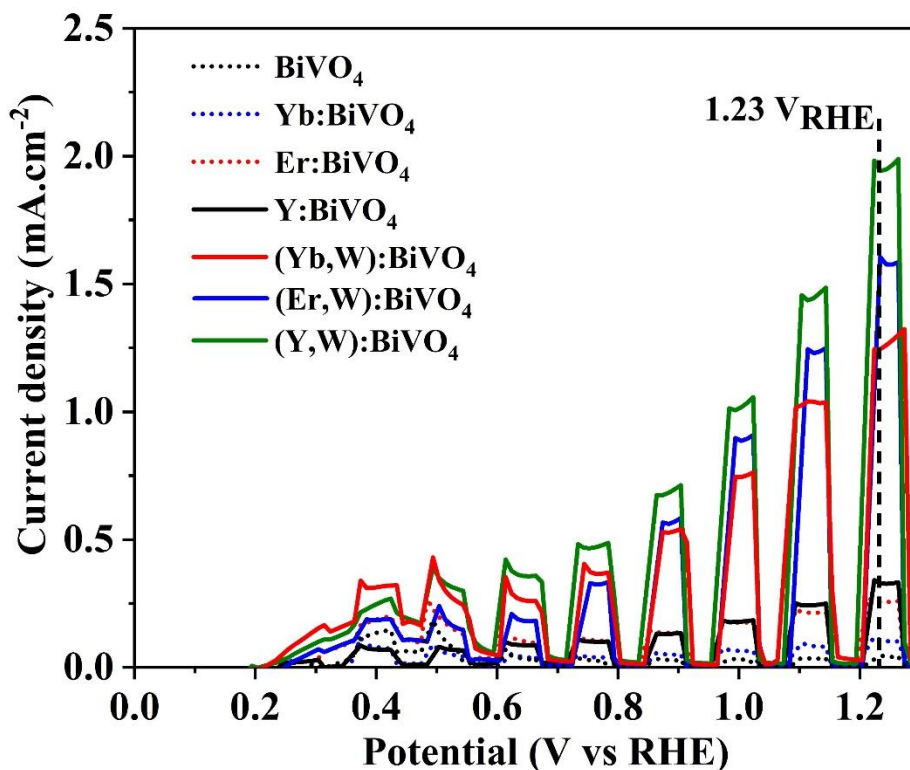


Figure 28 Linear sweep voltammetry for of sites doped and co-doped samples under 1 sun illuminations in K_2HPO_4 electrolyte.

The effect of catalysts aided in the negative shift of the onset potential which was observed in the PCD behavior. This negative shift in the onset potential confirms the conduction band shift, leading to high charge transfer efficiency and minimizing the recombination to increase water splitting performance. The Mott Schottky analysis also confirmed the negative shift in the onset potential. Where, negative shift for Yb:BiVO₄, Er:BiVO₄ and Y:BiVO₄ photoanodes are 98, 118 and 153 mV, respectively, compared to pristine BiVO₄. The relative shift in conduction band position was calculated from the Mott-Schottky. As a result, photoanodes are close to the water reduction potential of 0 V vs RHE, making the water-splitting process more facile.

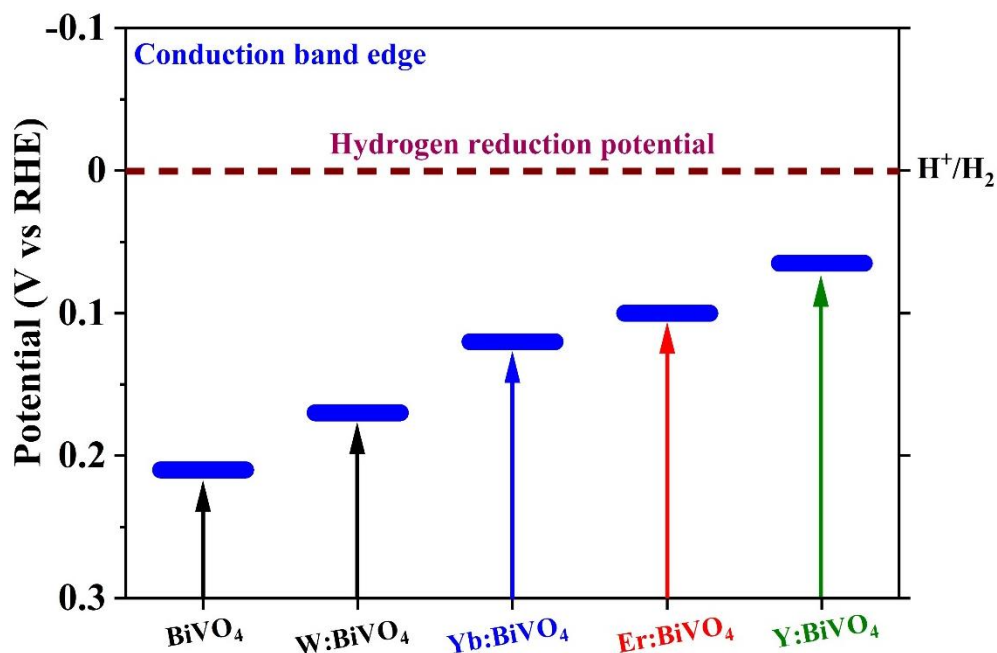


Figure 29 Shift in the conduction band edge of site doped and co-doped samples.

To support above argument on the bulk charge separation and surface transfer efficiencies, corresponding bulk and surface resistance of doped/co-doped photoanodes were investigated using the Electrochemical impedance (EIS) method. As shown in Figure 4a, pristine BiVO₄ demonstrates maximum impedance, which elucidates the poor water oxidation kinetics of pristine BiVO₄. Whereas W:BiVO₄ photoanode demonstrates minimum impedance, indicating that better charge separation with surface transfer leads to better water oxidation kinetics. Randles circuit (Figure B4a) contains multiple elements such as external contact, bulk and surface resistance and capacitance connected with the Helmholtz layer at photoanode and electrolyte interface. The estimated resistance and capacitance of photoanodes are shown in Figure 4b. The film bulk resistance (R_b) gradually decreases with Er, Y or Yb doping and significantly decreases with W doping. The co-doping of Er, Yb or Y with W in BiVO₄ increases the bulk resistance concerning W:BiVO₄

photoanode. The capacitance in bulk (C_b) was comparatively lower for W:BiVO₄ and (Y,W):BiVO₄ photoanode, which denotes that charge accumulation is less in the bulk of the film, i.e. getting separated and transported easily. It validates the achieved charge separation efficiency trend in Figure S3c. Additionally, surface charge transfer resistance (R_s) followed following decreasing trend: BiVO₄ > Yb:BiVO₄ > Er:BiVO₄ > Y:BiVO₄ > (Yb,W):BiVO₄ > (Yb,W):BiVO₄ > (Er,W):BiVO₄ > (Y,W):BiVO₄ > W:BiVO₄. The W:BiVO₄ photoanode showed minimum surface resistance, and again, co-doping with Er, Yb or Y led to an increase in the surface resistance. The surface capacitance (C_s) is maximum on W doped photoanode, illustrating that charges are accumulated on the film surface and available for the water oxidation process. It validates the achieved charge transfer efficiency trend in Figure B3d than pristine BiVO₄.

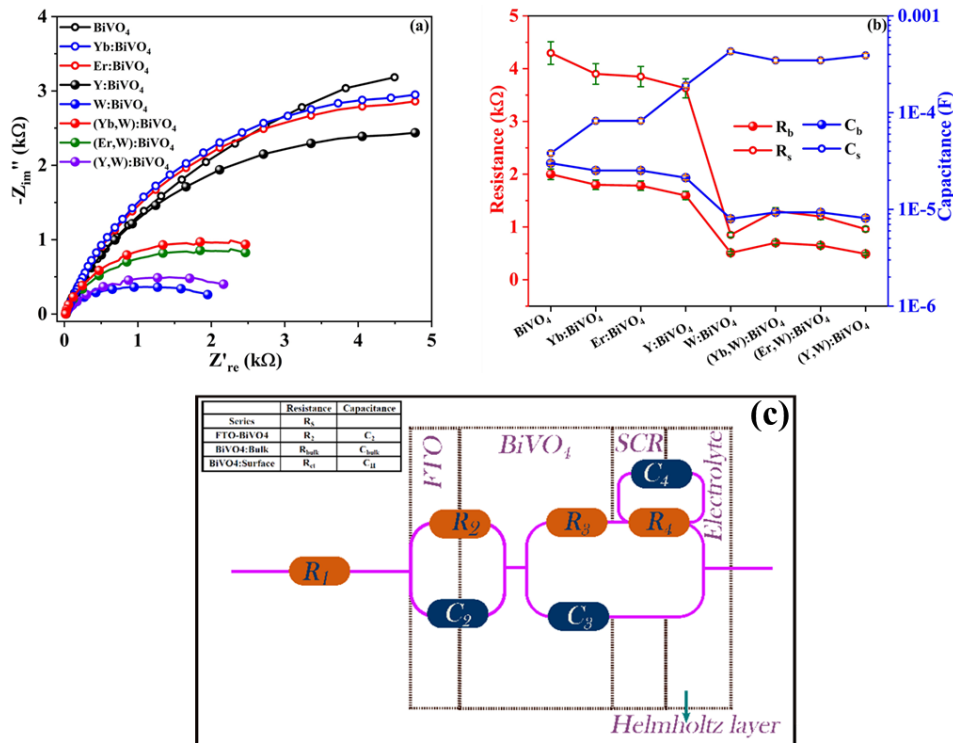
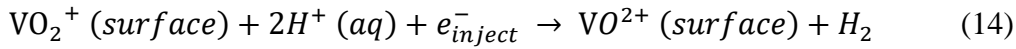
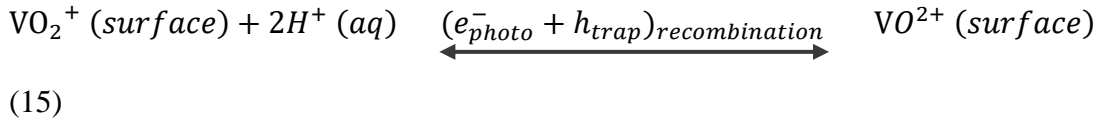


Figure 30 (a) Electrochemical impedance spectra (EIS) plot of pristine BiVO₄, Yb:BiVO₄, Er:BiVO₄, Y:BiVO₄, W:BiVO₄, (Yb,W): BiVO₄, (Er,W): BiVO₄ and (Y,W):BiVO₄ photoanodes measured at 1.23 V vs RHE. (b) Resistance and capacitance plot at bulk and surface (R_b, R_s, C_b and C_s). (c) Randle circuit for the resistance and capacitance calculation in bulk and surface.

In order to understand the recombination center or reaction sites at the photoanode surface and electrolyte interface, CV measurement was performed in K₂HPO₄ electrolyte from potential 0.45 to 2.5 V vs RHE in the dark (Figure 3c). The observed cathodic peak at ~1.45 V vs RHE describes the surface reaction given in eq 14⁷⁷.



Surface reaction VO₂⁺/VO²⁺ is irreversible direct that charge transfer from trap sites (termed as a surface state) and detrapping process is slow which lead to accumulation of charges in the trap sites and then increases recombination (eq 15)¹⁰⁴.



Since the peak potential is greater than the water oxidation potential (1.23 V vs RHE), the potential range for this state extends over the water oxidation in the dark. W:BiVO₄ photoanodes show a smaller peak intensity than other photoanodes, which depicts the low number of trap site formations, leading to higher PEC performance. The peak intensity (estimated by peak ~1.45 V vs RHE fitting using Matlab software) decreasing sequence is as follows: W:BiVO₄ > (Y,W):BiVO₄ > (Er,W):BiVO₄ > (Yb,W):BiVO₄ > Y:BiVO₄ > Er:BiVO₄ > Yb:BiVO₄ > BiVO₄.

The observed phenomena is explained by the formation of recombination centers on the electrode surface (surface states) with Er, Y/Yb doping along with W⁷⁷. The SS has been reported to influence charge transfer at the semiconductor electrode/electrolyte interface because they can work as reaction sites and recombination centers on the electrode surface¹³⁹. Doping of Er, Y and Yb enhanced light absorption efficiency (Figure 3b) better than W doped BiVO₄ sample. However, there are recombination centers on the BiVO₄ photoanode surface (surface states) with Er, Y& Yb doping, and it remains even along with W co-doping. As given in above supporting Figure 3c, the SS has been reported to influence charge transfer at the semiconductor electrode/electrolyte interface because they can work as reaction sites and/or recombination centers on the photoanode surface. The irreversible peak (VO₂⁺/VO²⁺ at ~ 1.45 V vs RHE, Figure 3c) intensity values follow the order: (Yb,W):BiVO₄ > (Er,W):BiVO₄ > (Y,W):BiVO₄ > W:BiVO₄, indicating formation of large number of recombination sites for the (Yb,W):BiVO₄, (Er,W):BiVO₄ and (Y,W):BiVO₄ photoanodes. This is a direct evidence for the PCD with the following order: (Yb,W):BiVO₄ < (Er,W):BiVO₄ < (Y,W):BiVO₄ < W:BiVO₄.

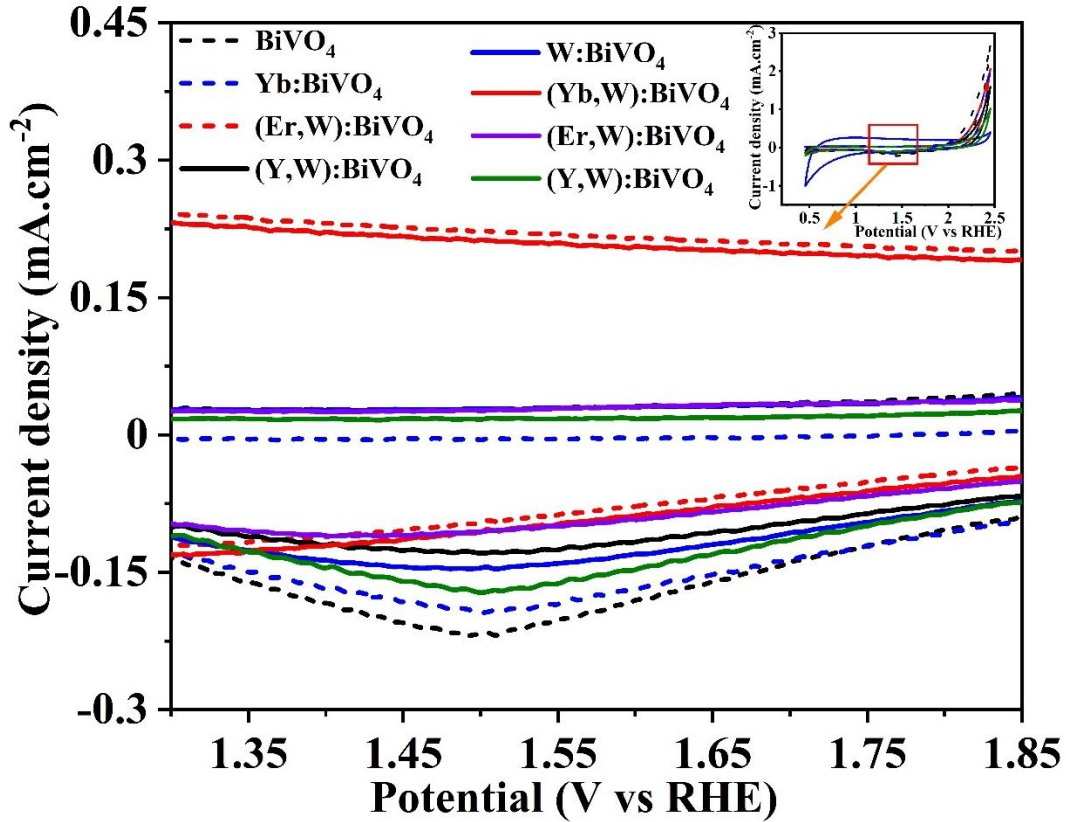


Figure 31 Cyclic voltammetry in dark at 20 mV/sec in 0.1 M K_2HPO_4 .

4.5 Type II heterojunction formation along with p-n junction

In $BiVO_4$, type-II heterojunction with WO_3 is most suitable due to the more negative potential of the conduction band and valence band of $BiVO_4$, which mediate for the efficient electron transfer from $BiVO_4$ to FTO film^{140,141}. Lee *et al.*¹⁴¹ have reported the most successful case of type-II heterojunction formation with a conformal coating of one-dimensional WO_3 nanorod and $BiVO_4$ by pulse electrodeposition and achieved impressive PCD ($\sim 4.55 \text{ mA.cm}^{-2}$) at 1.23 V vs RHE. Along with the formation of type-II heterojunction with WO_3 ,

Based on the above study, best-performing photoanodes (Er:W):BiVO₄, (Yb,W):BiVO₄ and (Y,W):BiVO₄ was selected for improving their charge transfer kinetics between film and FTO by forming type-II heterojunction (minimizing the formation of any recombination sites) with WO₃. In the FTO/WO₃/BiVO₄ heterojunction arrangement, the WO₃ interface layer act as an electron acceptor and participates in electron transportation to the charge collector FTO side. On the other hand, BiVO₄ layer act as a hole acceptor and participates in transferring holes from bulk to the film surface.

For WO₃ film formation, 3 mM ammonium tungstate (Sigma-Aldrich, CAS#10031513) was dissolved in 2M HNO₃ (Sigma-Aldrich, CAS#7803556). The precursor solution was sprayed over the FTO substrate (at 50 °C) using an ultrasonic spray coating tool. The film was annealed at 500 °C for 2 h to obtain thin adherent WO₃ film. To prepare WO₃/(Yb,W):BiVO₄ (composition WO₃/Bi_{0.96}Yb_{0.04}V_{0.992}W_{0.013}O₄), WO₃/(Er,W):BiVO₄ (composition WO₃/Bi_{0.93}Er_{0.03}V_{0.992}W_{0.013}O₄) and WO₃/(Y,W):BiVO₄ thin films (composition WO₃/Bi_{0.96}Y_{0.04}V_{0.992}W_{0.013}O₄) respective W:BiVO₄, (Er,W):BiVO₄ and (Y,W):BiVO₄ layer coated over WO₃. The fabrication process is shown in Figure 32.

p-n junction formation

p-n junction was formed with Fe:NiO (p-type) to further enhance the charge separation and transfer. Fe doped Ni(OH)₂ precipitate was prepared by the method reported in the literature¹⁴². The Fe doped Ni(OH)₂ precipitate (0.01 gm) was dispersed in 10 ml of DI water, and this solution was sprayed over WO₃/(Y,W):BiVO₄ film to deposit ~ 6µg of Fe doped Ni(OH)₂. The catalyst coated film was annealed for 2 h at 300 °C to obtain a thin layer of Fe:NiO over WO₃/(Y,W):BiVO₄, WO₃/(Er,W):BiVO₄ film. For cobalt phosphate

(Co-Pi) was deposited using 0.1 M K_2HPO_4 (Sigma-Aldrich, CAS#7758114) and 0.5 mM $\text{Co}(\text{NO}_3)_2 \cdot 6\text{H}_2\text{O}$ (Sigma-Aldrich, CAS#10026229) in DI water by applying 0.75 V vs SCE for 30 seconds to obtain final configuration of $\text{WO}_3/(\text{Er,W})\text{:BiVO}_4/\text{Fe:NiO}/\text{Co-Pi}$ and $\text{WO}_3/(\text{Y,W})\text{:BiVO}_4/\text{Fe:NiO}/\text{Co-Pi}$. Figure 32 illustrate the detailed film formation process of $\text{WO}_3/(\text{Y,W})\text{:BiVO}_4/\text{Fe:NiO}$ photoanode.

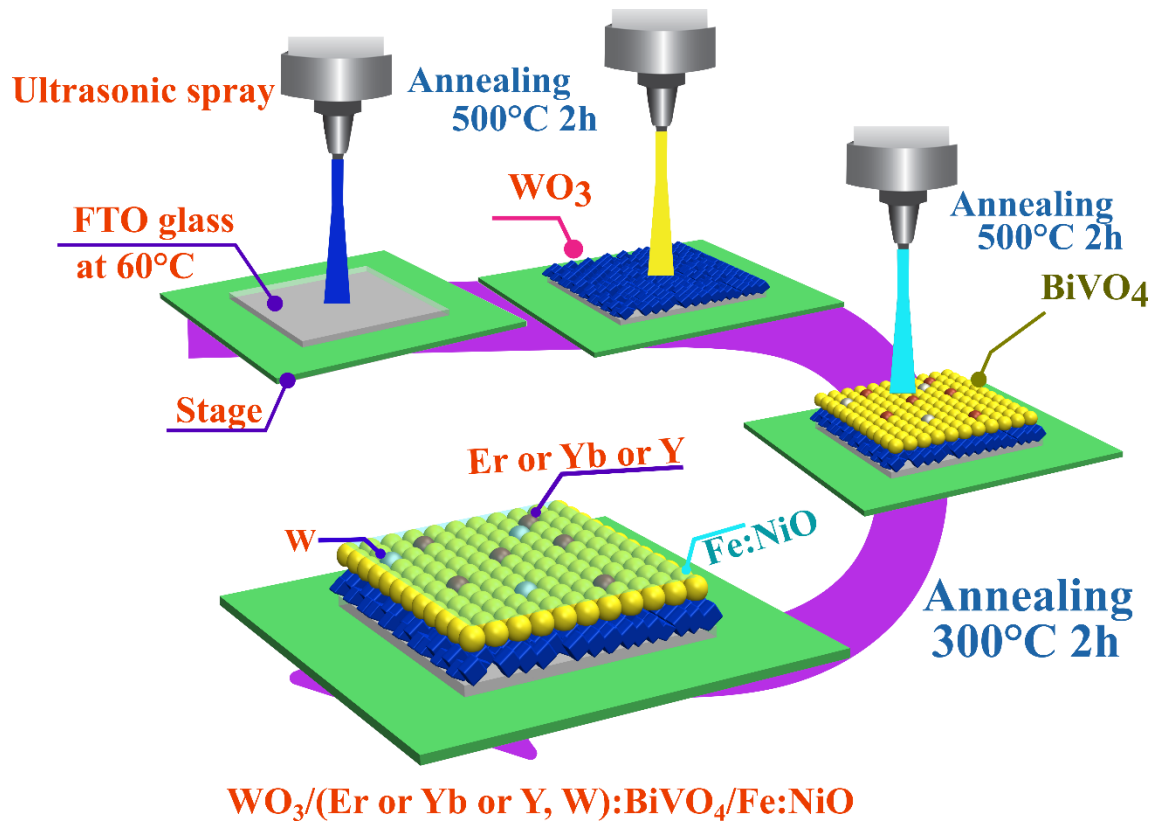


Figure 32 film fabrication process of $\text{WO}_3/(\text{Y,W})\text{:BiVO}_4/\text{Fe:NiO}$ photoanodes

4.6 photocurrent density measurements

It is evident from Figure 33 that the $\text{WO}_3/\text{Yb}:\text{BiVO}_4$, $\text{WO}_3/(\text{Er,W})\text{:BiVO}_4$ and $\text{WO}_3/(\text{Y,W})\text{:BiVO}_4$ photoanodes showed a noticeable enhancement in water oxidation with maximum PCD 2.48 ± 0.12 , 4.12 ± 0.22 and $4.32 \pm 0.22 \text{ mA}\cdot\text{cm}^{-2}$ at 1.23V vs RHE

exceeding the performance in comparison to their counter parts (Yb,W):BiVO₄, (Er,W):BiVO₄ and (Y,W):BiVO₄ photoanodes. This concludes that (Y,W):BiVO₄ and (Er,W):BiVO₄ have shown better water splitting performance compared to W:BiVO₄ after type-II heterojunction formation with WO₃ and the increment in PCD for (Er,W):BiVO₄ and (Y,W):BiVO₄ photoanode is much more pronounced at higher bias potential. The additional enhancement in the PCD performance of WO₃/(Y,W):BiVO₄ and WO₃/(Y,W):BiVO₄ photoanode is due to effectively utilizing individual properties of Er, Y and W in the co-doped sample.

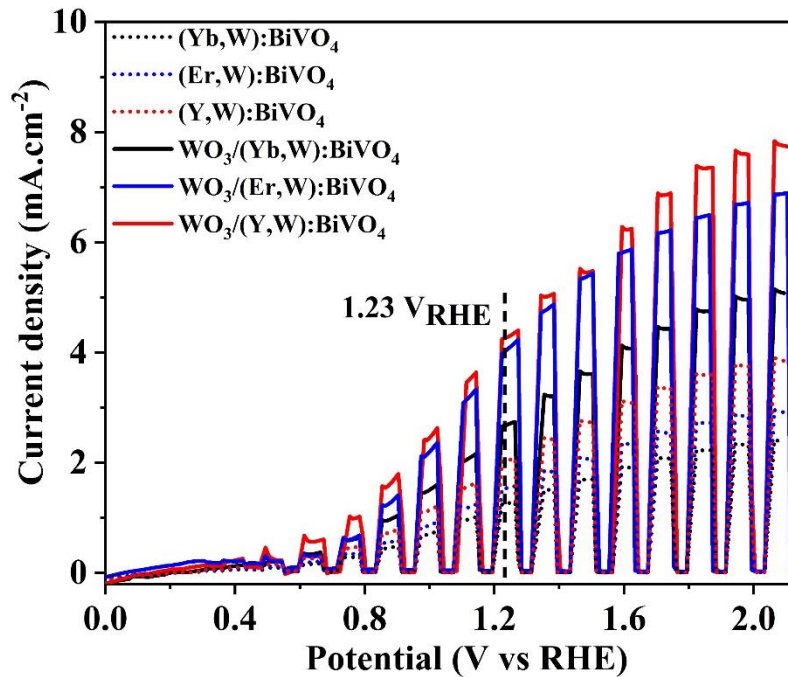


Figure 33 Linear sweep voltammetry for of heterojunction samples under 1 sun illuminations in K₂HPO₄ electrolyte.

It is evident from Figure 34 that the two best performing photoanodes $\text{WO}_3/\text{Y}:\text{BiVO}_4$ and $\text{WO}_3/(\text{Er},\text{W}):\text{BiVO}_4$ selected to study the p-n junction. It can be seen that $\text{WO}_3/(\text{Y},\text{W}):\text{BiVO}_4/\text{Fe}:\text{NiO}$ showed a noticeable enhancement in water oxidation with maximum PCD 5.2 ± 0.15 and $5.6 \pm 0.25 \text{ mA}\cdot\text{cm}^{-2}$ at 1.23V vs RHE exceeding the performance in comparison to their counter parts $\text{WO}_3/(\text{Y},\text{W}):\text{BiVO}_4$ and $\text{WO}_3/(\text{Er},\text{W}):\text{BiVO}_4$ photoanodes. Fe:NiO form p-n junction with the semiconducting BiVO_4 modifies bulk properties of the BiVO_4 film^{143,144}. Fe:NiO (p-type semiconductor) with a light-absorbing range of 350 to 550 nm with an indirect band gap of 2.35 eV, forms p-n junction with BiVO_4 ¹⁴³. Due to the p-n junction formed between the interface of $\text{WO}_3/(\text{Y},\text{W}):\text{BiVO}_4$ and $\text{WO}_3/(\text{Er},\text{W}):\text{BiVO}_4$ and Fe-NiO, an inner electric field is built, enhancing the surface reaction kinetics (transportation of electron-hole pairs), lowering the band bending conditions, and increasing the bulk charge separation. This leads to a reduction in bulk resistance and capacitance values¹⁴⁵.

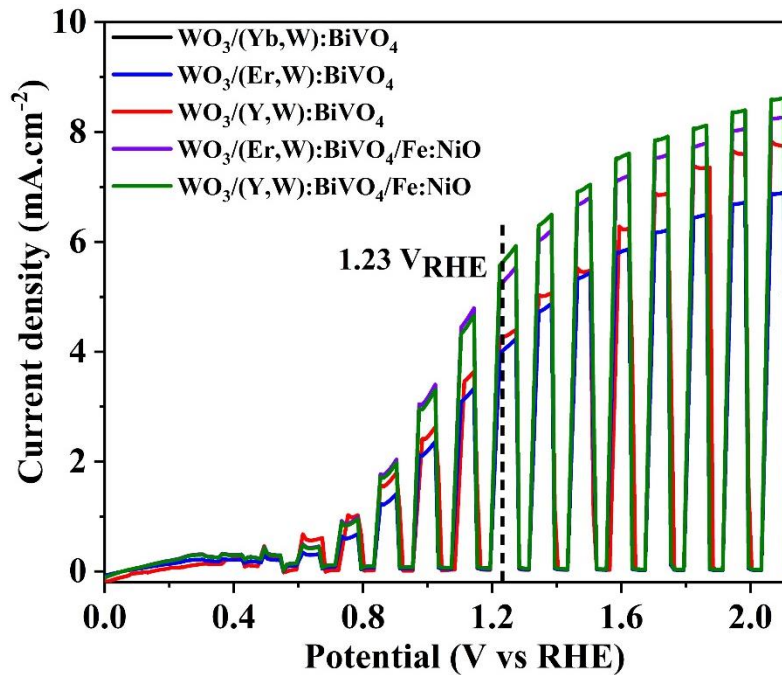


Figure 34 Linear sweep voltammetry for of heterojunction and p-n junction samples under 1 sun illuminations in K_2HPO_4 electrolyte.

4.7 Incident photon-to-current conversion efficiencies (IPCE) and absorbed photon-to-current conversion efficiency (APCE)

To quantify the total photon absorption concerning wavelength that undergoes to the photoactivity, the incident photon-to-current conversion efficiencies (IPCE) of the photoelectrode are measured at 1.23 V vs RHE (Figure 4a). The IPCE of pristine $BiVO_4$ photoanode demonstrates photoactivity from $\lambda \leq 510$. However, after co-doping with Er^{3+} , Y^{3+} , W^{6+} , the IPCE absorption range extended to $\lambda \leq 550$. The $WO_3/(Yb,W):BiVO_4$, $WO_3/(Er,W):BiVO_4$ and $WO_3/(Y,W):BiVO_4$ photoanodes showed maximum IPCE value 45 ± 2.15 , 63 ± 2.5 and 73 ± 3 %, respectively. Whereas $WO_3/(Er,W):BiVO_4$ and $WO_3/(Y,W):BiVO_4$ photoanodes with OER catalyst showed remarkably high IPCE (73 and ~98 %). Along with IPCE, integrated photocurrents were calculated (Figure 4a) to validate the obtained current from LSV in Figure 35a for all photoanodes. The integrated photocurrent for various photoanodes showed PCD closed to the respective experimental PCD. The evaluated absorbed photon-to-current conversion efficiency (APCE) (Figure 35b) illustrates the photons absorbed at the film surface, participating in the water-splitting process. The $WO_3/(Y,W):BiVO_4/Fe:NiO$ photoanode showed the highest APCE value (~95 % at 420 nm) along with $WO_3/(Er,W):BiVO_4/Fe:NiO$ (82 ± 3.5 %). The APCE results confirmed that photoanode with heterojunction (Er,W) & (Y,W) and p-n junction could effectively utilize the absorbed light towards the PEC water splitting process.

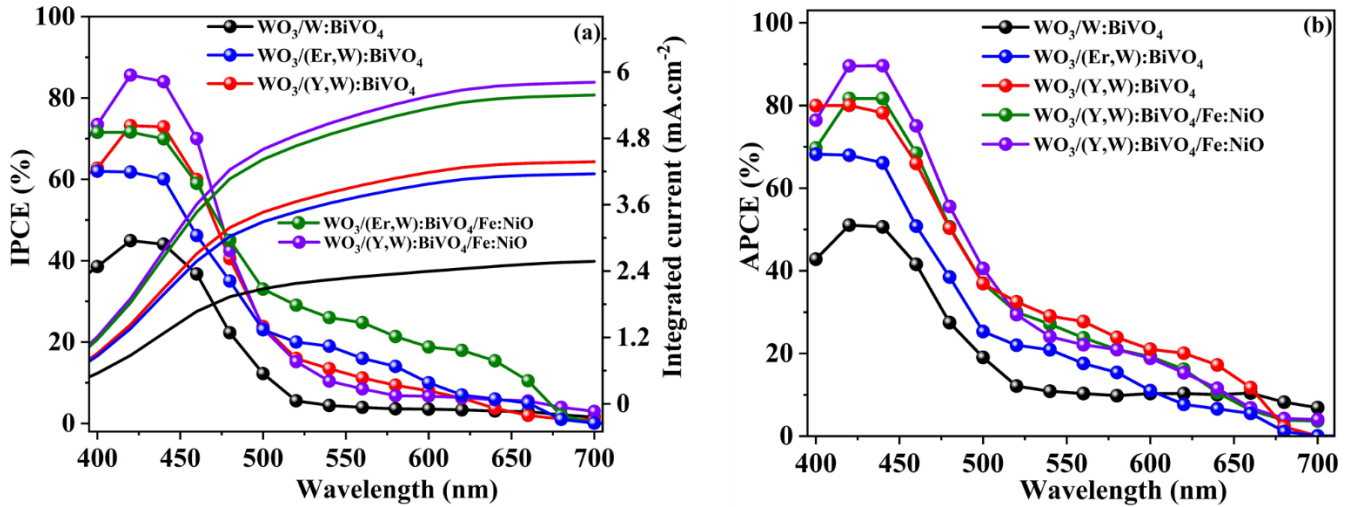


Figure 35 (a) Incident photon-to-current efficiency (IPCE), (b) absorbed photon-to-current efficiency (APCE) of for $\text{WO}_3/\text{W}:\text{BiVO}_4$, $\text{WO}_3/(\text{Er},\text{W}):\text{BiVO}_4$, $\text{WO}_3/(\text{Y},\text{W}):\text{BiVO}_4$, $\text{WO}_3/(\text{Er},\text{W}):\text{BiVO}_4/\text{Fe}:\text{NiO}$, $\text{WO}_3/(\text{Y},\text{W}):\text{BiVO}_4/\text{Fe}:\text{NiO}$ photoanodes at 1.23 V vs RHE in 0.1 M K_2HPO_4 electrolyte.

4.8 Band energy diagram for $\text{WO}_3/(\text{Y},\text{W}):\text{BiVO}_4/\text{Fe}:\text{NiO}/\text{Co-Pi}$

Effective charge transfer through WO_3 and $(\text{Y},\text{W}):\text{BiVO}_4$ heterojunction was crucial for higher PEC performance. Electrons and holes transfer process is illustrated in energy diagram Figure 36. On back-side illumination of photoanode, the first WO_3 layer absorbed mostly high energy photons $\lambda \leq 440$ nm and $(\text{Y},\text{W}):\text{BiVO}_4$ layer absorbed photons $\lambda \leq 550$ nm. Due to relative energy band configuration, photogenerated holes at WO_3 will transport and be collected at $(\text{Y},\text{W}):\text{BiVO}_4$ and simultaneously photogenerated electrons will move to WO_3 and then charge collector (FTO layer). This process will separate electrons and holes more efficiently. In addition, there will be systematic band bending at the interface of WO_3 and $(\text{Y},\text{W}):\text{BiVO}_4$ layers. The band bending plays a crucial role in charge

separation i.e. higher band bending can lead to better charge separation. The band bending phenomenon in our experiment was confirmed by the negative shift observed in the onset potential. Due to the band bending, there will be barrier formation ($35.34 \pm 1.8 \sim 60 \pm 0.3$ mV) between (Y,W):BiVO₄ and WO₃ layers. The electrons with average thermal energy ($\sim k_B T$) can easily overcome this barrier during PEC water oxidation process⁵⁸. In order to confirm the improved charge transport due to band bending, open circuit potential (ΔOCP) was measured for all photoanodes⁵⁸. It is reported that under 1 sun illumination, sufficiently high charge carriers are generated and lead to flattening the energy bands. A similar band bending explanation can be given for WO₃/(Er,W):BiVO₄/Fe:NiO/Co-Pi. The flattening of the energy band is mostly affected by built-in potential and recombination of charge carriers. The ΔOCP values gradually increase. Since the built-in potential is the same for all photoanodes, the increase in ΔOCP indicate lesser charge recombination in the film. The WO₃/(Y,W):BiVO₄/Fe:NiO/Co-Pi photoanode showed the highest drop in the potential that relate to the lowest charge recombination. Space charge width (SCL) or depletion layer was calculated to confirm the conclusion drawn from ΔOCP measurement. It was observed that for the WO₃/(Y,W):BiVO₄, WO₃/(Er,W):BiVO₄/Fe:NiO/Co-Pi and WO₃/(Y,W):BiVO₄/Fe:NiO/Co-Pi photoanodes, the SCL got widen with increasing anodic bias potential which illustrate that maximum minority carriers i.e. holes are transported to the reactive interface for water splitting process.

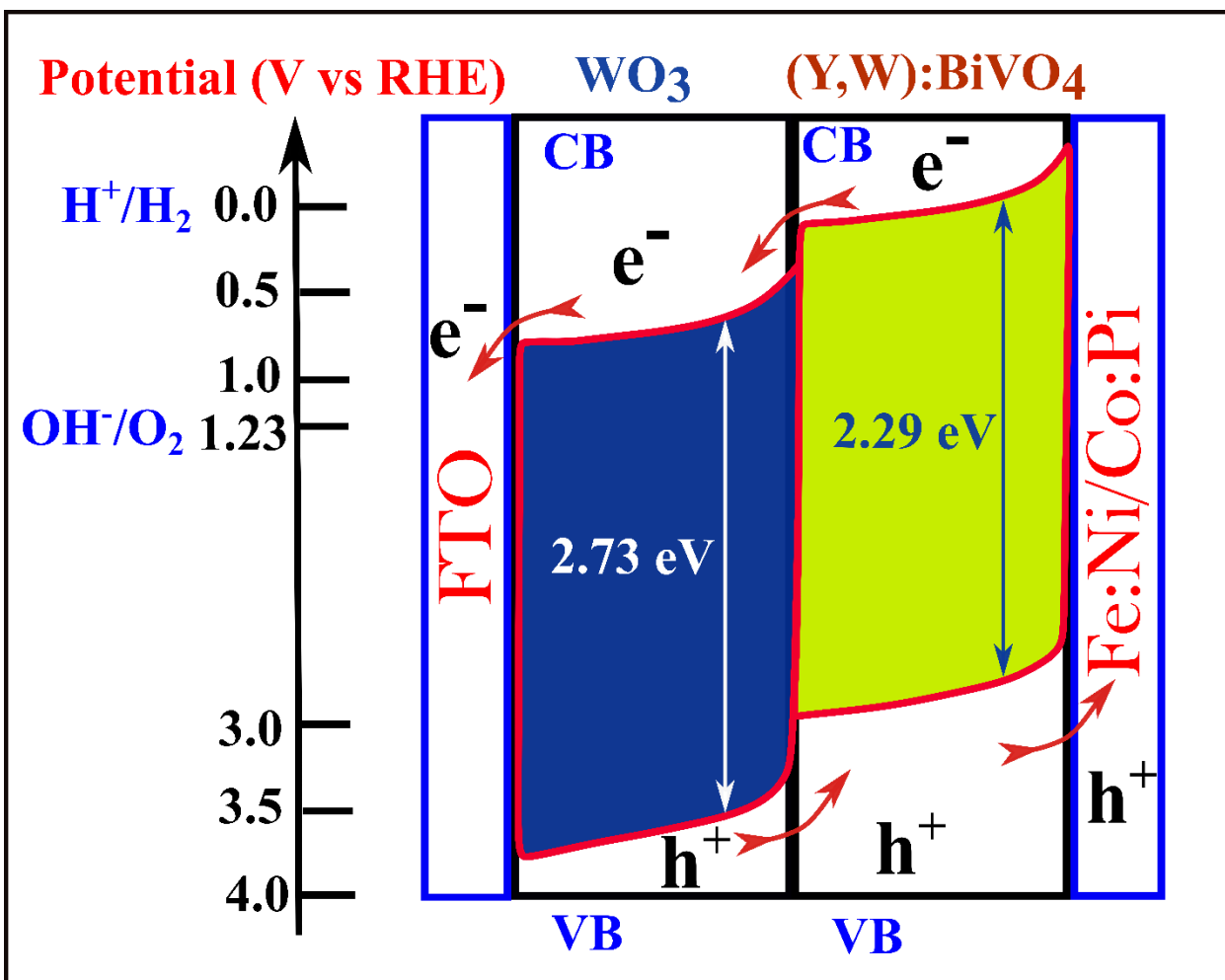


Figure 36 Figure 5. Energy diagram illustrating electron transfer in (a) $WO_3/(Y,W):BiVO_4/Fe:NiO/Co-Pi$.

4.9 Cyclic stability measurements

The cyclic stability measurement (Figure 37) of the $WO_3/(Y,W):BiVO_4/Fe:NiO$ photoanode was conducted for water oxidation at 1.23 V vs RHE by keeping light ON 11 h and OFF for 2 h. It was observed that $WO_3/(Y,W):BiVO_4/Fe:NiO/Co-Pi$ photoanode can retain ~95 % of the PCD even after 33 hrs of operation. In present $WO_3/(Y,W):BiVO_4/Fe:NiO/Co-Pi$ photoanode, the Fe:NiO and Co-Pi catalyst layer

combined effect were used to prevent the photo corrosion. The Fe:NiO and Co-Pi OER catalysts over the electrode is supposed to reverse catalyst dissolution in phosphate buffers through a self-repair process¹⁴⁶ and improve the rate of interfacial charge transfer. Moreover, in the present study, the stability test was carried out in cyclic mode (11 h each cycle), and after each cycle, a fresh electrolyte was used. Using new electrolyte in each cycle provide fresh Ni/Co metal to participate in the self-repair process¹⁴⁷. This could be the possible reason for the stability of the photoanode even after 33 h of cyclic operation.

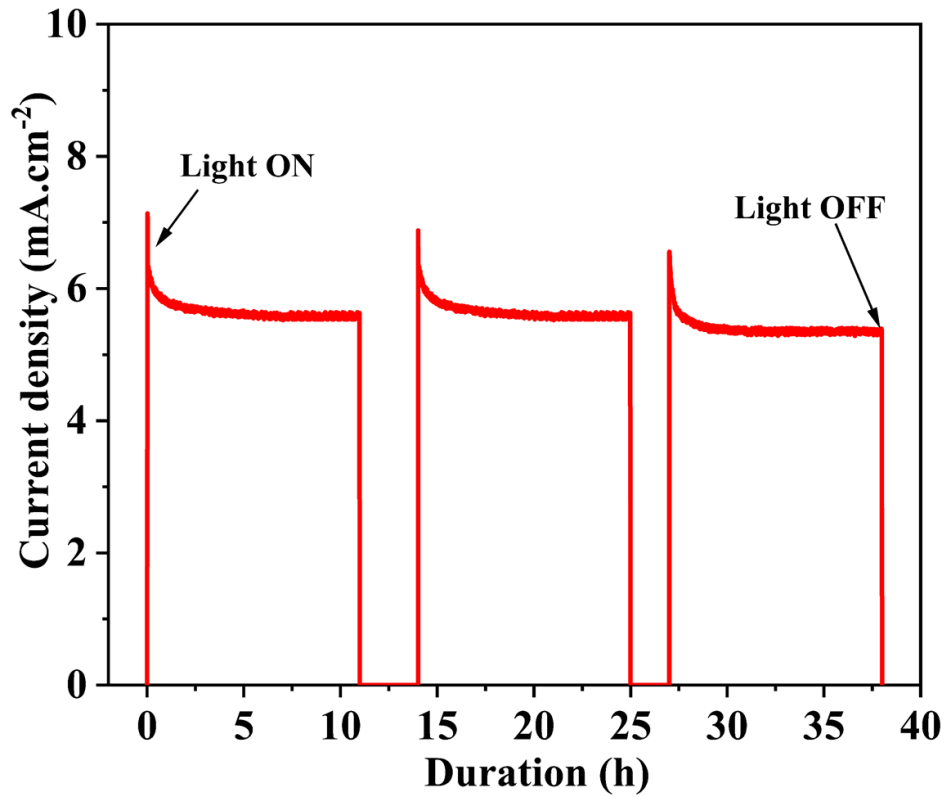


Figure 37 cyclic stability measurement for $\text{WO}_3/(\text{Y,W})\text{:BiVO}_4/\text{Fe:NiO/Co-Pi}$ photoanode.

4.10 Conclusion

The role of individual element doping W, Er, Y, Yb and co-doping (Y,W), (Er,W) and Yb,W) in BiVO₄ with respect to their light absorption, bulk, surface charge separation and transfer properties has been studied in detail. The doping of the rare earth metal ions Y³⁺ Er³⁺ or Yb³⁺ at Bi³⁺ site enhances light absorption ($\lambda \leq 550$) due to reduction in bandgap but leads to decreased charge transport property compared to W⁶⁺ doped at V⁵⁺ site photoanode. The detailed investigation of absorption efficiency, photogenerated charge dissipation, transfer and electrochemical impedance showed that even though there is high charge separation in bulk on W doping, the defect is generated especially at the surface with Y³⁺ or Er³⁺ or Yb³⁺ doping at Bi³⁺ site act as a recombination center. By introducing the WO₃ heterojunction for efficient electron transfer between film and FTO interface, the (Y,W):BiVO₄ photoanode showed better performance than W:BiVO₄ photoanode. The WO₃/(Y,W):BiVO₄/Fe:NiO photoanode with type two heterojunction and p-n junction demonstrated near-complete (~95 %) suppression of electrons and holes recombination, efficient charge transfer (~75 %) and improved absorption efficiency (~85 %). Due to the p-n junction formed between the interface of WO₃/(Y,W):BiVO₄ and WO₃/(Er,W):BiVO₄ and Fe-NiO, an inner electric field is built, enhancing the surface reaction kinetics (transportation of electron-hole pairs), lowering the band bending conditions, and increasing the bulk charge separation. The WO₃/(Y,W):BiVO₄/Fe:NiO photoanode showed a PCD of 5.77 ± 0.3 mA.cm⁻² at 1.23 V and 7.4 ± 0.45 mA.cm⁻² at 2.0 V (vs RHE) in K₂HPO₄ electrolyte. The electrode has shown remarkably high incident and absorbed photon to current conversion efficiency (~97 %). Thus, rare earth metal Y or Er or Yb

doping in BiVO₄ enhances light absorption but leads to decreased bulk and surface charge transport property, and this limitation can be overcome by using a suitable electron/hole transfer layer.

CHAPTER 5 DEVELOPMENT OF SULFUR MODIFIED Bi₂O₃ INTERFACIAL LAYER

5.1 Introduction

OER properties of BiVO₄ suffer from low charge transfer rates due to excessive surface recombination in the *ps-ns* time scale.^{94,148} In parallel, the desirable water oxidation occurs at a slower time scale, typically over the *ms-s* range, due to its four-electron reaction mechanism.^{149,7,9} Fast charge separation and transport of photogenerated electron-hole pairs are essential for efficient water oxidation.^{8,10} Several strategies have been employed to enhance the charge separation and transfer, such as composition tuning or doping,^{84,85} formation of homo- and hetero- junctions,^{5,11,12} passivation layer¹⁵² and co-catalyst.¹⁵³

Tungsten (W) and molybdenum (Mo) have been extensively studied as donor-type dopants in BiVO₄ to increase charge carrier density and mobility and minimize recombination pathways at solid/solid /solid/ solid/electrolyte interfaces.^{36,151} Along with composition tuning, forming heterojunction, in particular, type-II heterojunction formation between WO₃ (bandgap: 2.7 eV, VB: 0.4 eV & CB: 3.1 eV) and BiVO₄ (VB: 0.02 eV & CB: 2.4 eV) is efficient due to appropriate band alignment, which promotes spatial charge separation and relatively better charge transfer by providing substantial thermodynamic driving force and interfacial electric field.^{6,16}

5.2 Drawbacks of WO₃/BiVO₄ heterojunction

As shown from Figure 38, the WO₃/BiVO₄ heterojunction suffers from (1) slow charge transfer (sub μs) from BiVO₄ to WO₃ due to poor transport properties BiVO₄ and simultaneous photoexcited leading to a shorter lifetime of the electron.¹⁵⁵ The interface between The interface of WO₃/BiVO₄ contain (2) recombination center and trap sites that causes additional recombination at the heterojunction interface.^{8,17} Consequently, (3) new recombination channel activates where electrons from the conduction band recombine with trapped holes in the valence band of BiVO₄.¹⁵⁵

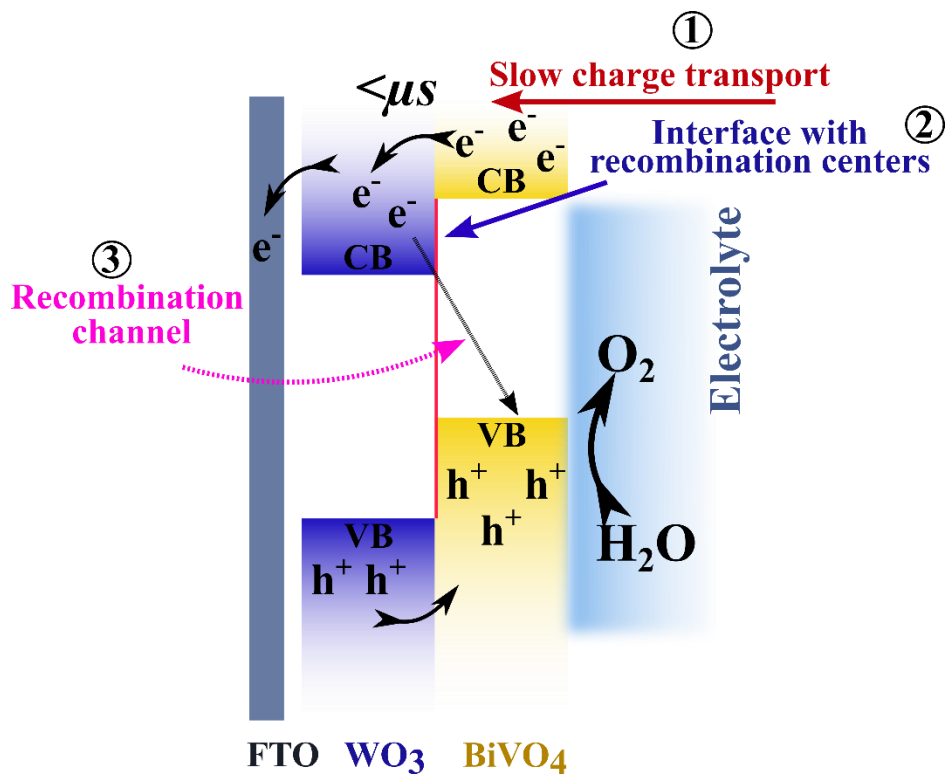


Figure 38 Major drawbacks of $\text{WO}_3/\text{BiVO}_4$ heterojunction.

5.3 The proposed solution to resolve the limitation of $\text{WO}_3/\text{BiVO}_4$ heterojunction

Our or other groups in the field have made several efforts to improve interfacial passivation, charge transfer, and reducing recombination sites by additional (interfacial or under/over) layers in $\text{WO}_3/\text{BiVO}_4$ heterojunction photoanodes. The obtained photocurrent densities at 1.23 V_{RHE} are plotted in Figure 9a. and Table S5. Choi et al.¹⁵⁷ incorporated a mild W doped BiVO_4 interfacial layer in the $\text{WO}_3/\text{BiVO}_4$ heterojunction for unidirectional charge flow. Zhang et al.¹⁵⁸ designed a three-story device to improve the conductivity by placing reduced graphene oxide between WO_3 and BiVO_4 layers that acted as a multichannel pathway. A Z-scheme device was designed by Wang et al.¹⁵⁹ by incorporating a W-layer between BiVO_4 and WO_3 layers for accessing holes. Beak et al.¹⁶⁰ used porous

SnO₂ underlayer in the WO₃/BiVO₄ heterojunction where WO₃/(WO₃+SnO₂) layers formed a mixed composite for better contact and low resistance. Figure 9b and Table S6 compare hydrogen production rates at 1.23 V_{RHE} under simulated AM 1.5G illumination for BiVO₄ based heterojunction photoanodes along with the present results on our WO₃/S:Bi₂O₃/(Ga,W):BiVO₄/Co-Pi photoanode. Our results are among the highest reported photocurrent densities and hydrogen production rates.

In order to overcome the mentioned challenges, an interfacial layer (Bi₂O₃) was placed synergistically between the WO₃/BiVO₄ heterojunction, as detected in Figure 39. Additionally, Bi₂O₃ has a staggered structure. This layer was supposed to facilitate (1) enhance the charge transfer rate after simultaneous photoexcited, leading to longer lifetime and rapid electron and hole transfer (> sub μs) of the electron. Simultaneous, (2) Bi₂O₃ provide a much better crystal match between WO₃/Bi₂O₃ and Bi₂O₃/BiVO₄ and rapid charge transfer rate leading to minimize interfacial recombination. Consequently, (3) interfacial layer (Bi₂O₃) acts as an electron blocking layer, reducing interfacial recombination and deactivating or minimizing the new recombination channels.

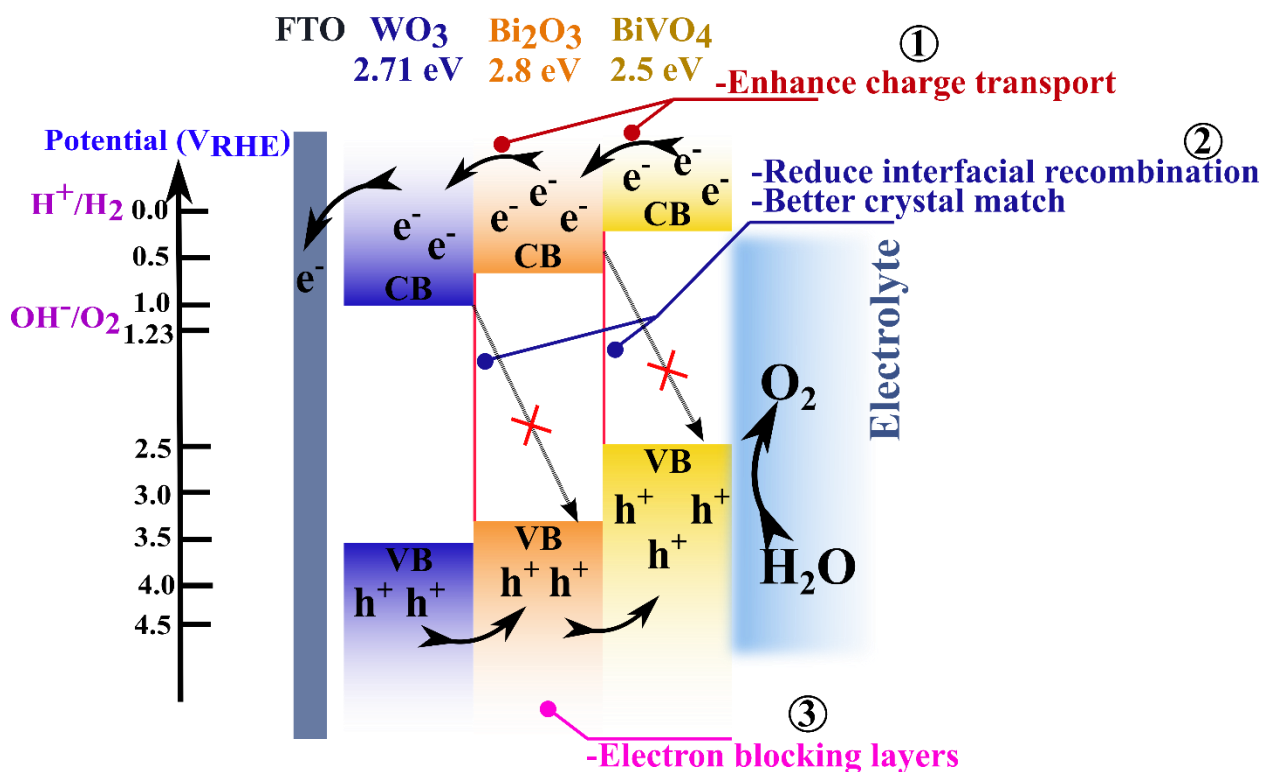


Figure 39 Proposed solution to resolve the limitation of WO₃/BiVO₄ heterojunction.

In the present study, a multifaceted approach was implemented for addressing the interfacial charge recombination in WO₃/BiVO₄ heterojunction where (i) BiVO₄ was co-doped and (ii) an interfacial layer was implemented to improve the effective charge separation and transfer. Initially, BiVO₄ was co-doped with Ga³⁺ and W⁶⁺ at the Bi³⁺ and V⁵⁺ sites, respectively, to enhance light absorption, the concentration of photogenerated charge carriers, and improve bulk charge separation. A uniquely prepared sulfur (S) modified Bi₂O₃ (S:Bi₂O₃) layer was implemented so that S diffused to adjacent underlayer (WO₃) and overlayer ((Ga,W):BiVO₄), which helped in increasing additional reactive sites for charge transport. Energy-dispersive X-ray analysis (EDAX), X-ray photoelectron spectroscopy (XPS) and time-of-flight secondary ion mass spectrometry (TOF-SIMS)

depth profiling determined the qualitative and uniform distribution of sulfur in all layers. The PCD increased from 2.8 ± 0.12 to 4.0 ± 0.2 mA.cm⁻² for WO₃/(Ga,W):BiVO₄ and WO₃/S:Bi₂O₃/(Ga,W):BiVO₄, respectively. Additionally, the photocurrent improved to 5.1 ± 0.25 mA.cm⁻² after adding cobalt phosphate (Co-Pi) to yield a hydrogen collection rate of 67.3 μmol.h⁻¹cm⁻² for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄/Co-Pi photoanode at 1.23 V_{RHE} in K₂HPO₄ (KPi) under simulated AM 1.5G illumination. Time-resolved photoluminescence (TRPL) and in *operando* femto- and nano-second transient absorption spectroscopy (fs- and ns- TA) results are consistent with more holes rapidly directed to the reactive surface initially and fast electron transfer from (Ga,W):BiVO₄ to S:Bi₂O₃ in *ps-ns* and from S:Bi₂O₃ to WO₃ in *ns-μs* time scale. From the detailed analysis, we show that the insertion of a S:Bi₂O₃ interfacial layer resulted in the best charge separation and transfer kinetics, as well as reduced interfacial recombination sites of all architectures tested. The achieved results are among the highest reported photocurrent densities and hydrogen production rates in the literature.

5.4 Experimental

The BiVO₄ based thin films were fabricated on 1×1 cm² fluorine-doped tin oxide (FTO) glass substrate (Aldrich Chemistry: 2.3 mm thick, ~7 Ω/sq surface resistivity) using ultrasonic spray coating (Sono-Tek Corporation, USA). A precursor solution of BiVO₄ was prepared by dissolving 3mM Bi(NO₃)₃·5H₂O (Alfa-Aesar, CAS#10035060) and 3mM NH₄VO₃ (Sigma-Aldrich, CAS#7803556) in 2M HNO₃ (Sigma-Aldrich, CAS#7803556). The precursor solution was sprayed at a 0.1 ml/min flow rate for 4 cycles over a FTO substrate held at 70°C, then annealed for 10 min at 500°C in the furnace (Thermo Scientific

Thermolyne, model: F48028). The annealed film was sprayed with an additional 4 cycles for optimized film thickness and then annealed at 500°C for 2 h. Ga doping was performed by dissolving 3mM $\text{Ga}(\text{NO}_3)_3 \cdot x\text{H}_2\text{O}$ (Sigma-Aldrich, CAS#69365726) in the BiVO_4 precursor solution to get varied $\text{Bi}_{1-x}\text{Ga}_x\text{VO}_4$ compositions (where $x = 0.01 - 0.06$ and $x = 0.04$ was found to be optimal) (Figure S1a). W doping was carried out non-stoichiometrically³⁶ by mixing 3mM $(\text{NH}_4)_{10}\text{H}_2(\text{W}_2\text{O}_7)_6$ (Sigma-Aldrich, CAS#11140775) in the BiVO_4 precursor solution to acquire $\text{BiV}_{0.992}\text{W}_{0.013}\text{O}_4$ (termed W: BiVO_4). The simultaneous co-doping of Ga and W in BiVO_4 was executed by taking the required amount of gallium nitrate and ammonium tungstate in BiVO_4 precursor solution to obtain $\text{Bi}_{0.96}\text{Ga}_{0.04}\text{V}_{0.992}\text{W}_{0.013}\text{O}_4$ (termed (Ga,W): BiVO_4).

WO_3 films were fabricated by dissolving 3mM $(\text{NH}_4)_{10}\text{H}_2(\text{W}_2\text{O}_7)_6$ (Sigma-Aldrich, CAS#10031513) in 2M HNO_3 (Sigma-Aldrich, CAS#7803556). Using an ultrasonic spray coating tool, the precursor solution was sprayed for 4 cycles over FTO substrate (kept at 40°C) with a 0.1 ml/min flow rate. Next, the film was annealed at 500°C for 2 h in the air to obtain a thin adherent WO_3 film. (Ga,W): BiVO_4 was then sprayed over the WO_3 film to form $\text{WO}_3/(\text{Ga,W}): \text{BiVO}_4$.

The precursor solution for Bi_2O_3 was prepared by dissolving 1mM $\text{Bi}(\text{NO}_3)_3 \cdot 5\text{H}_2\text{O}$ (Alfa-Aesar, CAS#10035060) in 10 ml acetic acid (Sigma-Aldrich, CAS#64197). $\text{WO}_3/\text{Bi}_2\text{O}_3$ film was fabricated by ultrasonically spraying Bi_2O_3 precursor on WO_3 film (kept at 70°C) for 3 cycles. The $\text{WO}_3/\text{Bi}_2\text{O}_3$ bilayer was then annealed at 500°C for 2 h in air. (Ga,W): BiVO_4 was subsequently sprayed (as discussed) to form $\text{WO}_3/\text{Bi}_2\text{O}_3/(\text{Ga,W}): \text{BiVO}_4$.

Figure 40 show a schematic of the $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga},\text{W}):\text{BiVO}_4/\text{Co-Pi}$ film fabrication process. First, the sprayed Bi_2O_3 film was immersed in 35 ml methanol (Sigma-Aldrich, CAS#67561) and 0.4mM dibenzyl disulfide (Alfa Aser, CAS#150607) for 20 min and then annealed in sulfur vapor using a tube furnace (Thermo Scientific Thermolyne, model: HTF55322C). Next, sulfur vapor was generated by heating 2.5 g of sulfur powder (Alfa Aser, CAS#7704349) at 120°C in the tube furnace's upstream section. Argon (purity: 99.99%) was used as a carrier gas the sulfur vapor downstream where the thin film was placed in the hot zone of the tubular furnace at 445°C in air for 1 h to incorporate S in the Bi_2O_3 (termed $\text{S}:\text{Bi}_2\text{O}_3$). In the final step, the sulfur-rich film with WO_3 layer was used as a substrate to spray $(\text{Ga},\text{W}):\text{BiVO}_4$ precursor solution and annealed in air at 500°C for 2 h to obtain $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga},\text{W}):\text{BiVO}_4$ film.

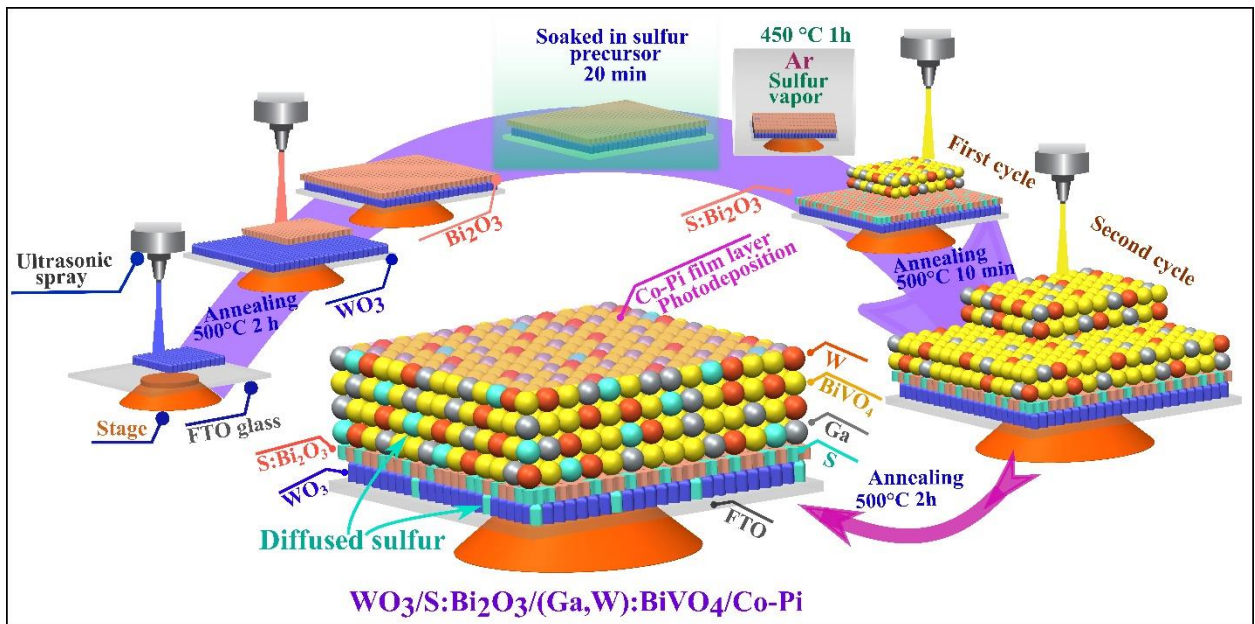


Figure 40 Schematic illustration of the $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga},\text{W}):\text{BiVO}_4/\text{Co-Pi}$ film fabrication process.

A co-catalyst Co-Pi was photo-electrodeposited by dissolving 0.1M K_2HPO_4 (Sigma-Aldrich, CAS#7758114) and 0.5mM $Co(NO_3)_2 \cdot 6H_2O$ (Sigma-Aldrich, CAS#10026229) in DI water at 0.71 $V_{Ag/AgCl}$ for 30 s under simulated AM 1.5G illumination to obtain $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4/Co-Pi$.

5.5 Photoelectrochemical and optical measurements

Looking first at films, Figure 41a compare the PEC performance of intrinsic $BiVO_4$ (i- $BiVO_4$), $Ga:BiVO_4$, $W:BiVO_4$ and $(Ga,W):BiVO_4$ under chopped light up to 2.4 V_{RHE} . $Ga:BiVO_4$ exhibited $0.4 \pm 0.02 \text{ mA.cm}^{-2}$, almost twice that of the i- $BiVO_4$ ($0.25 \pm 0.01 \text{ mA.cm}^{-2}$); this improvement is attributed to increased Fermi-level splitting and therefore decreased carrier recombination, via incorporation of Ga^{3+} at Bi^{3+} sites.¹⁶¹ Similarly, $W:BiVO_4$ exhibited enhanced PCD ($1.02 \pm 0.04 \text{ mA.cm}^{-2}$) of over four times that of i- $BiVO_4$, which is attributed to increased carrier concentration from W^{6+} donors at V^{5+} sites.¹⁶² Finally, $(Ga,W):BiVO_4$ demonstrated superior (~ 7 times) PEC performance ($1.68 \pm 0.1 \text{ mA.cm}^{-2}$) compared to i- $BiVO_4$, likely due to the combined effects of Ga and W doping.

Next, PEC performance of heterojunctions was evaluated (Figures 41b). Figure 41a, $(Ga,W):BiVO_4$ was selected to form a type-II heterojunction with WO_3 . By doing so, $WO_3/(Ga,W):BiVO_4$ photoanode showed $2.8 \pm 0.12 \text{ mA.cm}^{-2}$ photocurrent, nearly doubled compared to $(Ga,W):BiVO_4$, likely due to improved light absorption at $\lambda \leq 450 \text{ nm}$, charge transfer kinetics and reduced recombination sites.^{163,164} However, the $WO_3/BiVO_4$

interface has a high defect density, which can lead to significant recombination and slow charge transport.^{148,156} Therefore, a thin layer of bismuth oxide (Bi_2O_3) was inserted at the $\text{WO}_3/\text{BiVO}_4$ interface. While Bi_2O_3 has appropriate band alignment to promote charge transfer, the PEC was not significantly enhanced relative to $\text{WO}_3/(\text{Ga,W})\text{:BiVO}_4$ (only 1.2 times higher), likely due to the higher levels of recombination in this layer.¹⁶⁵ Therefore, sulfur (S) was incorporated into the Bi_2O_3 such that, along with passivating the Bi_2O_3 bulk, S also diffused into the adjacent WO_3 and $(\text{Ga,W})\text{:BiVO}_4$ layers (Figure 41b). Sulfur is expected to enhance water oxidation by generating oxygen vacancies and forming new reaction sites that help charge migration/separation and reduce carrier recombination.^{125,261} The optimized $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$ photoanode demonstrated an excellent photocurrent of $4.0 \pm 0.2 \text{ mA}\cdot\text{cm}^{-2}$ at $1.23 \text{ V}_{\text{RHE}}$ which was ~ 1.2 and ~ 1.5 times higher than the $\text{WO}_3/\text{Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$ and $\text{WO}_3/(\text{Ga,W})\text{:BiVO}_4$ photoanodes, respectively. A surface catalyst (Co-Pi) deposited $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4/\text{Co-Pi}$ photoanode exhibited a remarkably high photocurrent $5.1 \pm 0.25 \text{ mA}\cdot\text{cm}^{-2}$ at $1.23 \text{ V}_{\text{RHE}}$ in KPi. The Co-Pi layer facilitates hole collection at the photoanode/electrolyte interface to participate in the water oxidation reaction.⁸⁵

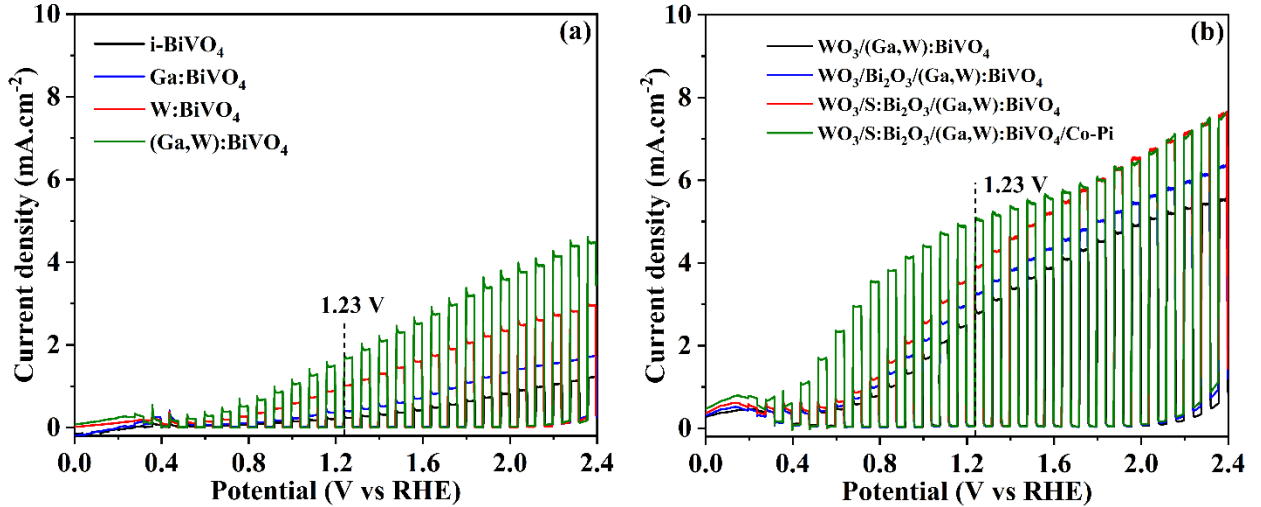


Figure 41 J–V plots under simulated AM 1.5G illumination in KPi for photoanodes (a) Ga, W doped and (Ga,W) co-doped along with i-BiVO₄, (b) with WO₃ heterojunction and Bi₂O₃ interface layer without and with sulfur modification.

The spectral response was investigated to understand the impact of doping, co-doping and heterojunction formation. From Figure 42, it was observed that doping BiVO₄ with Ga enhanced total light absorption and extended the onset from ~520 to ~535 nm. A similar trend was observed for the co-doped (Ga,W):BiVO₄ sample, likely due to the redshift in light absorption caused by Ga doping.¹⁶¹ There was no substantial change in absorption observed for W doping.⁸⁴ Moreover, the light interaction improved by forming a heterojunction with WO₃ (i.e., WO₃/(Ga,W):BiVO₄) where WO₃ ($\lambda \leq 450$ nm) absorbs high energy photons along with modified BiVO₄ (300 – 530 nm), which absorb a wide range of photons. S:Bi₂O₃ ($\lambda \leq 430$) further improved the light interaction for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ compared to WO₃/Bi₂O₃/(Ga,W):BiVO₄ due to the formation of interband on S modification which causes the redshift in the light absorption.^{165,166} The respective absorption efficiency (ϕ_{abs}) was calculated by integrating the absorption spectra from 300 to 550 nm for all samples and indicated in Figure 42a and

42a: inset. The measured bandgaps were 2.71 and 2.8 eV for WO_3 and Bi_2O_3 , respectively. There was a slight (~ 0.04 eV) reduction in the optical bandgap for $\text{Ga}:\text{BiVO}_4$ (2.39 eV) and $(\text{Ga,W}):\text{BiVO}_4$ (2.38 eV) compared to i-BiVO_4 (2.42 eV), which was expected due to the redshift in the absorption edge on Ga doping.

The IPCE determined the quantification of absorbed photons undergoing photoactivity corresponding to wavelength. The measurement for all heterojunction based photoanodes was conducted at $1.23 V_{\text{RHE}}$ (Figure 3b). $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ photoanode showed maximum IPCE value $63\pm 3\%$ followed by $\text{WO}_3/\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ ($52\pm 2\%$) and $\text{WO}_3/(\text{Ga,W}):\text{BiVO}_4$ ($42\pm 1.6\%$), respectively at 460 nm. The $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ photoanode with Co-Pi exhibited the highest IPCE ($72\pm 3.2\%$). The IPCE was integrated over the AM1.5G reference spectrum, and the resulting photocurrent densities for each sample (Figure 42b) agreed with those measured under simulated AM 1.5G illumination at $1.23 V_{\text{RHE}}$ (Figure 41b). Due to measuring uncertainty, the small variation ($\sim 5\%$) in the photocurrents measured by LSV and integrated current from IPCE is a general phenomenon.

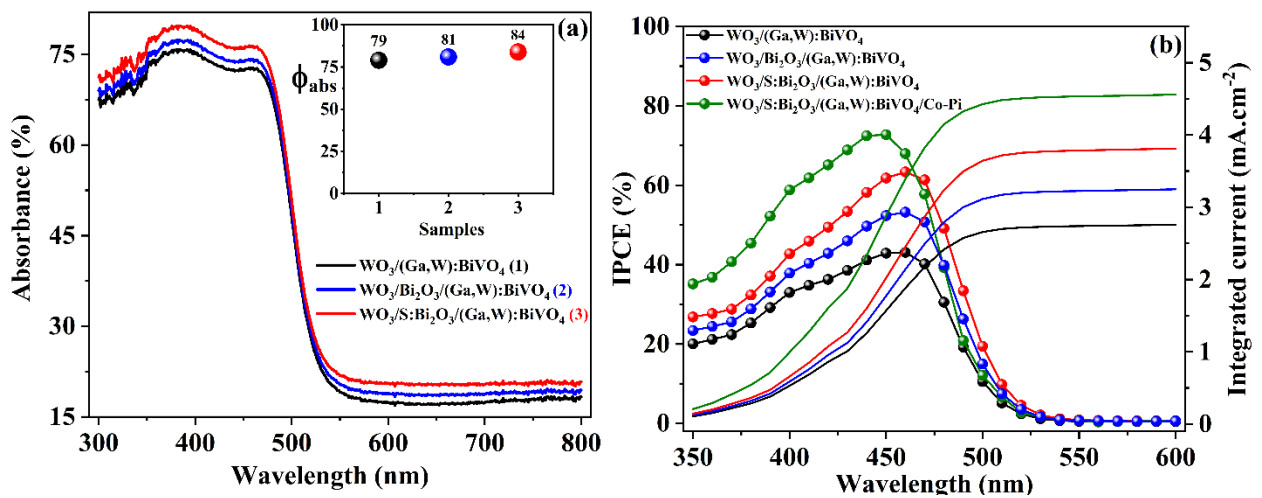


Figure 42 (a) Absorption spectra (inset: absorption efficiency), (b) incident photon-to-current efficiency, measured at 1.23 V_{RHE} in KPi electrolyte for photoanodes with WO₃ heterojunction and Bi₂O₃ interface layer without and with sulfur modification.

5.6 Surface morphology, crystal structure and elemental analysis of thin films

To better understand the PEC performance trends, the physicochemical characterization of intrinsic and doped samples was carried out to evaluate morphology, elemental mapping, crystal structure and oxidation state. The SEM images reveal that i-BiVO₄, WO₃ and Bi₂O₃ have a planar structure with uniform nanoporous morphology. Figure 43a shows that after co-doping the i-BiVO₄ film with Ga and W, the overall porosity increased substantially without changing the grain size (50 – 200 nm). The inset image illustrates the consistent growth of nano-size grains, leading to better light absorption and more electrochemical active surface area by increasing the contact area between film surface and electrolyte. The cross-section image (Figure 43b) for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ demonstrated the uniformly connected nanoporous grains. The layers thicknesses are 200-300, 200-300 and 500-750 nm for the WO₃, S:Bi₂O₃ and (Ga,W):BiVO₄ layers, respectively. It was observed that clear separation of all three layers is difficult as layers amalgamated due to the porous nature of all films. The FTO coating thickness on the glass substrate was ~50 nm. The composition and elemental distribution of as-deposited WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ were mapped based on the integrated intensities of peak Bi, V, O, W, Ga and S signals as a function of beam position using FESEM-EDAX mode. Figure 43c-h reveals the uniform distribution of elements Bi, V, O, W, Ga, and S. Consequently, the element spectra in Figure 4i demonstrates the uniform presence of S along with other elements. In Figure 43i inset, Bi and S peaks were deconvoluted to determine the distinct measure of S due to the

near overlap of the two peaks. S and Bi peaks were determined at 2.36 and 2.45 keV, respectively. Additionally, the quantification of S was determined to be 2.77 at% from EDAX analysis (Figure 4i: inset).

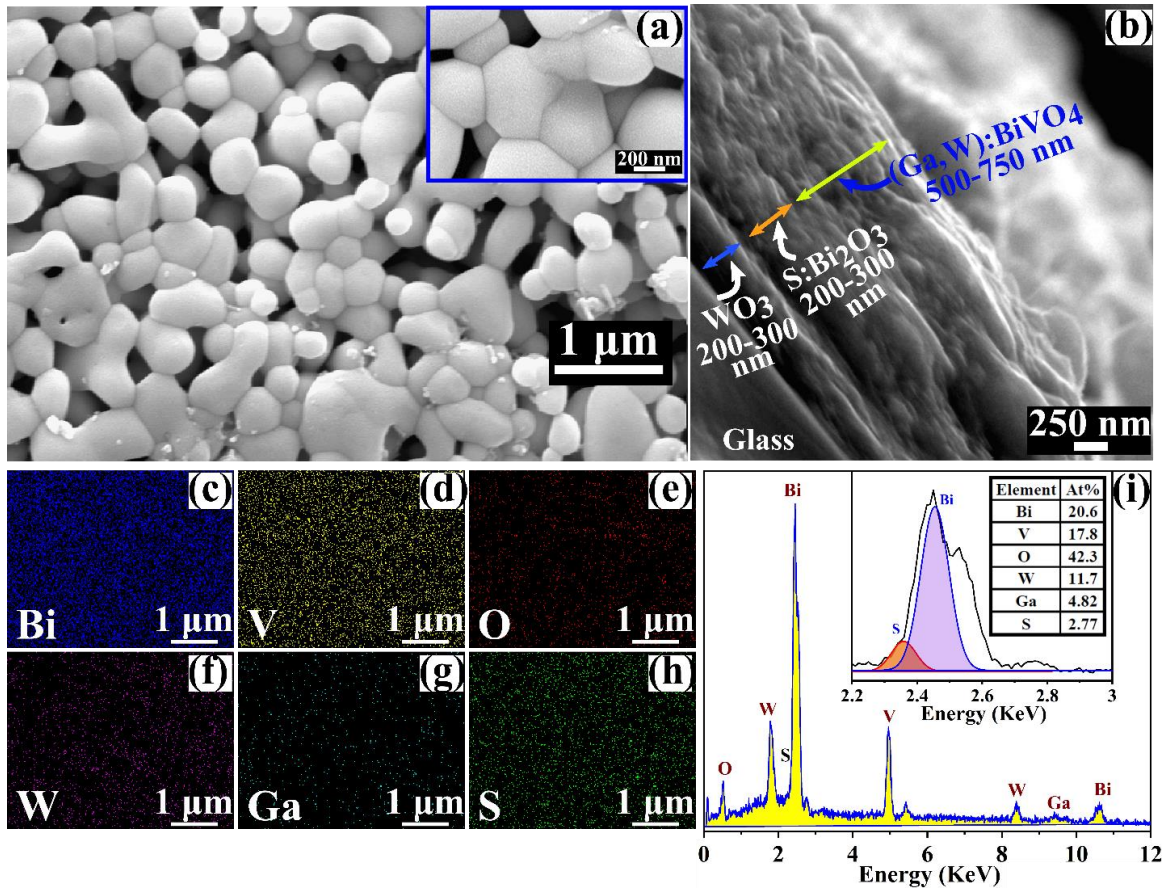


Figure 43 (a) Surface morphology. (b) Cross-section, (c-h) plan view elemental mapping and (i) elemental spectra (inset: deconvolution of Bi and S peaks and at%) of $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga},\text{W}):\text{BiVO}_4$ sample.

The crystal structure was determined using X-ray diffraction (XRD) analysis for intrinsic, doped BiVO_4 , Bi_2O_3 , WO_3 and heterojunction samples without any impurity, complex phases and S peaks.¹⁵⁵ The oxidation state of Bi, V, W, Ga and O in $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga},\text{W}):\text{BiVO}_4$ sample was determined using surface XPS. However,

subsequently employed XPS depth profiling could not identify S in any layers due to the low concentration of S and detection limit of XPS. In order to determine the oxidation states of sulfur, two distinct samples were prepared (Figure 44a): an intermediate S treated $\text{WO}_3/\text{Bi}_2\text{O}_3$ and $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ with high S content (total S treatment to $\text{WO}_3/\text{Bi}_2\text{O}_3$ layer was 4 hrs, 4 times than actual sample). From the S 2s spectrum in Figure 44b, the oxidation state of S was attributed to -2 in the form of Bi_2S_3 (224.8 eV) and Bi_2O_3 (230.6 and 233.8 eV) peaks for S treated $\text{WO}_3/\text{Bi}_2\text{O}_3$ sample.¹⁰⁹ Similarly, $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ sample with high S content validated -2 states (Bi_2S_3 (223.4 eV) and Bi_2O_3 (233.3 eV)). However, it is possible that peaks at 233.8 eV and 233.3 eV could also have sulfates or highly oxidized sulfur species (SO_x).¹⁰⁹ Additionally, depth profiling was performed in Figure 44c for $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ with high S content sample to determine the atomic concentration of Bi 4f, V 2p, O 1s, W 4f, Ga 2p and S 2s with depth. It was observed that the S distribution was uniform throughout the film depth except slightly higher at the film surface. The atomic concentration of S was approximately 12 at% uniformly distributed in the sample with high S content. It may be estimated that sulfur could be approximately 3 at% uniformly distributed in the actual sample considering S diffusion rates as sulfur treatment was 4 times in high S content sample. The atomic concentration of Bi 4f, V 2p, O 1s, W 4f and Ga 2p was distributed as per the filmstack structure. The V 2p and Ga 2p was noticed to have minor diffusion in the adjacent layers, which was possible due to the porous nature of the film.

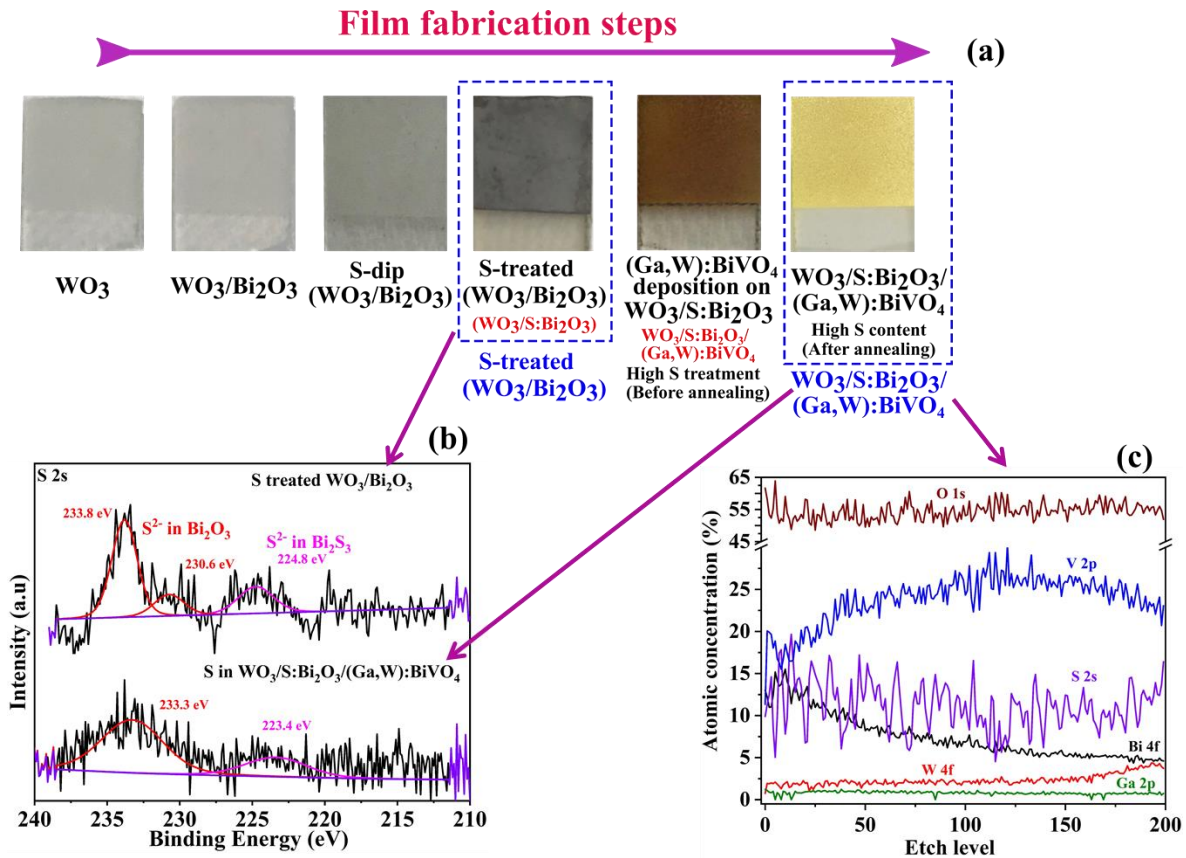


Figure 44 (a) Prepared sample for the XPS surface and depth profiling. (b) S 2s XPS spectra of S treated WO_3/Bi_2O_3 and with high S concentrated $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4$ film. (c) XPS depth profiling spectra for atomic concentration (%) of Bi 4f, V 2p, O 1s, W 4f, Ga 2p and S 2s as a function of etch level for $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4$ film with high S content.

In order to understand the nature of the sulfur diffusion process in the actual film from Bi_2O_3 interfacial layer to the WO_3 and $(Ga,W):BiVO_4$ adjacent layers, TOF-SIMS depth profiling was employed for the $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4$ sample in three distinct annealing conditions after $(Ga,W):BiVO_4$ precursor deposition on sulfur treated WO_3/Bi_2O_3 film. The prepared samples, as shown in Figure 45a, were control (without annealing), short annealing (5 min) and complete annealing (final sample). Secondary ion signals were selected, which were of high intensity and represented major components of

the various layers in the filmstack. These species were: Bi^- , VO^- , WO_2^- , GaO^- and S^- to represent Bi, V, W, Ga and S elements, respectively. The layers interface was not measured due to high surface roughness, and it was also observed that clear distinction of each layer was difficult (Figure 43b and 43a) due to their porous nature. The control sample showed that sulfur was contained to the Bi_2O_3 layer only, as observed by the pronounced sulfur peak in the Bi_2O_3 layer in Figure 45b. Contrarily, Figure 45c demonstrated that even on short annealing of 5 min at 500°C , significant migration of sulfur has occurred as the sulfur distribution migrated significantly into the $(\text{Ga,W})\text{:BiVO}_4$ and WO_3 layers, also noted by the significant broadening of the sulfur trace. Subsequently, in Figure 45d, a completely annealed sample (2 h time at 500°C) showed that the sulfur distribution was uniform throughout the film thickness, which was also corroborated by EDAX analysis (Figure 43c-i) and XPS depth profiling (Figure 44b). However, the sulfur content was higher on the $(\text{Ga,W})\text{:BiVO}_4$ surface, possibly due to the small deposition of sulfur during migration from Bi_2O_3 layer similar behavior was observed from XPS depth profiling (Figure 44c). It was assumed that sulfur was passivated in all grain boundaries and surfaces/interfaces/defects throughout all layers, rather than being a bulk alloy element. Along with sulfur, a less extreme amount of diffusion was observed for the components Bi, V, W and Ga in the film thickness (Figure 45b-d) may be due to the highly porous nature of the film (Figure 43a) similar behavior was observed from XPS depth profiling. The distribution of the substrate elements (F^- , Sn^- and Si^-) was also observed.

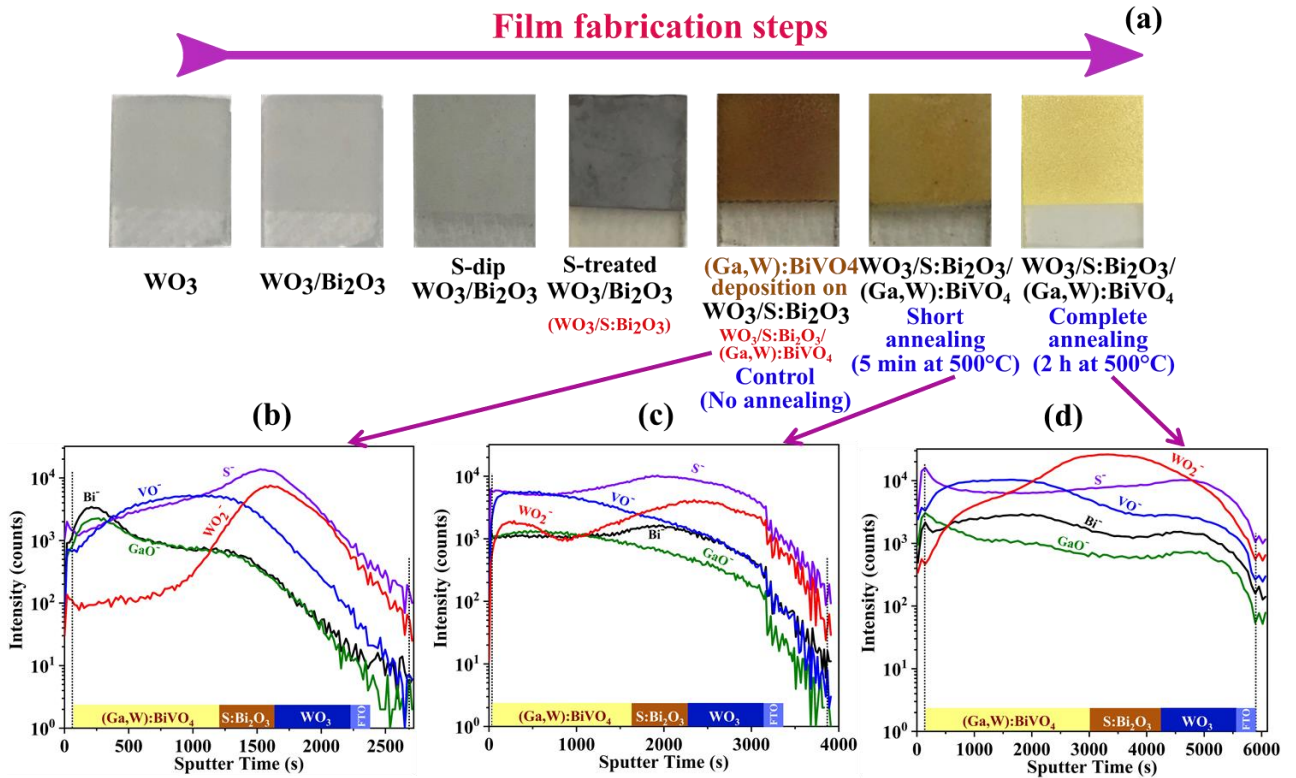


Figure 45 (a) Prepared sample for TOF-SIMS in three distinct environments control (no annealing), short annealing (5 min at $500^\circ C$) and complete annealing (2h at $500^\circ C$). Negative polarity TOF-SIMS depth profiles of $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4$ sample for three distinct environments (a) control (no annealing), (b) short annealing (5 min at $500^\circ C$) and (c) complete annealing (2h at $500^\circ C$) for Bi^- , VO^- , WO_2^- , GaO^- and S^- species.

5.7 Electrochemical impedance analysis

Figure 46a shows the impedance patterns of photoanodes with WO_3 heterojunction and Bi_2O_3 interface layer without and with sulfur modification. $WO_3/(Ga,W):BiVO_4$ photoanode shows lower impedance than $WO_3/Bi_2O_3/(Ga,W):BiVO_4$ at the low-frequency region. Interestingly, $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4$ photoanode demonstrated even lower real impedance at a lower frequency than $WO_3/Bi_2O_3/(Ga,W):BiVO_4$. Resistance and capacitance in bulk and at the surface were evaluated as a function of voltage using Randles

circuits (Figure 46b & 46c), which consists of resistance related to connections (R_{series}), bulk resistance (R_{bulk}), surface resistance ($R_{surface}$), bulk capacitance (C_{bulk}) and surface capacitance ($C_{surface}$) connected to a Helmholtz layer at the photoanode and electrolyte interface.

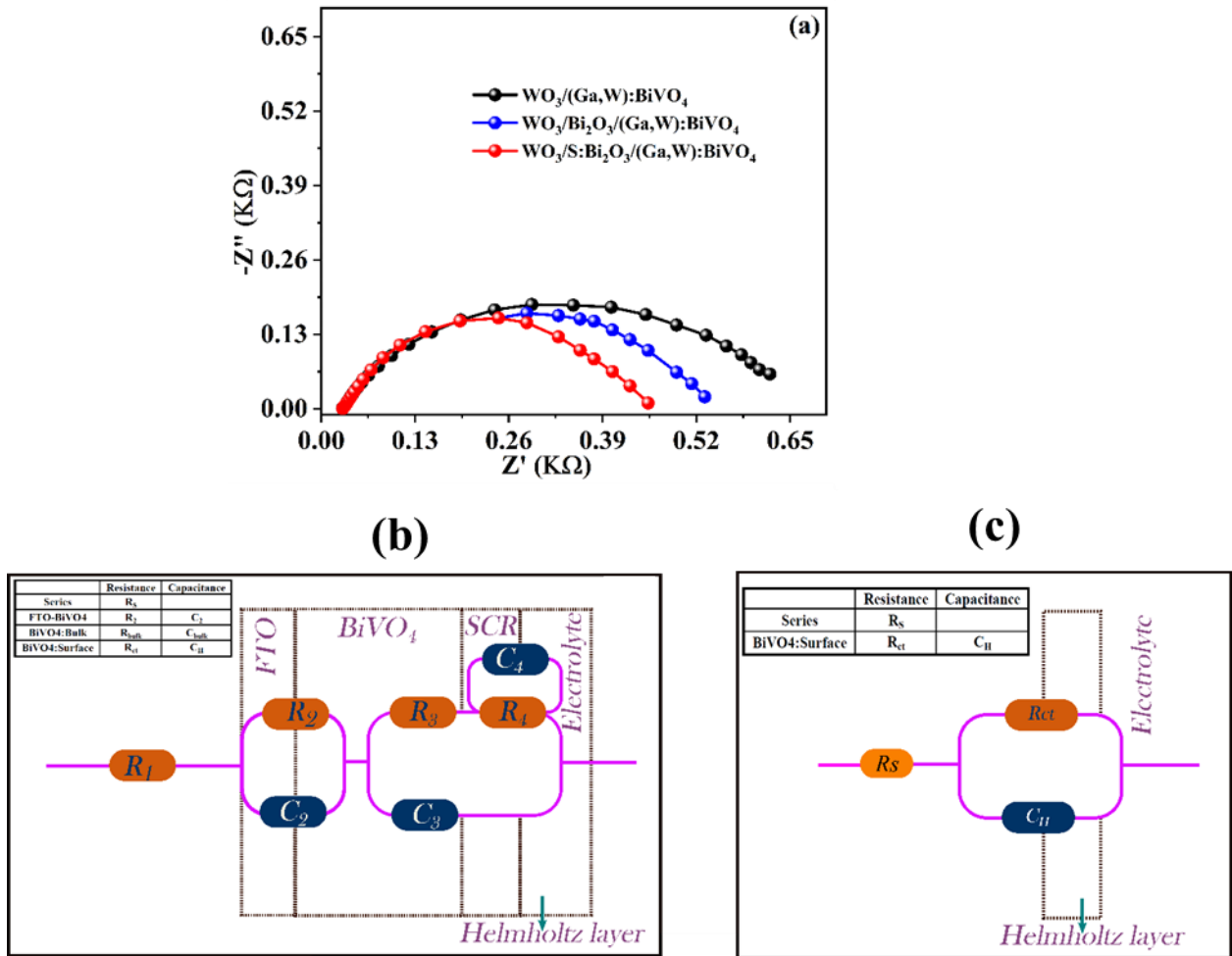


Figure 46 (a) Nyquist plots measured in KPI at 1.23 VRHE under simulated AM 1.5G illumination. (c) and (d) Randles circuit for calculating $R_{surface}$, R_{bulk} , $C_{surface}$ and C_{bulk} .

Figure 47a shows that R_{bulk} and $R_{surface}$ tend to drop gradually until ~ 1 V_{RHE} after which, the photocurrent was mainly controlled by photogenerated holes reaching the surface.¹⁶⁸ R_{bulk} followed the order of $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4 < WO_3/Bi_2O_3/(Ga,W):BiVO_4 <$

WO₃/(Ga,W):BiVO₄. The evaluated capacitance of photoanodes shown in Figure 47b illustrated that C_{bulk} decreases with increasing potential and exhibits less recombination in bulk and facilitated charge transfer. The $C_{surface}$ gradually increased with potential, followed the trend WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ > WO₃/Bi₂O₃/(Ga,W):BiVO₄ > WO₃/(Ga,W):BiVO₄. The interfacial layer with S enhanced the charge transfer rate, facilitated the charge accumulation and transport by reducing the density of surface trapped holes in the bulk and the surface.

Total resistance (R_{tot}), which represent the combination of charge transport (bulk) and interfacial charge transfer (surface), was evaluated using $R_{tot} = \left(\frac{dI}{dV}\right)^{-1}$ in Figure 47c. A valley was observed at ~ 1 V_{RHE} for all photoanodes. The cathodic shift of 164.3 and 33.5 mV in the valley implied higher charge extraction and a decrease in the R_{tot} of 39.2 and 12 $\Omega \cdot \text{cm}^{-2}$ for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ and WO₃/S:Bi₂O₃/(Ga,W):BiVO₄, respectively from WO₃/(Ga,W):BiVO₄) indicated the reduced bulk recombination (indicated in Figure 6b).^{168,169} Both of these criteria best fit the WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ photoanode confirms the higher charge separation and transfer rate. The close relationship was demonstrated by R_{tot} calculated from I - V ($R_{tot} = \left(\frac{dI}{dV}\right)^{-1}$) and impedance measurement ($R_{tot}=R_{bulk}+R_{surface}$) as shown in Figure 6d. This excellent agreement substantiates the photocurrent obtained from experiment.

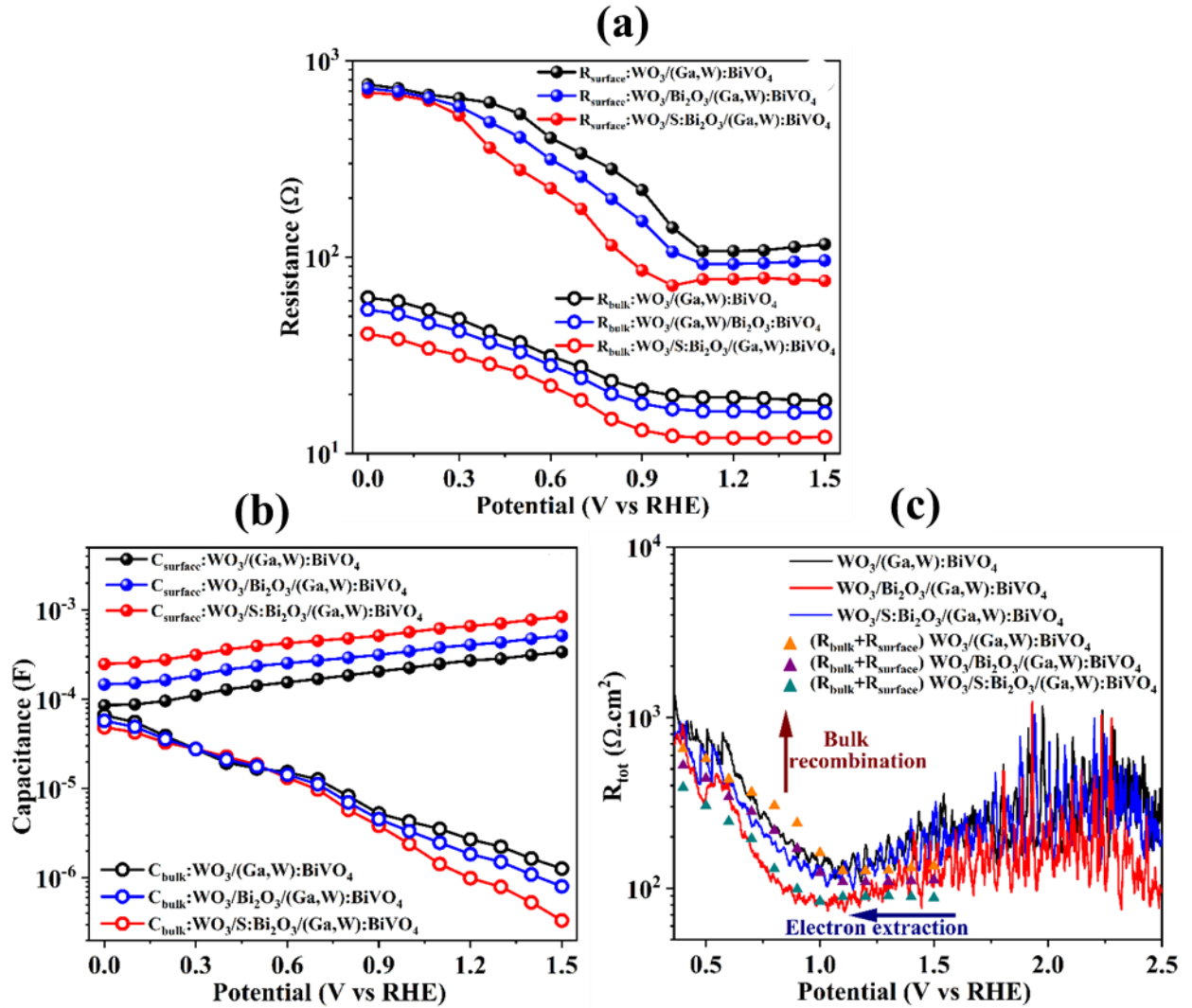


Figure 47 (a) R_{surface} (solid markers), R_{bulk} (open markers), (b) C_{surface} (solid markers) and C_{bulk} (open markers) determined using Randles circuit (Figure 46 b and c) for photoanodes with WO_3 heterojunction and Bi_2O_3 interface layer without (blue) and with (red) sulfur modification. (c) R_{tot} (line) calculated by $(\frac{dI}{dV})^{-1}$ and compared with R_{tot} (triangles) obtained by impedance ($R_{\text{tot}} = R_{\text{bulk}} + R_{\text{surface}}$) measurement.

5.8 Time-resolved study of charge dynamics

The photogenerated charge carrier dynamics and kinetics were explored by TRPL measurement of the $\text{WO}_3/(\text{Ga,W}):\text{BiVO}_4$ and $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ samples.

Figure 48 exhibits the PL intensity decay after excitation the thick (Ga,W):BiVO₄ layer and likely produces excited states in this layer by a laser source centered at 405 nm. The PL decay ($I(t)$) was fit with a second-order exponential function $I(t) = A_1 \exp\left(-\frac{t}{\tau_1}\right) + A_2 \exp\left(-\frac{t}{\tau_2}\right)$, where A_1 and A_2 are amplitudes of components with lifetime τ_1 and τ_2 , respectively.¹⁷⁰ The average PL lifetime ($\langle\tau\rangle$) of each sample was calculated using $\langle\tau\rangle = \frac{A_1\tau_1^2 + A_2\tau_2^2}{A_1\tau_1 + A_2\tau_2}$ (all calculated parameters are presented in Table 2). The average carrier lifetimes for WO₃/(Ga,W):BiVO₄ and WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ were 0.477±0.05 and 0.418±0.04 ns, respectively. Interestingly, the two dominant benefits which are expected from S:Bi₂O₃ incorporation (i.e., reduced recombination and fast charge transport) have competing effects on carrier lifetime, where reduced recombination increases lifetime while fast charge transport reduces it. This may be the reason that lifetime was not found to vary significantly between the two samples. The charge transfer rate constant (k_{ct}) can also be calculated as $k_{ct} = \frac{1}{\langle\tau\rangle}$.¹⁷⁰ The obtained k_{ct} for WO₃/(Ga,W):BiVO₄ and WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ were 2.095±0.2 ns⁻¹ and 2.393±0.22 ns⁻¹, respectively, suggesting that the enhanced charge transfer may be slightly more dominant.

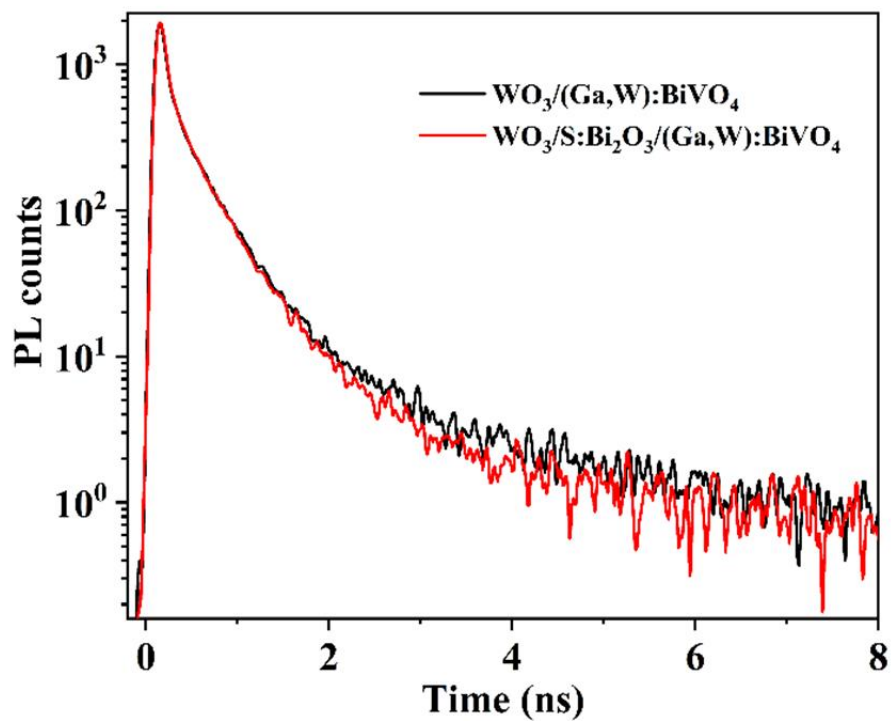


Figure 48 Time-resolved PL emission (excited at $\lambda = 405$ nm).

Table 2 Time-resolved PL analysis calculated parameters

Photoanode	A_1	τ_1 (ns)	A_2	τ_2 (ns)	$\langle \tau \rangle$ (ns)	K_{et} (ns ⁻¹)
$\text{WO}_3/(\text{Ga,W})\text{:BiVO}_4$	646.31 ± 81.42	0.34 ± 0.03	23.88 ± 8.94	1.39 ± 0.24	0.477 ± 0.05	2.095 ± 0.20
$\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$	679.97 ± 90.52	0.31 ± 0.03	37.54 ± 17.41	1.02 ± 0.18	0.418 ± 0.04	2.393 ± 0.22

TA was employed for an in-depth understanding of the charge dynamics behavior across $\text{WO}_3/(\text{Ga,W})\text{:BiVO}_4$ interface without and with the $\text{S}:\text{Bi}_2\text{O}_3$ interfacial layer by placing the sample in the air and electrolyte (*operando*). First, fs-TA data were collected for in air, pumped at 430 nm and probed in the range 900-1400 nm for $\text{WO}_3/(\text{Ga,W})\text{:BiVO}_4$ and $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$ samples. It is believed that this infrared probing range tracks

the free and trapped photogenerated carriers, while the excitation first strikes the thick (Ga,W):BiVO₄ layer and likely predominately produces excited states in this layer. The intensity decay curve plotted in Figure 49a demonstrates faster initial decay on *ps* time scale for the WO₃/(Ga,W):BiVO₄ sample compared to WO₃/S:Bi₂O₃/(Ga,W):BiVO₄. This fast decay likely corresponds to geminate electron-hole recombination, which is ameliorated with the additional Bi₂O₃ layer, facilitating electron movement away from BiVO₄ and suppressing initial recombination. The recorded decay (ΔA) signal was fitted using the exponential decay model $\Delta A = \sum_{i=1}^n A_i \exp\left(-\frac{t}{\tau_i}\right)$ Where A_i and τ_i are the amplitude and the lifetime of an exponential decay component, respectively, the calculated fitting parameters are summarized in Table 3, and the values are commensurate with those found in the literature.¹⁵⁰ The fs-TA is the best fit with 3 exponentials in the *ns* regime without an extended component in the microsecond regime due to the absence of electrolyte that stabilizes separated charges. Time constant τ_1 , τ_2 and τ_3 can be inferred as loss of excited states due to hole trapping and depletion of the trapped hole due to electron-hole recombination with free and thermalized electrons.^{150,171} It is inferred from τ_1 that the initial fast processes leading to carrier loss are reduced in the WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ sample, as all decay time constants are slower than for the WO₃/(Ga,W):BiVO₄ sample. The subsequent remaining carriers are left to undergo slower interfacial recombination on a *ns* timescale without electrolyte. We note that unlike TRPL, which only measures radiative electron-hole recombination, and thus separation leads to reduced lifetime, the absorptive TA signal represents carrier population, and as such, a persistent signal also indicates carrier motion to avoid recombination.

Next, the ns-TA measurement was conducted with samples submerged in the electrolyte to evaluate hole transfer kinetics at the semiconductor/electrolyte interface. The measurement was conducted at open circuit potential, pumped at 430 nm and probed in the range 900-1400 nm in KPi electrolyte. It was predicted that an electron trap state partially occupied at open circuit potential could exhibit optical transition behavior to a localized trap state.¹⁴⁹ The band bending at the photoanode/electrolyte interface can prolong the photogenerated holes lifetime (μs) and accumulation.¹⁴⁹ This was confirmed by measuring open circuit potential (~ 0.5 and ~ 0.55 V_{RHE}) in the dark and flat-band potential (0.092 and 0.041 V_{RHE} (SI section 4)) exhibited significant band bending for WO₃/(Ga,W):BiVO₄ and WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ photoanodes. From the fs-TA data described above, it is known that a larger number of holes survived the initial electron-hole recombination due to rapid charge separation/transport and subsequent transport to the reactive film surface for the water oxidation reaction.^{149,154} Subsequently, from the normalized ns-TA data tracking secondary decays in Figure 49b, it was observed that WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ exhibited slightly faster *ns* decay than WO₃/(Ga,W):BiVO₄ but otherwise had nearly identical kinetics. The recorded decay signal was fitted using the exponential decay model. The calculated fitting parameters are summarized in Table 4. The ns-TA best fit with 4 exponentials due to the presence of long-lived carriers. The shortest time scale (τ_1) for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ might represent carrier loss due to the initial, more rapid sweeping to the surface as facilitated by the additional layer. The electron extraction (K_{TA}) rate was higher for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ photoanode that denoted the enhanced electron mobility after placing S:Bi₂O₃ layer and impact of S diffusion to adjacent layers.

Correspondingly, the recombination between trapped holes and free electrons (τ_2) on the > 30 ns timescale was similar in $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ (36 ns) compared to $\text{WO}_3/(\text{Ga,W}):\text{BiVO}_4$ (43 ns). The recombination of the trapped hole with thermalized electrons (τ_3) was occurring in μs range (1.1 to 1.3 μs) and expected that it would not significantly impact the overall water splitting process.¹⁵⁴ By the time the μs timescale is reached, the leftover carriers surviving recombination have been swept far away from the internal interface, where the composition is distinct between the samples, to the semiconductor/electrolyte interface where composition and thus kinetics become similar. This study provides evidence that the number of long-lived photogenerated charge carriers is improved after adding interfacial layer $\text{S}:\text{Bi}_2\text{O}_3$. In addition, we conclude that $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ decays faster in the < 10 ns regime compared with $\text{WO}_3/(\text{Ga,W}):\text{BiVO}_4$, suggesting improved electron transfer rate and accumulation of holes at the $(\text{Ga,W}):\text{BiVO}_4$ surface for water oxidation kinetics.

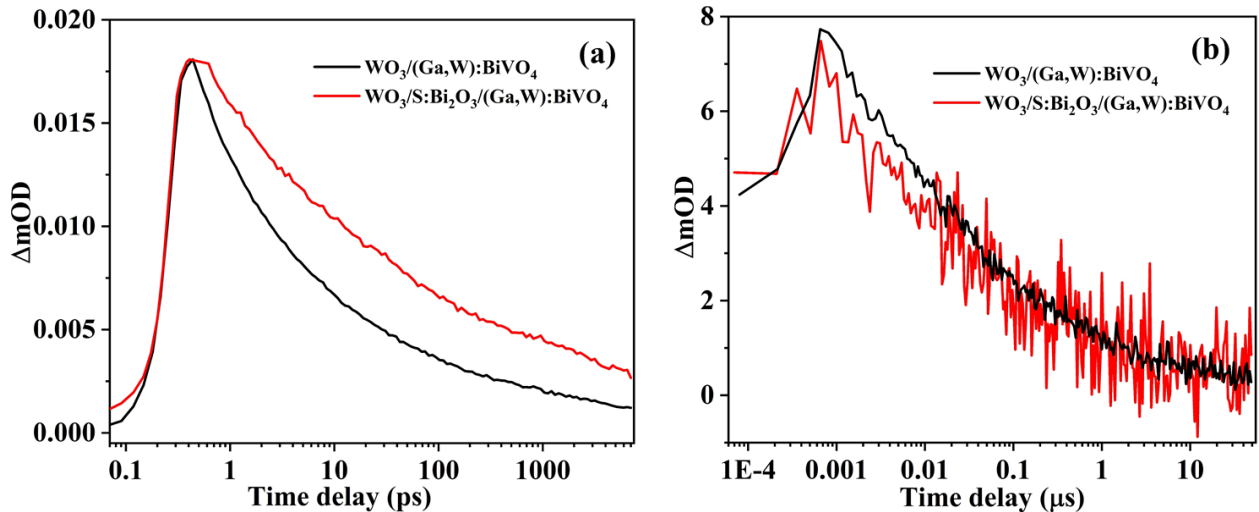


Figure 49 TA spectra collected, pumped at 430 nm probed in the range 900-1400 nm (a) in the air for fs-TA and (b) in KPi electrolyte for ns-TA at an open circuit potential for $\text{WO}_3/(\text{Ga,W}):\text{BiVO}_4$ and $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga,W}):\text{BiVO}_4$ photoanodes.

Table 3 fs-TA analysis calculated parameters of dry film

	WO ₃ /(Ga,W):BiVO ₄		WO ₃ /S:Bi ₂ O ₃ /(Ga,W):BiVO ₄	
	A	τ (ps)	A	τ (ps)
τ ₁	1.06E-02	1.164	1.95E-03	1.947
τ ₂	5.50E-03	31.15	1.45E-03	60.45
τ ₃	2.96E-03	4640	1.35E-03	8233

Table 4 ns-TA analysis calculated parameters in operando.

	WO ₃ /(Ga,W):BiVO ₄			WO ₃ /S:Bi ₂ O ₃ /(Ga,W):BiVO ₄		
	A	τ (ns)	K _{TA} (ns ⁻¹)	A	τ (ns)	K _{TA} (ns ⁻¹)
τ ₁	0.43	2.5	0.4	0.35	1.1	0.909
τ ₂	0.38	43	0.023	0.37	36	0.0278
τ ₃	0.21	1300	0.0008	0.21	1100	0.0009
τ ₄	0.07	>100000	<0.00001	0.07	>100000	<0.00001

5.9 Energy band diagram

The primary electrons and holes separation and transfer pathways occurring among three oxides were shown in the band diagram (Figure 50). The CB edge was determined using flat-band potential, considering the negligible difference between the flat-band and bottom of the CB edge.¹⁷² It was assumed that the small amount of S would not significantly change the VBs and CBs position of Bi₂O₃, WO₃ and (Ga,W):BiVO₄ layers. Being the main absorber, BiVO₄ will absorb low energy photons ($\lambda \leq 530$), while WO₃ ($\lambda \leq 450$) and S:Bi₂O₃ ($\lambda \leq 430$) will absorb high energy photons. Due to the stepped alignment and the appropriate VBs and CBs configurations, electrons can readily transport from the CBs of

BiVO₄ into WO₃ via the S:Bi₂O₃ interfacial layer and the current collector.^{85,149} Simultaneously, photogenerated holes at WO₃ will transport to and be collected at (Ga,W):BiVO₄ through the interfacial S:Bi₂O₃ layer.

The time scales for charge separation and transport from TRPL, fs- and ns-TA analysis indicate that more holes are directed to the reactive surface on the *ps-ns* range in (Ga,W):BiVO₄. Subsequently, photogenerated electrons will transfer from S:Bi₂O₃ into WO₃ on a *ns-μs* time scale. Recombination of photoexcited free electrons in (Ga,W):BiVO₄ is reduced by being transferred into the CB of WO₃ via the S:Bi₂O₃ layer. Once in the WO₃, the electrons have a longer lifetime.¹⁴⁸ In this process S:Bi₂O₃ play a key role in facilitating rapid charge transfer initially to WO₃ to improve the photoactivity of WO₃/S:Bi₂O₃/(Ga,W):BiVO₄ photoanode. Furthermore, the backflow of charge carriers within the photoanode is reduced by the CBs and VBs energy barriers present among the WO₃, S:Bi₂O₃ and (Ga,W):BiVO₄ layers that suppress holes and electron backflow.^[33,34,35]

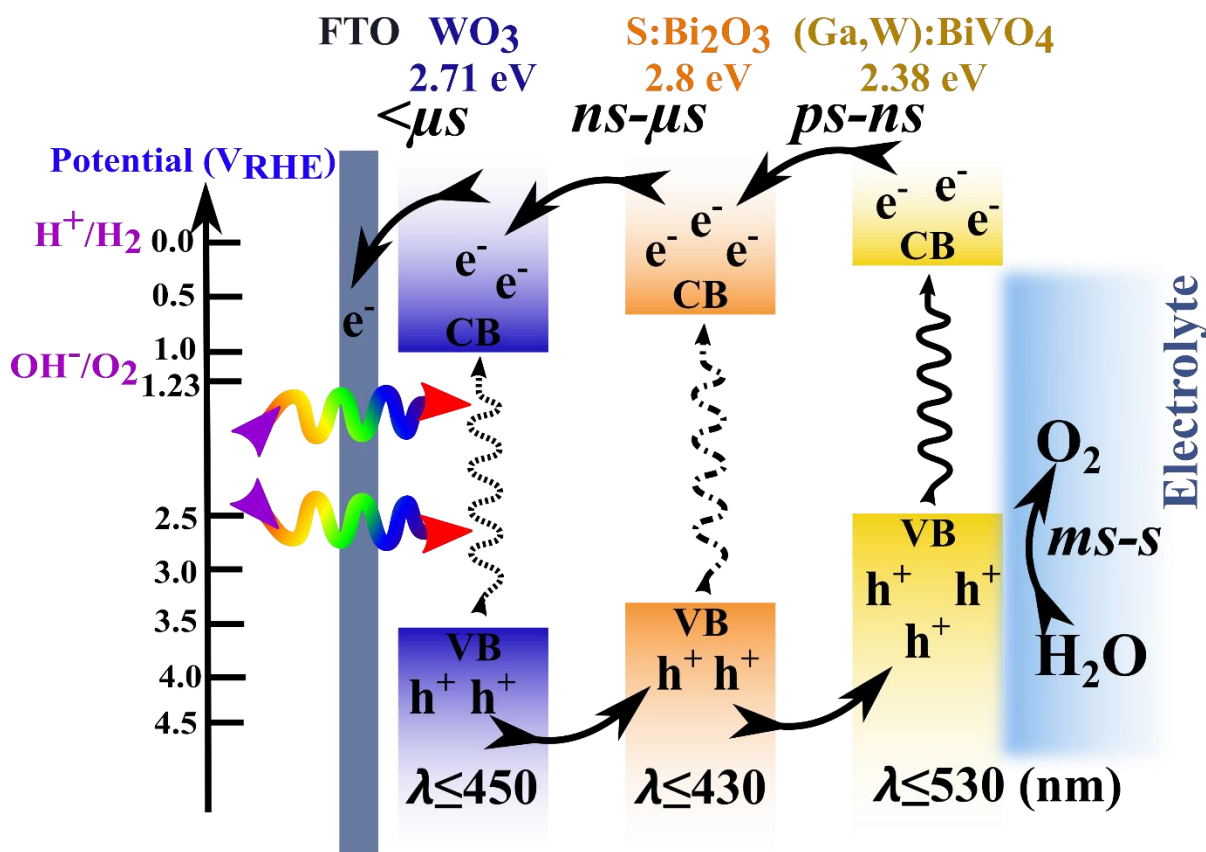


Figure 50 Schematic of band alignment for $\text{WO}_3/\text{S}:\text{Bi}_2\text{O}_3/(\text{Ga},\text{W}):\text{BiVO}_4$ heterojunction illustrating photoactivated charge generation, transfer process and related time scale.

5.10 Electrochemical stability and hydrogen measurement

As observed from Figure 51a, the photocurrent of all photoanodes decreases initially due to dominating photocorrosion of $(\text{Ga},\text{W}):\text{BiVO}_4$ from the loss of V^{5+} ions in the form of V_2O_5 . However, the photocurrent further ameliorates when V_2O_5 dissolution gets saturated¹⁷⁶ as it can be observed for $\text{WO}_3/(\text{Ga},\text{W}):\text{BiVO}_4$ photoanode, which could retain ~60% of the initial photocurrent. Further, the effect of interfacial layer Bi_2O_3 and $\text{S}:\text{Bi}_2\text{O}_3$

get more pronounced in ameliorating the charge dynamics and photocatalytic performance for $\text{WO}_3/\text{Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$ and $\text{WO}_3/\text{S:Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$ photoanodes by retaining ~80 and ~85 % of the initial photocurrent. Consequently, adding a protective layer Co-Pi demonstrate self-healing nature and $\text{WO}_3/\text{S:Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4/\text{Co-Pi}$ photoanode performance improve by retaining 90% of the photocurrent density compared to ~85% for $\text{WO}_3/\text{S:Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4$ photoanode after 10 h.⁸⁵ The repeatability of photoanodes after stability measurement demonstrated no significant change in the photocurrent onset and PCD at 1.23 V_{RHE} . The amount of H_2 and O_2 gases generated was measured to verify the faradaic efficiency of each water splitting half-reaction. The measurement was performed for the $\text{WO}_3/\text{S:Bi}_2\text{O}_3/(\text{Ga,W})\text{:BiVO}_4/\text{Co-Pi}$ photoanode at 1.23 V_{RHE} under simulated AM 1.5G illumination in KPi electrolyte. Figure 51b shows the H_2 and O_2 gas generation rate (67.3 and 33.6 $\mu\text{mol}\cdot\text{h}^{-1}\text{cm}^{-2}$, respectively) along with the theoretical production rate and the corresponding faradaic efficiency (secondary Y-axis in Figure 51b) values (91.5 and 88%, respectively) The slightly lower values of faradaic efficiency are attributed to inhibition of proton reduction, diffusion of H_2 gases, and potential back reactions at counter electrode from dissolved O_2 .^[22,23]

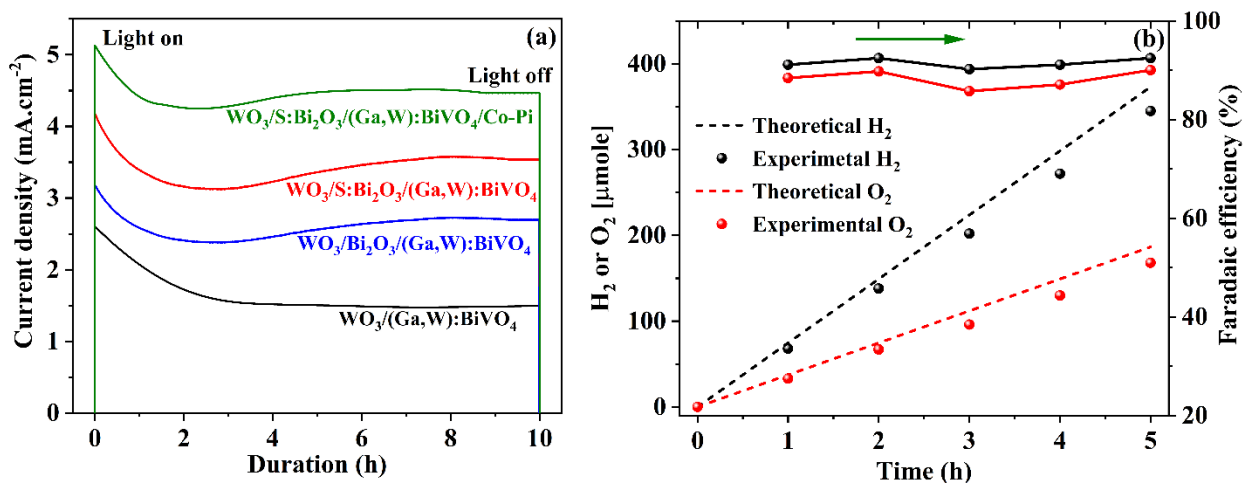


Figure 51 (a) Photoelectrochemical stability measurements of photoanodes with WO₃ heterojunction and Bi₂O₃ interface layer without and with sulfur modification. (b) Evolution of H₂ and O₂ gases for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄/Co-Pi photoanode. *The measurements were conducted at 1.23 V_{RHE} in KPi electrolyte under simulated AM 1.5G illumination.*

5.11 Conclusion

The performance of photoanodes containing a WO₃/BiVO₄ heterojunction is limited, in part, by charge separation, transfer and recombination across the heterojunction interface. To mitigate these losses, sulfur modified Bi₂O₃ interfacial layer was introduced between WO₃ and BiVO₄ layers. The BiVO₄ layer was optimized with co-doping at Bi³⁺ and V⁵⁺ sites by Ga³⁺ and W⁶⁺, respectively, to improve the light absorption and photogenerated charge carrier extraction. The S:Bi₂O₃ layer between WO₃ and (Ga,W):BiVO₄ and Co-Pi co-catalyst led to achieving 5.1±0.25 mA.cm⁻² and 67.3 μmol.h⁻¹cm⁻² photocurrent density and hydrogen collection rate for WO₃/S:Bi₂O₃/(Ga,W):BiVO₄/Co-Pi photoanode. EDAX, XPS and TOF-SIMS depth profiling corroborated the uniform diffusion of S in all layers, whereas EIS and TRPL confirmed the enhanced interfacial charge transfer kinetics. Subsequently, *operando* fs- and ns-TA analysis concluded that more long-lived

photogenerated charge carriers remain after adding S:Bi₂O₃ interfacial layer, providing more holes directed to the reactive surface due to effective charge separation/transfer and improved the overall photoanode performance. As a result, the photocurrent density and hydrogen production rates are among the highest reported for interlayer enhanced WO₃/BiVO₄ heterojunction photoanodes.

CHAPTER 6 SUMMARY AND OUTLOOK

Non-renewable hydrogen production methods can serve as a temporary supply for the hydrogen economy, various renewable strategies are being developed to enable hydrogen production, which is predictable to be comprehended as soon as possible before permanent damage is done onto the environment by a fossil fuel-based system. It is estimated that the low cost, environmentally friendly photocatalytic water splitting is a contemporary approach for hydrogen production. It will play a vital role in hydrogen production and contribute much to the coming hydrogen economy. Overall, hydrogen generation through solar pathways is an ideal and long-term approach for producing green energy, but the involved process is complex and requires a highly efficient system to achieve decent solar to hydrogen efficiency.

The photoelectrochemical method is a promising solar pathway for hydrogen production. The scheelite monoclinic structure of BiVO_4 was selected as one of the most suitable photoanode materials for the photoelectrochemical water splitting producing green H_2 due to its crystal and electronic structures. However, being a limited light absorber, BiVO_4 faces various challenges such as positive CB position, substantial electron-hole recombination, and the poorly catalytic properties towards O_2 evolution. To address these challenges, various methods such as synthesis/fabrication methods, doping with metal and non-metal, heterojunction formation with metal oxide and OER surface catalysts have been discussed in detail. Additional improvements include reducing excessive recombination at the surface by generating efficient physical charge separation by compositional tuning,

coupling with efficient semiconductor material for heterojunction formation and efficient oxygen evolution catalyst for transferring almost 100% holes to the reactant surface. Increasing light absorption without simultaneously generating trap sites is another challenge that needs to be addressed. Notably, factors such as electronic properties, chemical composition, structure, crystallinity, surface states and morphology of catalysts need to be carefully considered to tune and determine their photocatalytic activity for drastically improving hydrogen production efficiency in practical applications. This dissertation discussed the four major approaches to enhance the charge dynamics.

Thin films were prepared by ultrasonic spray coating and atmospheric pressure chemical vapor deposition (ALCVD). First, the alkali metal was placed in the crystal structure of BiVO_4 and extended light absorption for Li:BiVO_4 and Na:BiVO_4 compared to K:BiVO_4 and pristine BiVO_4 . The XRD and Raman results indicated that alkali metal occupied the interstitial position of the BiVO_4 lattice structure. The diffusion length of charge particles was measured by implementing a positron at the surface of the thin films and found that the diffusion length of the positron increased by ~ 4 times in Na:BiVO_4 and Li:BiVO_4 compared to that of the pristine. It was also observed that the Bi and V based defect density was minimum on alkali metal placement in the BiVO_4 crystal structure. The *ab initio* DFT calculations confirmed that the Li and Na doping in the BiVO_4 interstitial site was energetically the most favorable position. It was evident that oxygen atoms formed weak bonds with Li and Na atoms, and multiple interbands formed between conduction and valence band, leading to more interactions and a small reduction in the bandgap in improving charge dynamics Na:BiVO_4 and Li:BiVO_4 .

Second, the doping of the rare earth metal ions Y^{3+} Er^{3+} or Yb^{3+} at Bi^{3+} and W^{6+} doped at V^{5+} site to enhances light absorption ($\lambda \leq 550$) due to reduction in bandgap and increased charge transport property compared to intrinsic $BiVO_4$ photoanode. The third approach introduced junction formation to enhance the light harnessing in the wide spectrum. Type II heterojunction with WO_3 and $p-n$ junction form with $Fe:NiO$ for efficient electron transfer and enhancing charge dynamics. The $WO_3/(Y,W):BiVO_4/Fe:NiO$ photoanode with type two heterojunction and the $p-n$ junction with $Fe:NiO$ demonstrated near-complete (~95 %) suppression of electrons and holes recombination, efficient charge transfer (~75 %) and improved absorption efficiency (~85 %). Due to the $p-n$ junction formed between the interface of $WO_3/(Y,W):BiVO_4$ or $WO_3/(Er,W):BiVO_4$ with $Fe-NiO$, an inner electric field is built, enhancing the surface reaction kinetics (transportation of electron-hole pairs), lowering the band bending conditions, and increasing the bulk charge separation. Thus, rare earth metal Y or Er or Yb doing along with W in $BiVO_4$ enhances light absorption but leads to decreased bulk and surface charge transport property and this limitation can be overcome by using a suitable electron/hole transfer layer.

Finally, it was detected that the performance of photoanodes containing a $WO_3/BiVO_4$ heterojunction is limited, in part, by charge separation, transfer and recombination across the heterojunction interface. To mitigate these losses, sulfur modified Bi_2O_3 interfacial layer was introduced between WO_3 and $BiVO_4$ layers. The $BiVO_4$ layer was optimized with dual co-doping to improve the light absorption and photogenerated charge carrier extraction. The $S:Bi_2O_3$ layer between WO_3 and $(Ga,W):BiVO_4$ and $Co-Pi$ co-catalyst led to achieving $5.1 \pm 0.25 \text{ mA.cm}^{-2}$ and $67.3 \text{ } \mu\text{mol.h}^{-1}\text{cm}^{-2}$ photocurrent density and hydrogen collection rate for $WO_3/S:Bi_2O_3/(Ga,W):BiVO_4/Co-Pi$ photoanode. EDAX, XPS and TOF-

SIMS depth profiling corroborated the uniform diffusion of S in all layers, whereas EIS and TRPL confirmed the enhanced interfacial charge transfer kinetics. Subsequently, *operando* fs- and ns-TA analysis concluded that more long-lived photogenerated charge carriers remain after adding S:Bi₂O₃ interfacial layer, providing more holes directed to the reactive surface due to effective charge separation/transfer and improved the overall photoanode performance. The photocurrent density and hydrogen production rates are the highest reported for interlayer enhanced WO₃/BiVO₄ heterojunction photoanodes.

Unquestionably, the charge kinetics of photocatalysts is a complex phenomenon as it involves multiple steps and mechanisms. While the existing mechanisms are proposed primarily based on the theories and the experimental data derived from several state-of-the-art characterization techniques, an in-depth understanding of charge kinetics is often constrained by the limitations of the characterization techniques and real-life experimental conditions. State-of-the-art characterization techniques with high spatial, temporal and spectral resolutions are essential for *in situ* and direct observations of charge kinetics concerning the morphological, compositional, electronic changes and charge dynamics of a photocatalyst. Subsequently, given the multidisciplinary field, integrating materials science, electrochemistry, physical chemistry and surface science, the collaboration between researchers across multiple disciplines is required to understand the system for developing a new and effective photocatalytic process. Till now, the highest reproducible STH energy conversion efficiency value achieved using the particulate photocatalytic system is far lower than values obtained with photovoltaic-electrolysis systems and photoelectrochemical devices.^{72,72,182} Considering the simple construction of industrial-scale solar hydrogen production facilities based on particulate photocatalytic overall water

splitting systems, an STH energy conversion efficiency of $\sim 5 - 8 \%$ will be a decent starting point for practical applications. Therefore, improving the efficiency of present-day narrow bandgap photocatalysts and developing novel nanostructured active materials capable of harnessing red or near-infrared light are still the prime challenges. Based on the research discussed in this thesis and photocurrent summarized in the Table 5, all the implemented methods are well characterized and validated. However, the developed sulfur modified interfacial layer is the most suitable and recommended strategy to improve the photocatalytic efficiency of BiVO_4 . The comprehensive refinement of photocatalyst materials to accentuate surface properties and fine-tuning reaction conditions is also necessary.^{72,183} Moreover, ongoing investigations regarding restricted systems will be required. In general, attempts inspired from a wide range of scientific areas will be highly desired to allow future innovations in the advancement of overall water splitting efficiency to recognize the ‘‘Holy Grail’’ of artificial photosynthesis soon as possible.^{155,177}

Table 5 Photoanodes and respective photocurrent at $1.23 \text{ V}_{\text{RHE}}$ under 1 sun illumination.

Strategy	Photoanodes	Photocurrent at $1.23 \text{ V}_{\text{RHE}}$ ($\text{mA} \cdot \text{cm}^{-2}$)
Alkali metal doping	BiVO_4	0.2 ± 0.01
	$\text{K}:\text{BiVO}_4$	0.7 ± 0.02
	$\text{Na}:\text{BiVO}_4$	1.75 ± 0.09
	$\text{Li}:\text{BiVO}_4$	2.2 ± 0.1
W doping at V^{5+} site	$\text{Bi}_{0.987}\text{V}_{0.992}\text{W}_{0.013}\text{O}_4$	1.2 ± 0.08
	$\text{BiV}_{0.97}\text{W}_{0.013}\text{O}_4$	1.9 ± 0.1
	$\text{BiV}_{0.992}\text{W}_{0.013}\text{O}_4$	2.4 ± 0.12
Rare earth metal doping at Bi^{3+} site	$\text{Yb}:\text{BiVO}_4$	0.3 ± 0.02
	$\text{Ga}:\text{BiVO}_4$	0.25 ± 0.01

	Er:BiVO ₄	0.4 ± 0.02
	Y:BiVO ₄	0.6 ± 0.02
Dual doping at Bi ³⁺ and V ⁵⁺ sites	(Yb,W):BiVO ₄	1.9 ± 0.1
	(Ga,W):BiVO ₄	1.8 ± 0.1
	(Er,W):BiVO ₄	2.3 ± 0.12
	(Y,b):BiVO ₄	2.6 ± 0.12
Heterojunction formation with WO ₃	WO ₃ /(Yb,W):BiVO ₄	4.5 ± 0.2
	WO ₃ /(Er,W):BiVO ₄	4.3 ± 0.2
	WO ₃ /(Y,b):BiVO ₄	2.6 ± 0.12
<i>p-n</i> junction formation	WO ₃ /(Er,W):BiVO ₄ /Fe:NiO	5.6 ± 0.2
	WO ₃ /(Y,b):BiVO ₄ /Fe:NiO	5.8 ± 0.3
Interfacial layer S:Bi ₂ O ₃	WO ₃ /(Ga,W):BiVO ₄	2.4 ± 0.12
	WO ₃ /Bi ₂ O ₃ /(Ga,W):BiVO ₄	3.2 ± 0.2
	WO ₃ /S:Bi ₂ O ₃ /(Ga,W):BiVO ₄	4.2 ± 0.2

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